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(54) **HEAD-MOUNTED MATRIX DISPLAY**

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ation of application No. 08/220,042, filed on Mar. 30, 1994, now abandoned, which is a continuation-in-part of application No. 08/141,133, filed on Oct. 22, 1993, now abandoned.

Publication Classification

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(52) **U.S. Cl. 345/8**

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(57) **ABSTRACT**

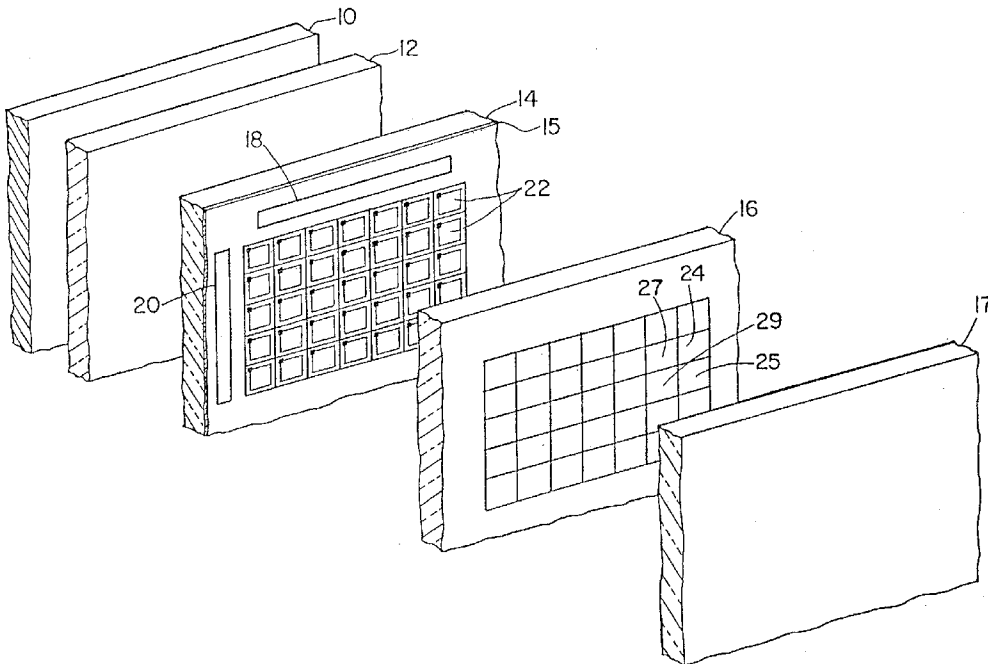
(21) Appl. No.: **09/119,274**

(22) Filed: **Jul. 20, 1998**

A compact, light weight head mounted display in which a pair of matrix display elements are mounted within a housing. The display utilizes a pair of arms or stems that are rotatable mounted to the housing such that the user can pivot each arm from a folded position into an open position. The arms can be spring mounted onto the housing to secure the display to the user's head and can also incorporate ear-phones that can be retracted into each arm when not in use.

Related U.S. Application Data

(63) Continuation of application No. 08/579,448, filed on Dec. 27, 1995, now abandoned, which is a continu-



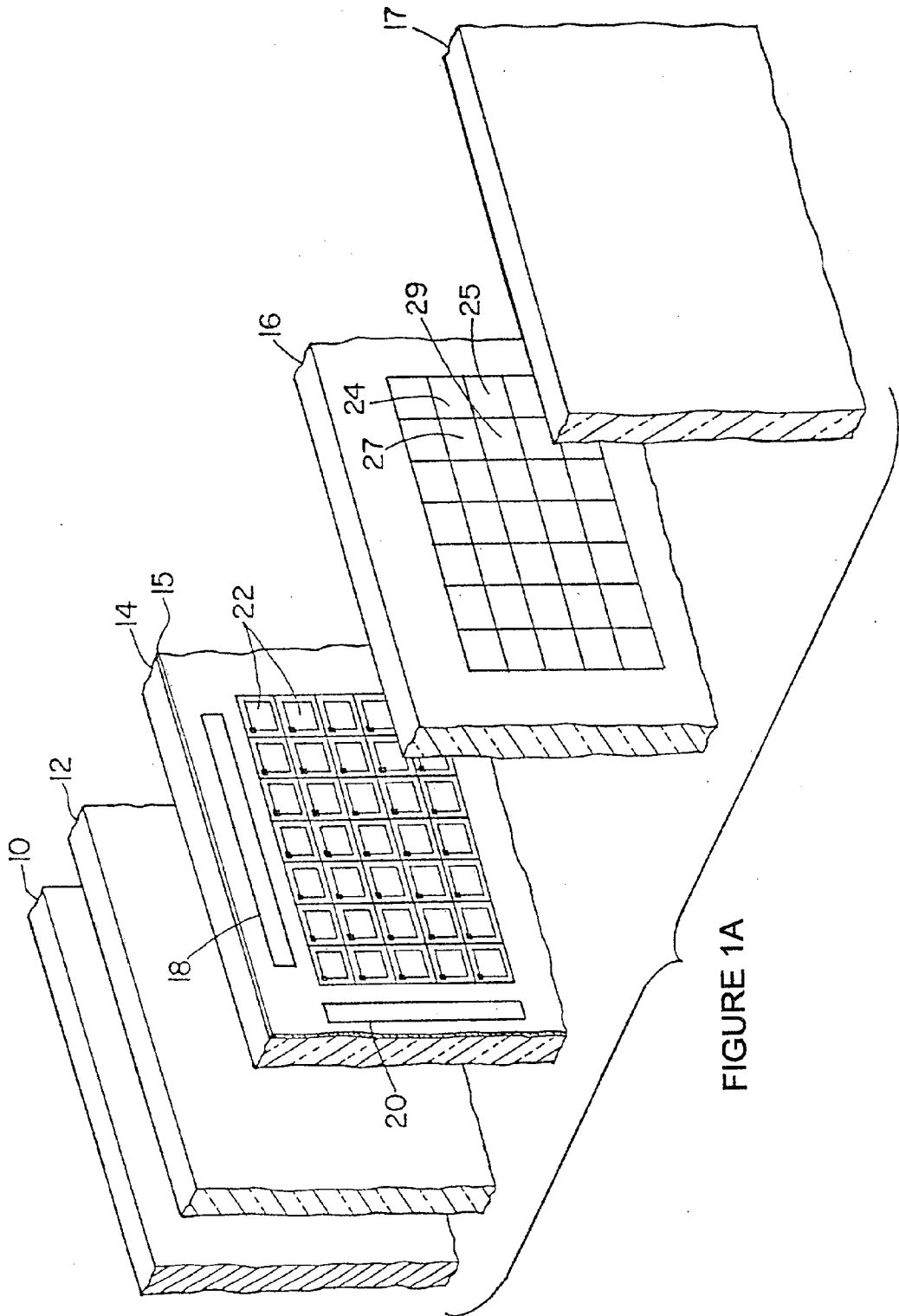
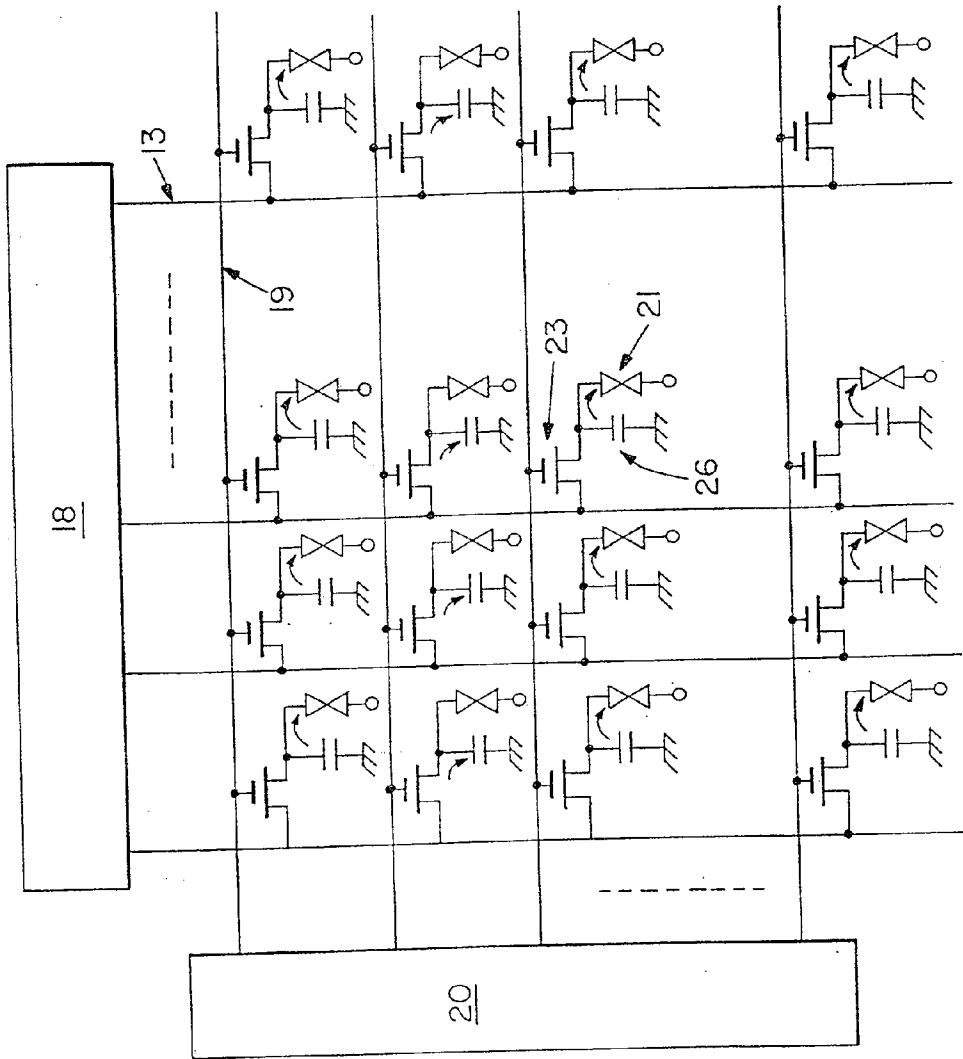


FIGURE 1B



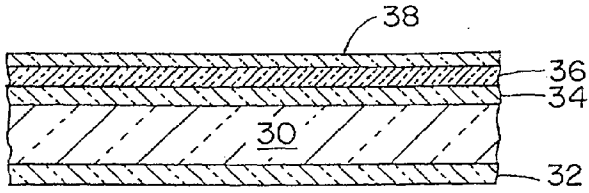


FIGURE 2A

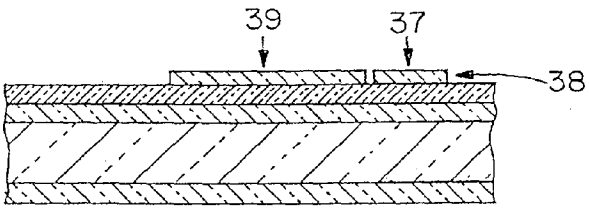


FIGURE 2B

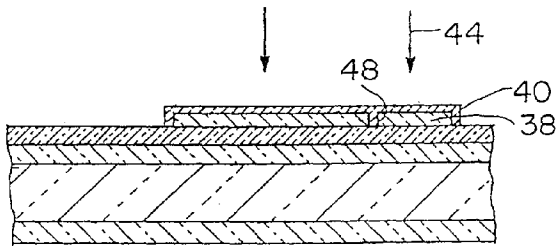


FIGURE 2C

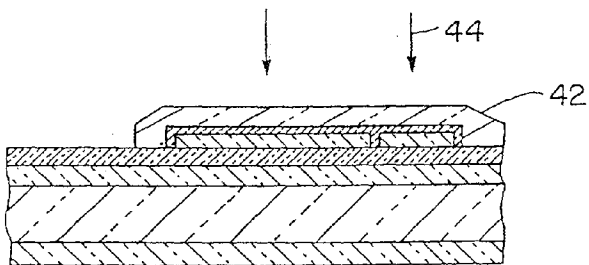


FIGURE 2D

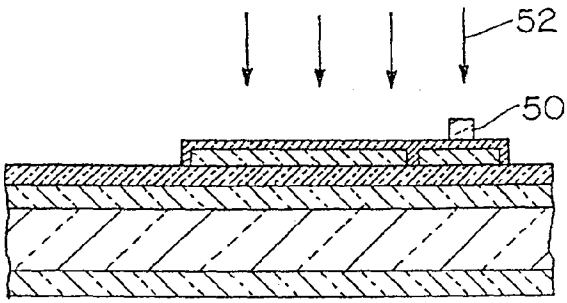


FIGURE 2E

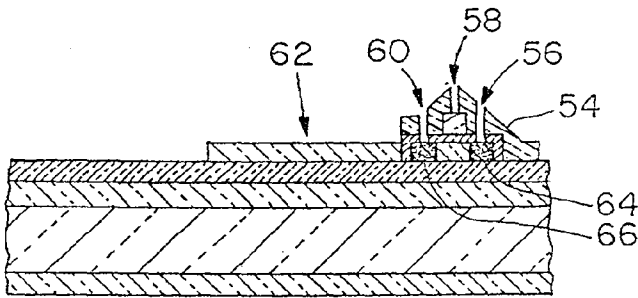


FIGURE 2F

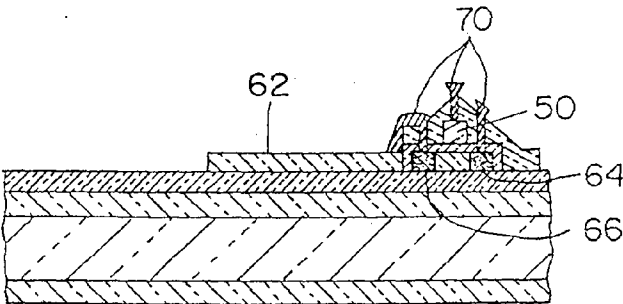


FIGURE 2G

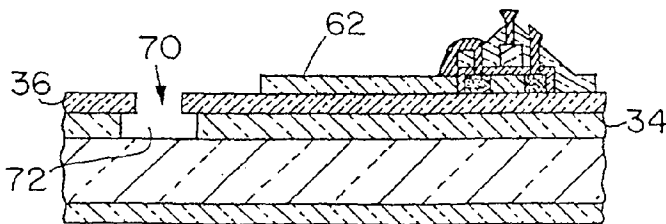


FIGURE 2H

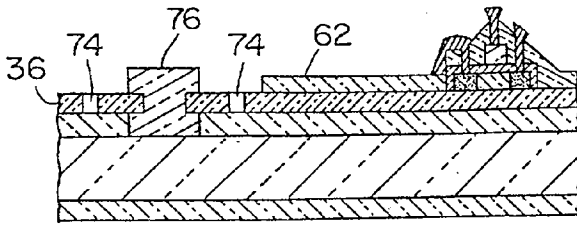


FIGURE 2I

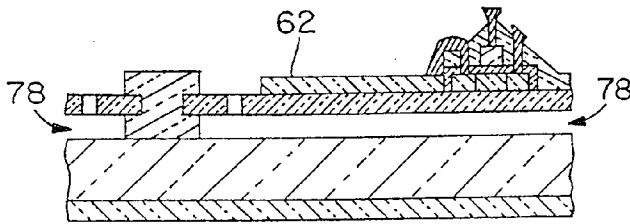


FIGURE 2J

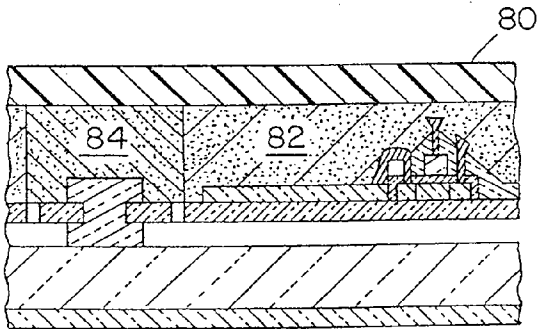


FIGURE 2K

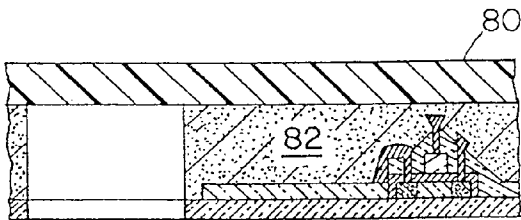


FIGURE 2L

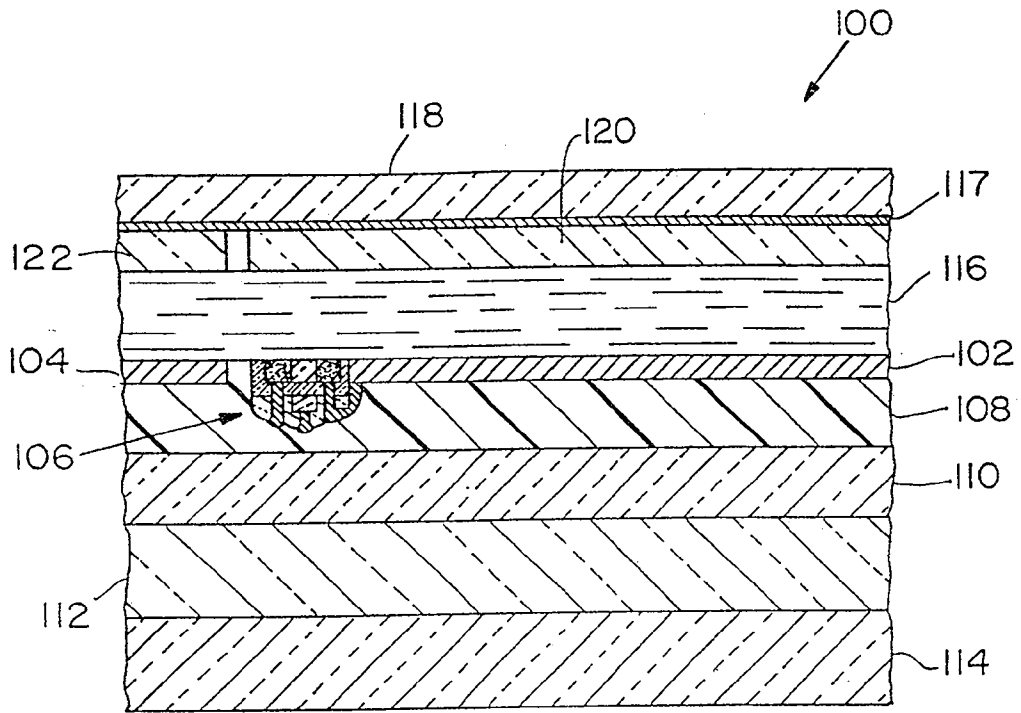


FIGURE 3

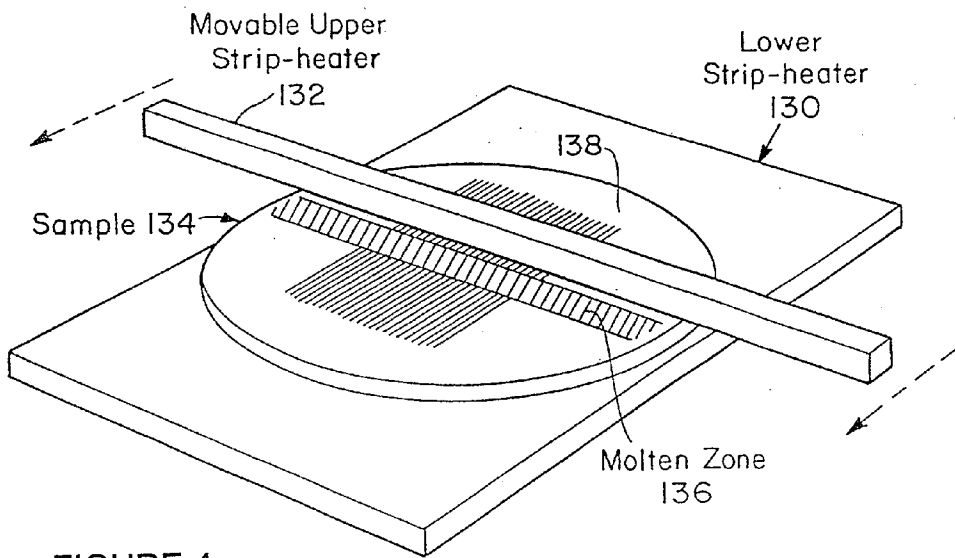


FIGURE 4

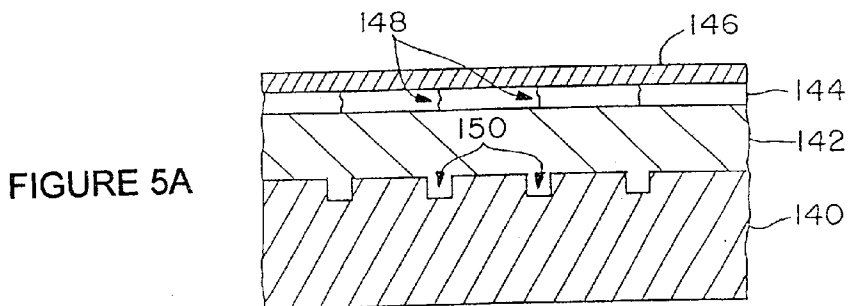


FIGURE 5A

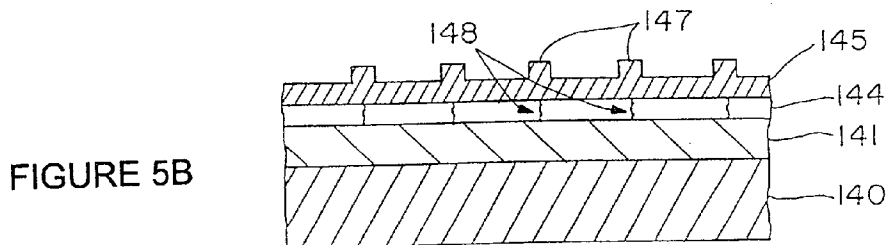


FIGURE 5B

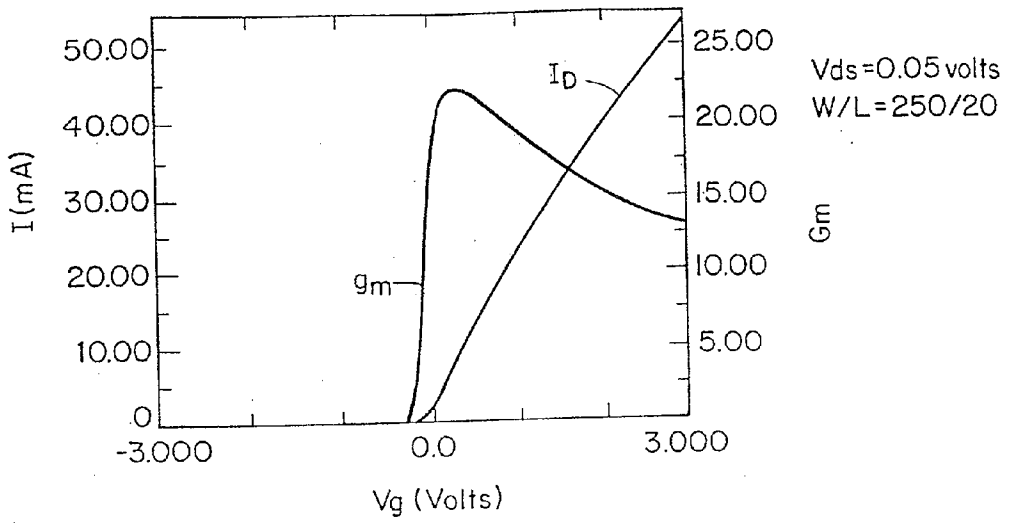


FIGURE 6A

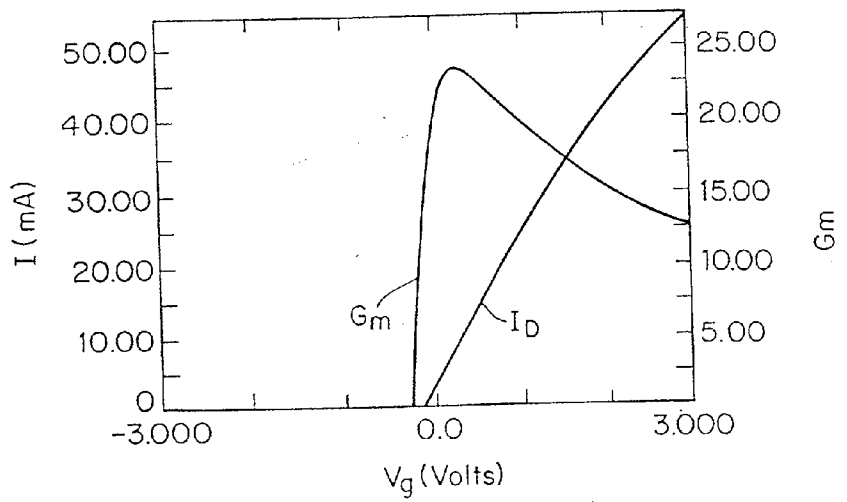
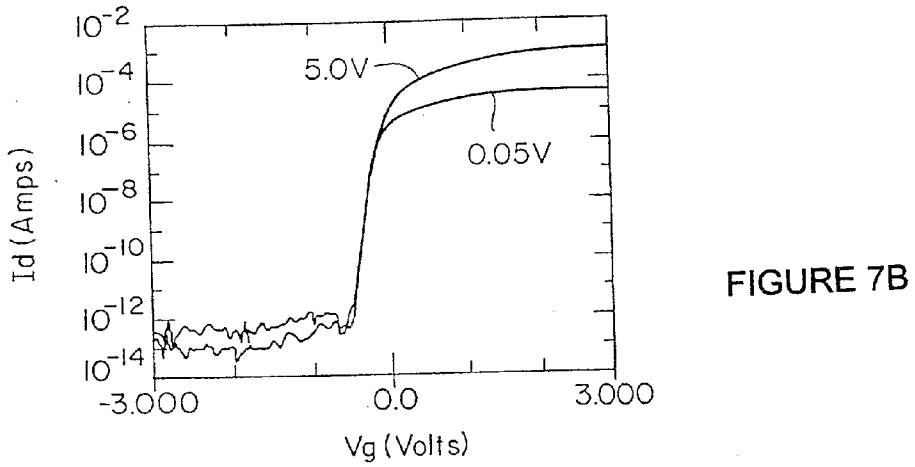
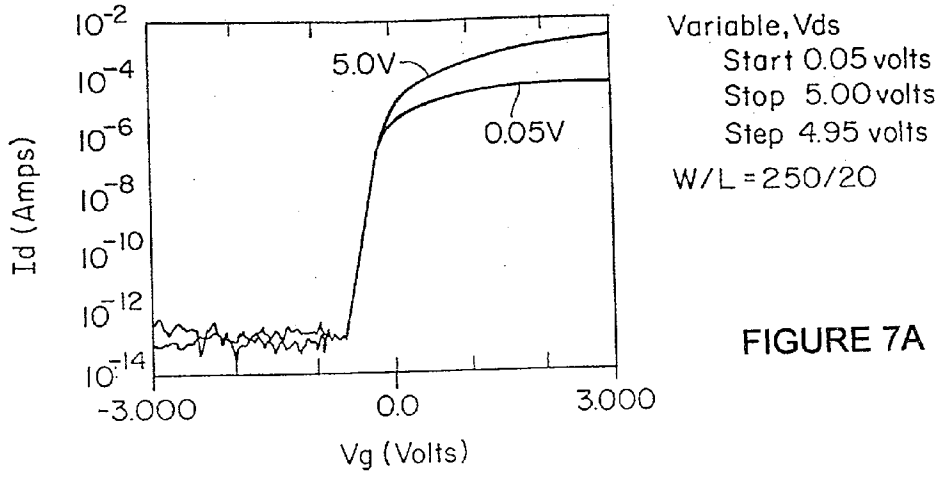


FIGURE 6B



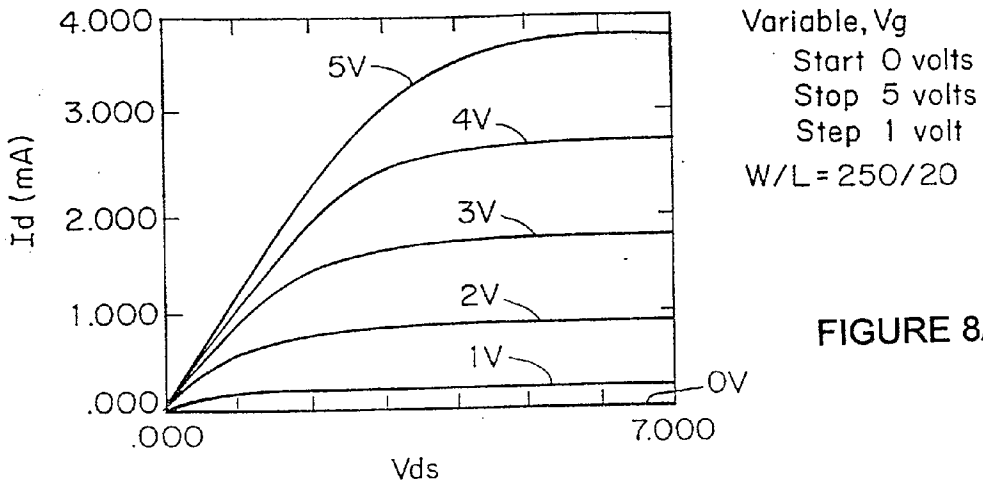


FIGURE 8A

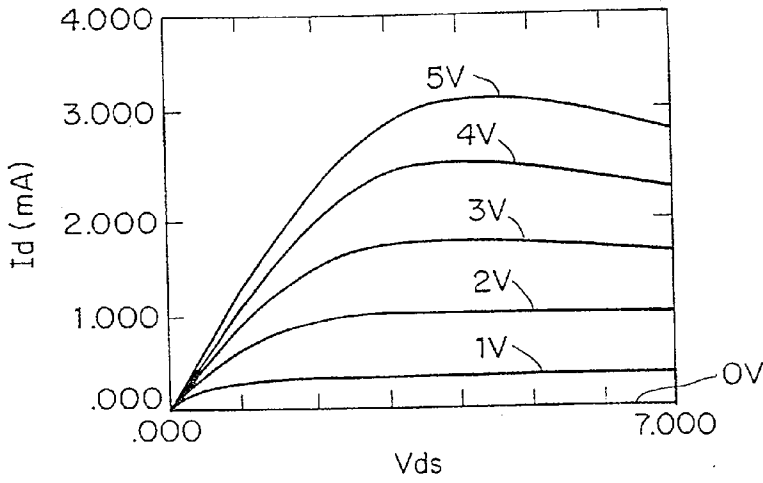


FIGURE 8B

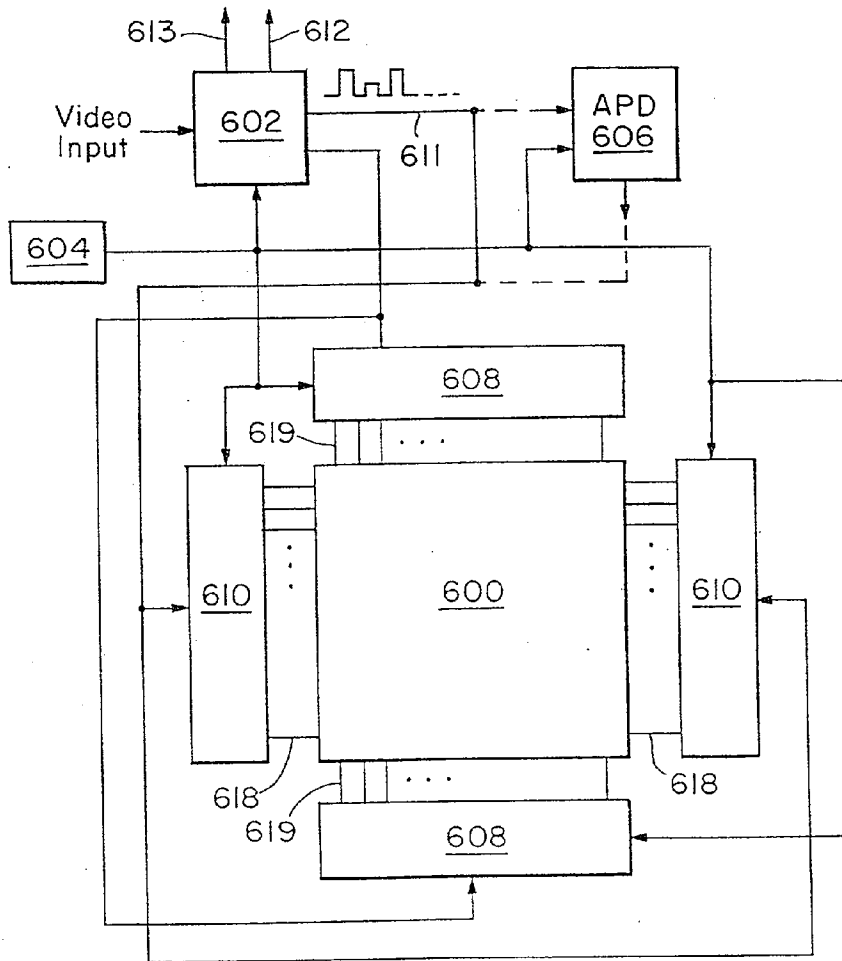
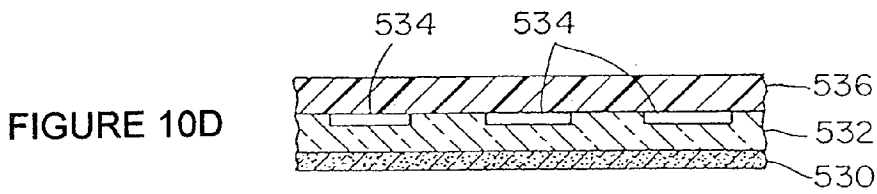
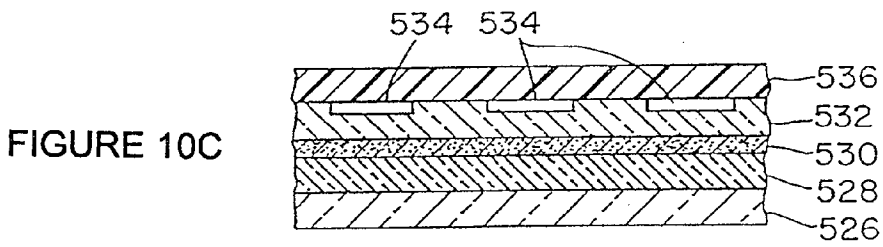
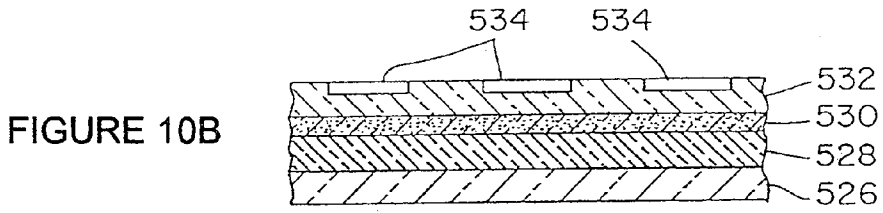
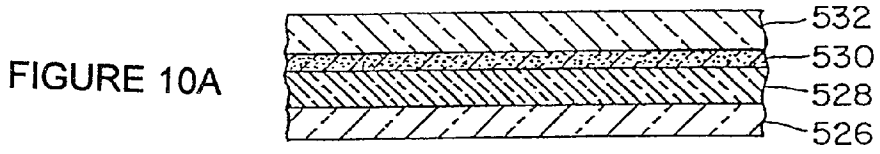
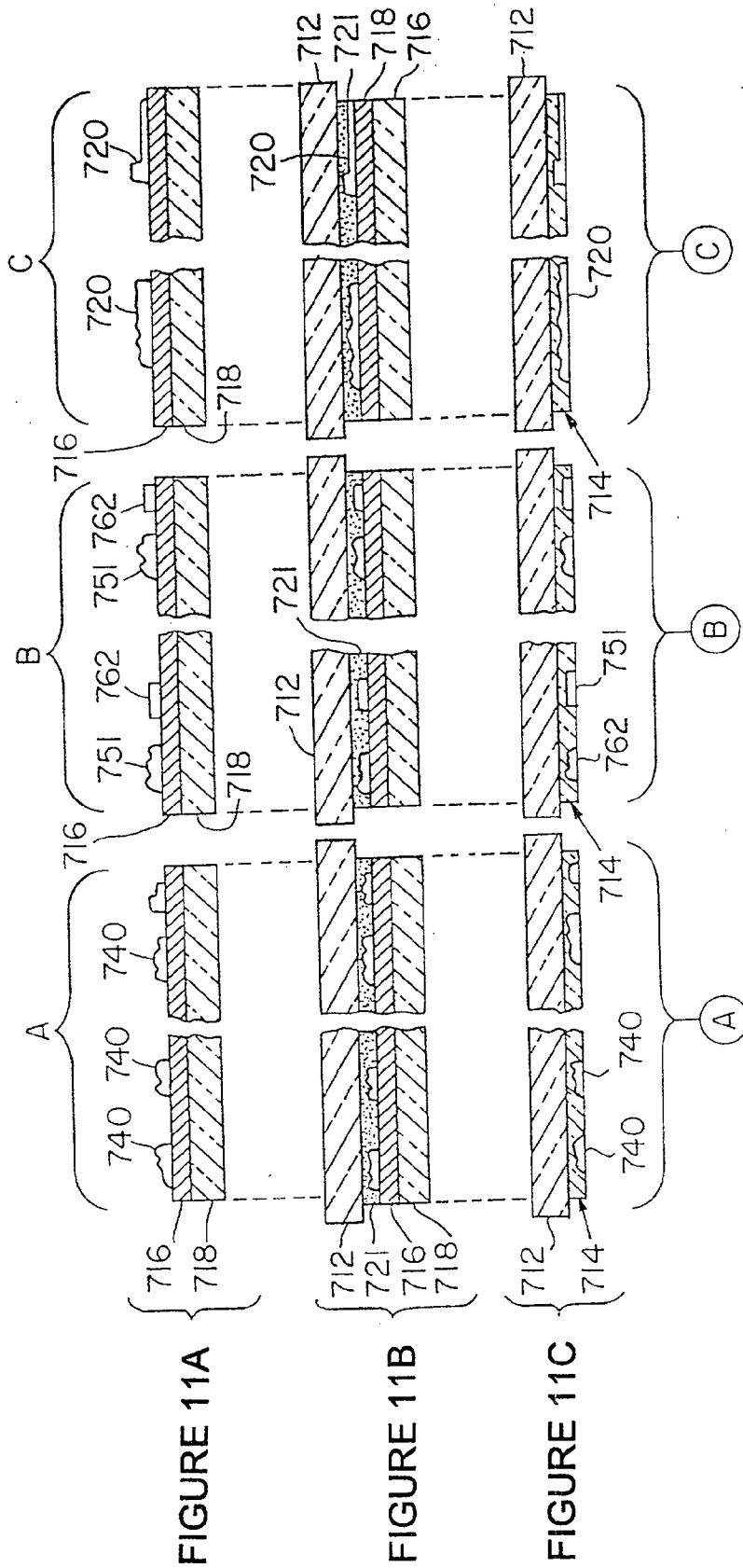


FIGURE 9





CROSS-SECTIONAL VIEW

TOP VIEW

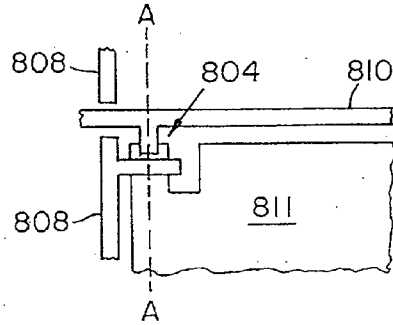
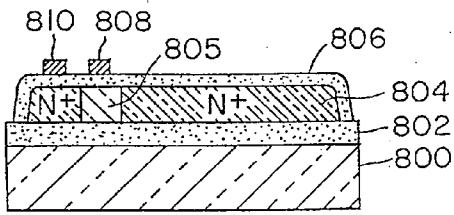


FIGURE 12A

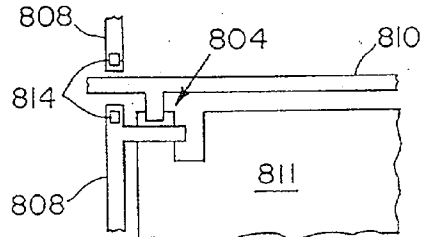
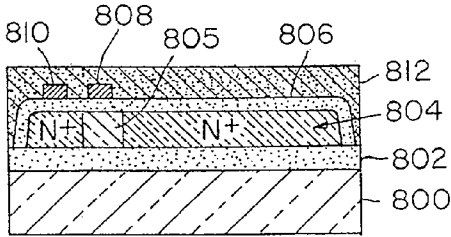


FIGURE 12B

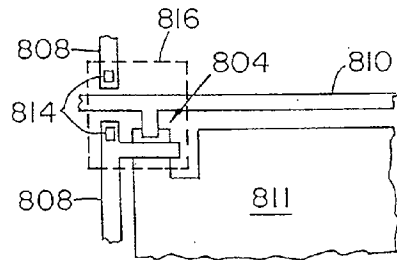
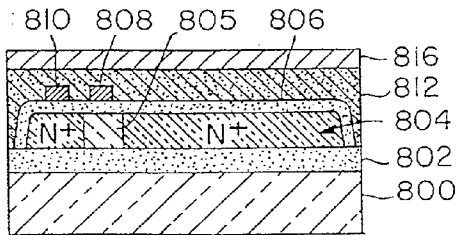


FIGURE 12C

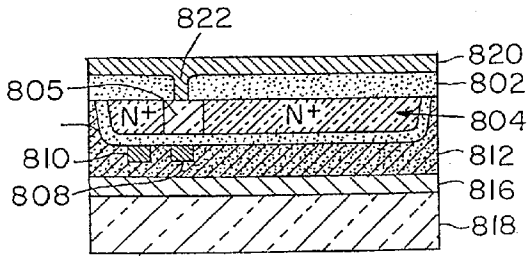


FIGURE 12D

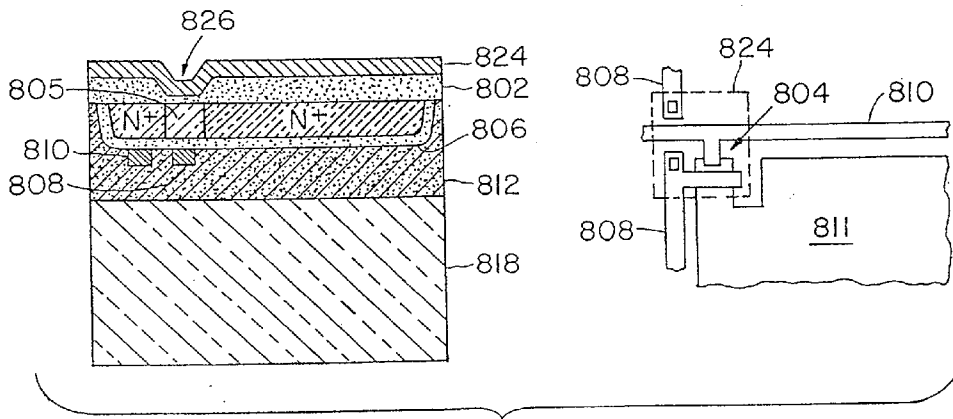


FIGURE 12E

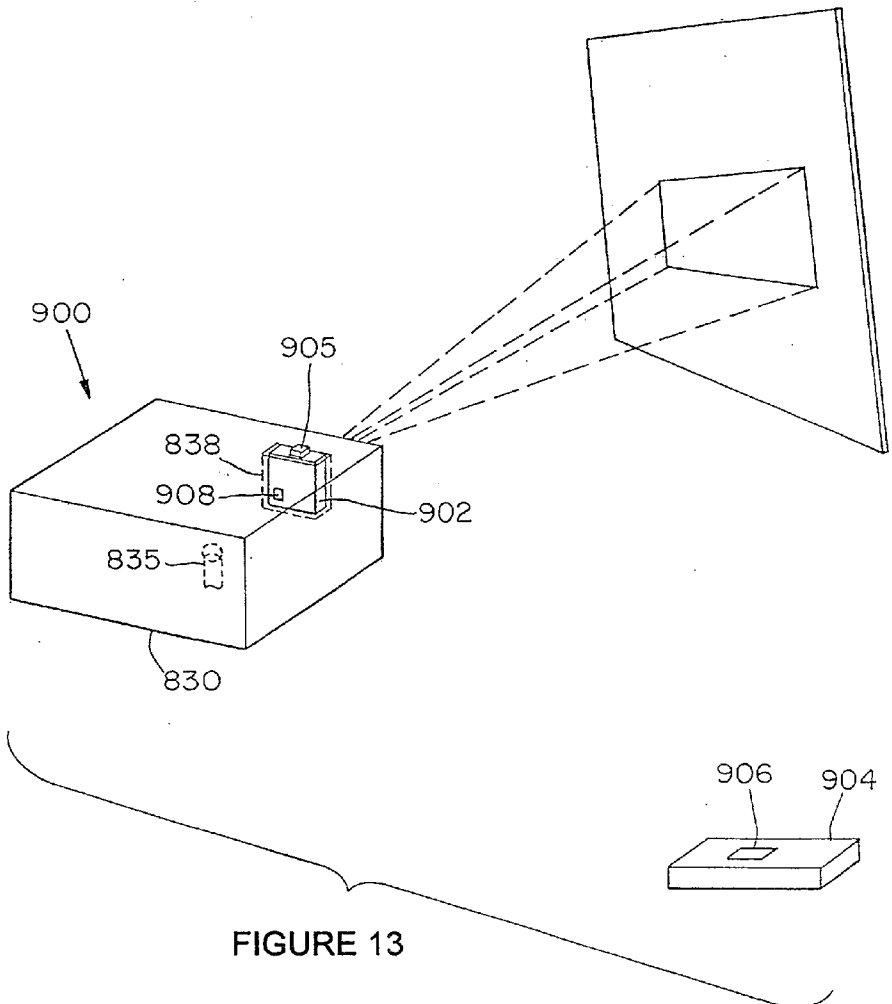


FIGURE 13

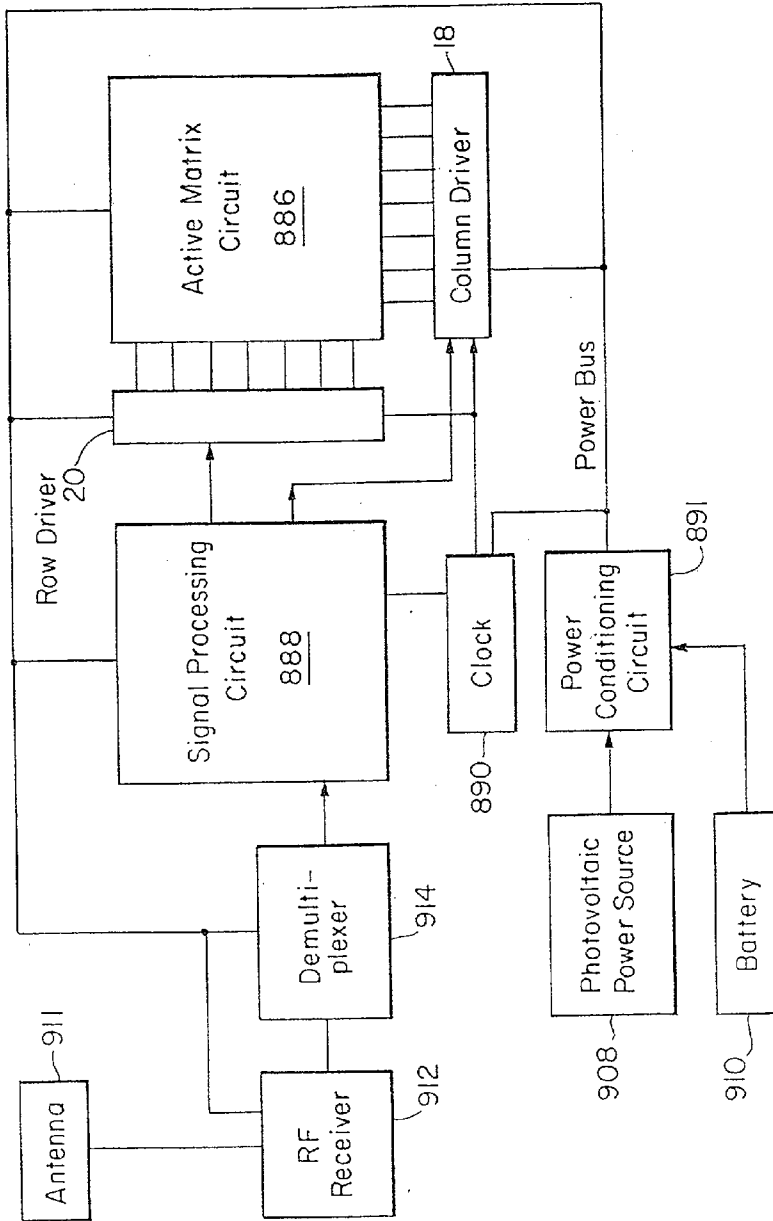


FIGURE 14

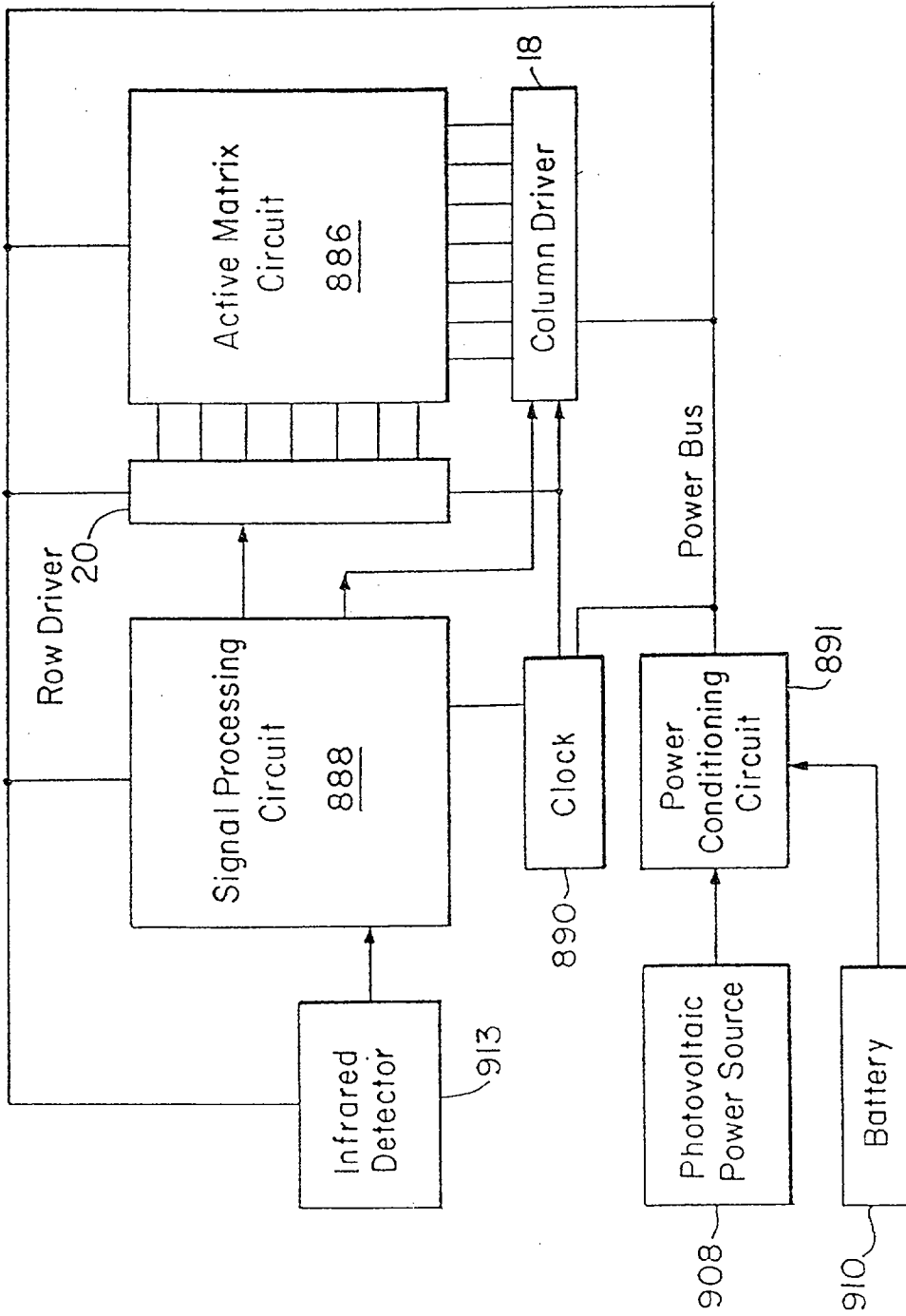


FIGURE 15

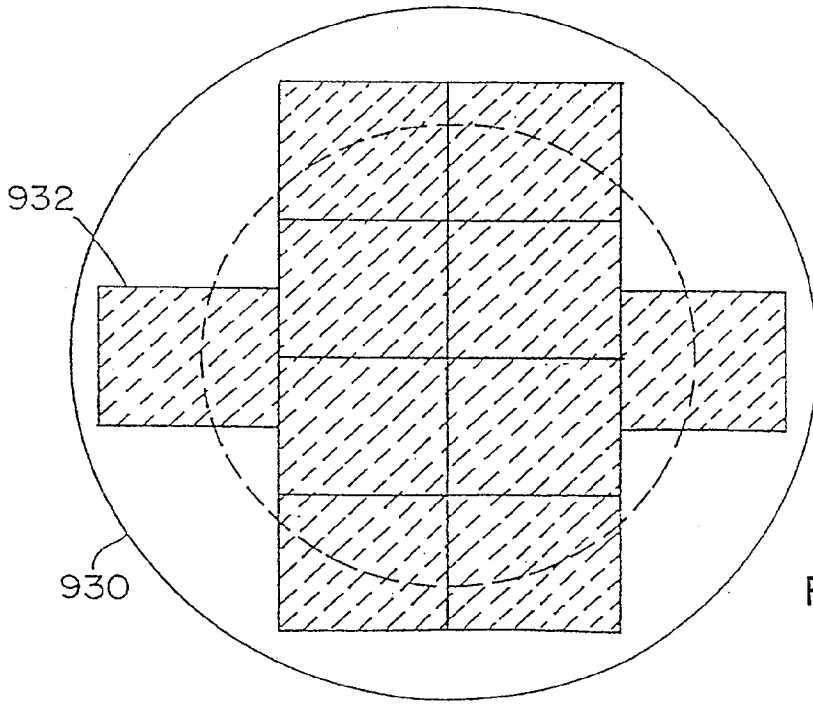


FIGURE 16

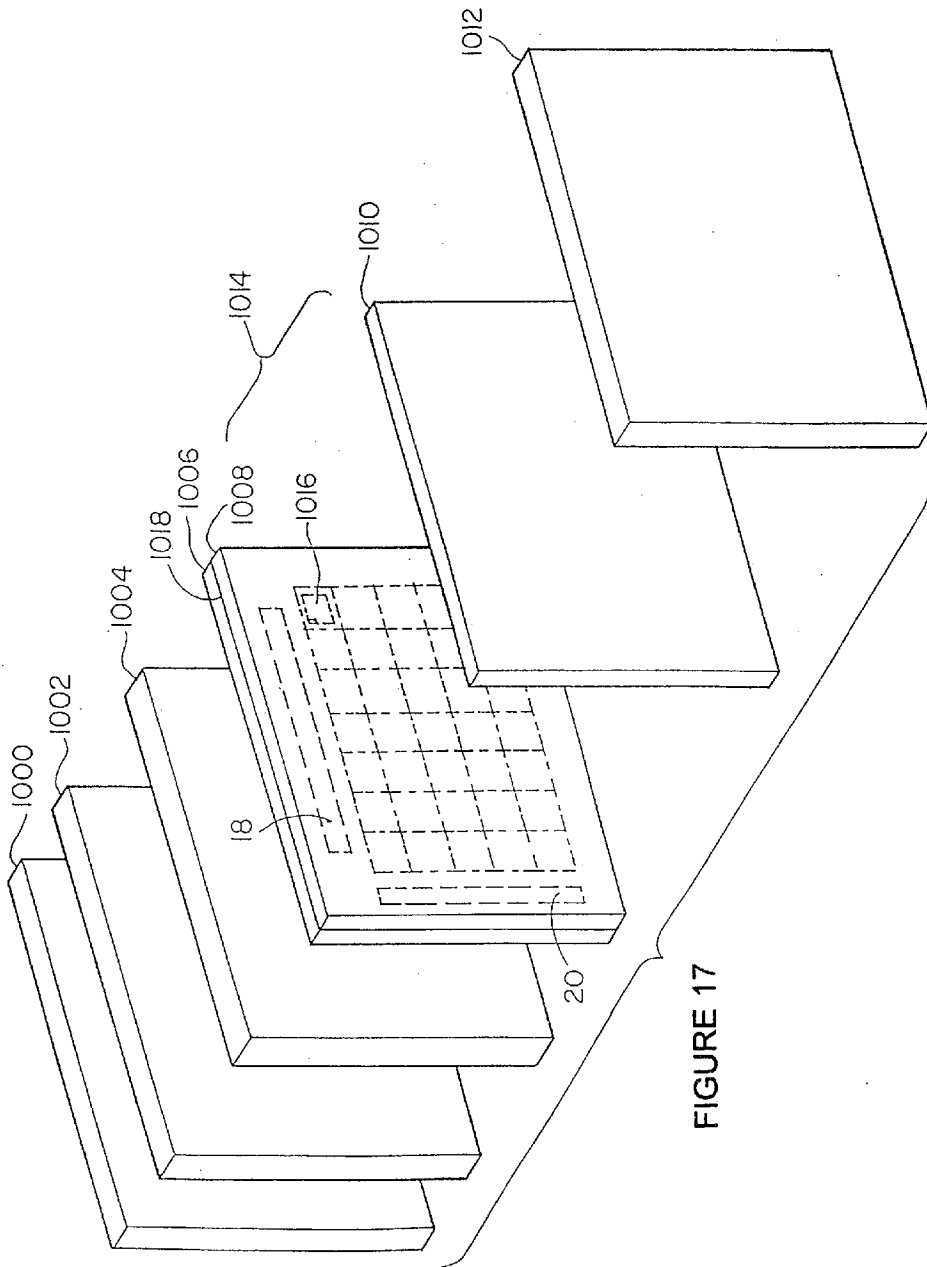


FIGURE 17

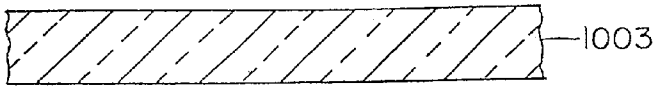


FIGURE 18A

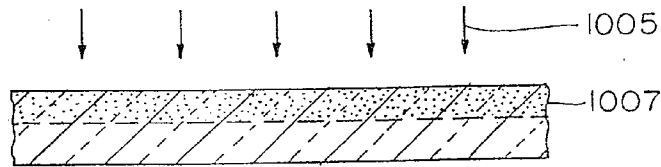


FIGURE 18B

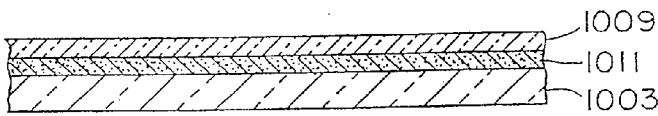


FIGURE 18C

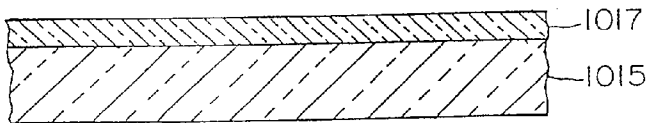


FIGURE 19

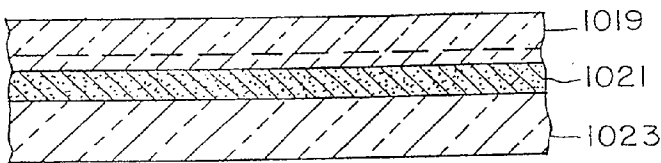


FIGURE 20A

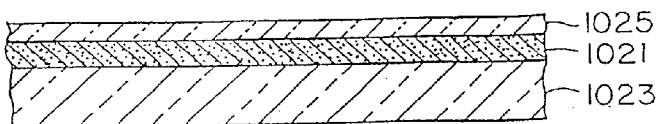


FIGURE 20B

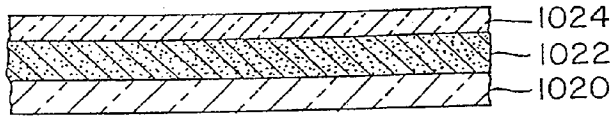


FIGURE 21A

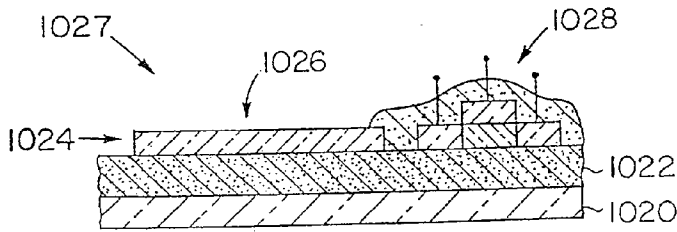


FIGURE 21B

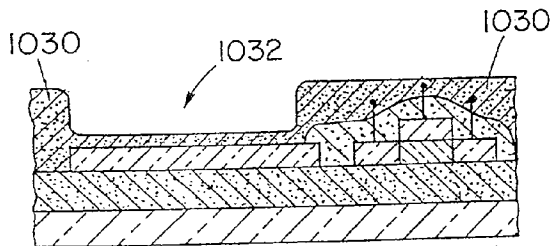


FIGURE 21C

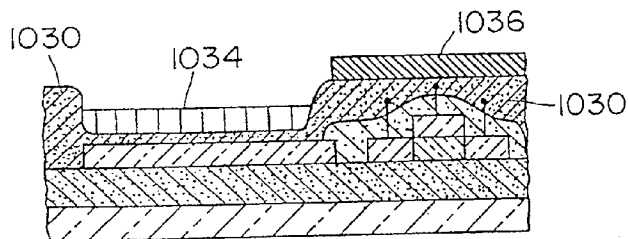


FIGURE 21D

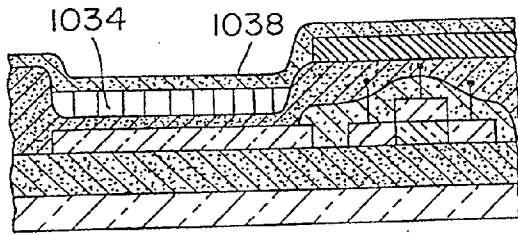


FIGURE 21E

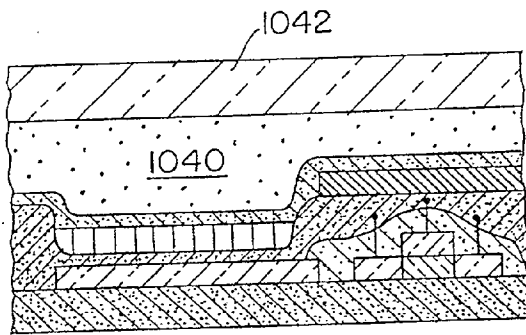


FIGURE 21F

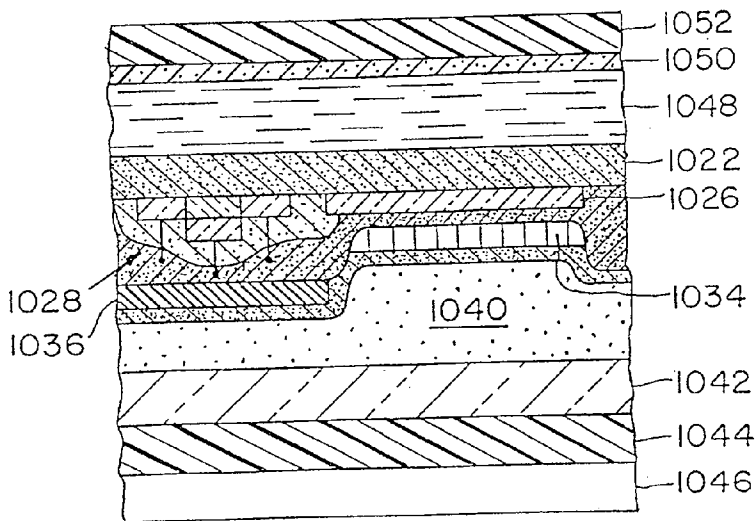


FIGURE 21G

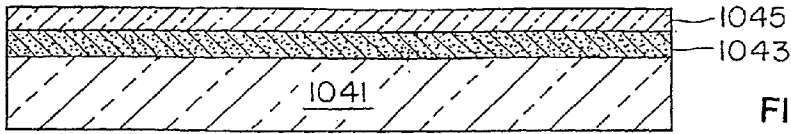


FIGURE 22A

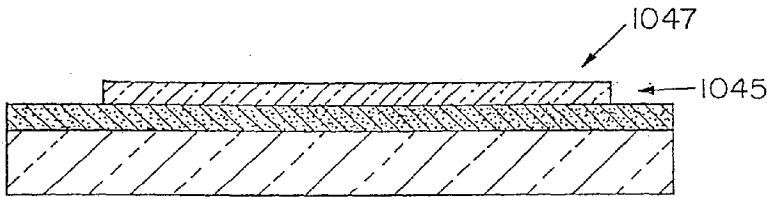


FIGURE 22B

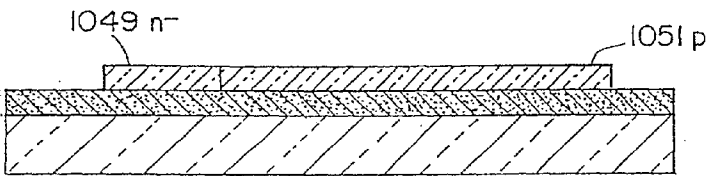


FIGURE 22C

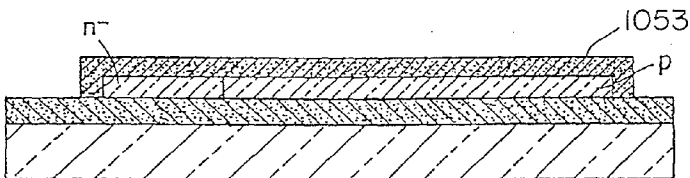


FIGURE 22D

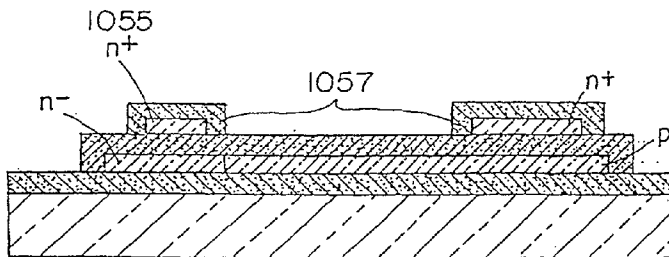


FIGURE 22E

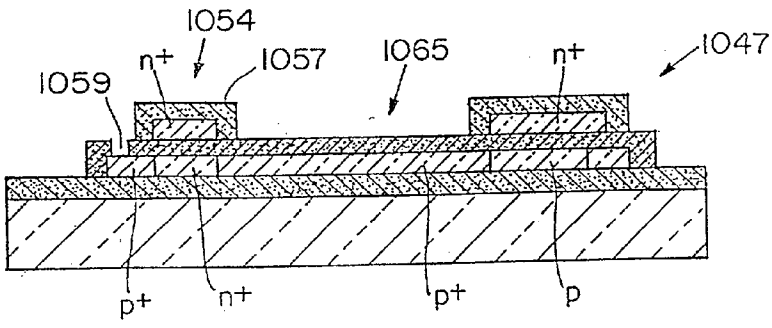


FIGURE 22F

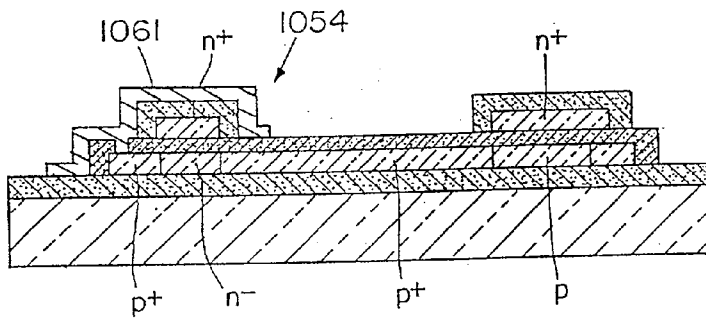


FIGURE 22G

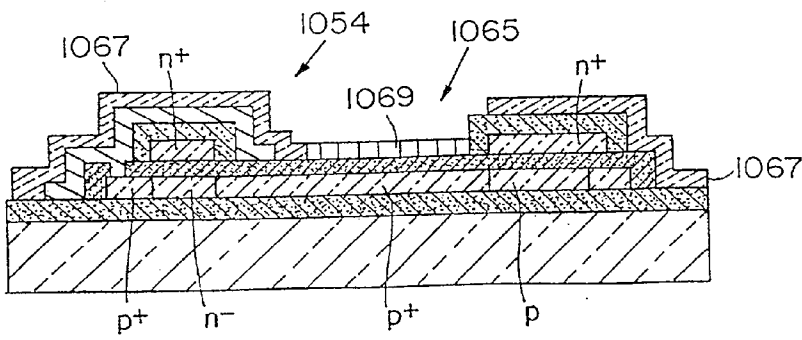
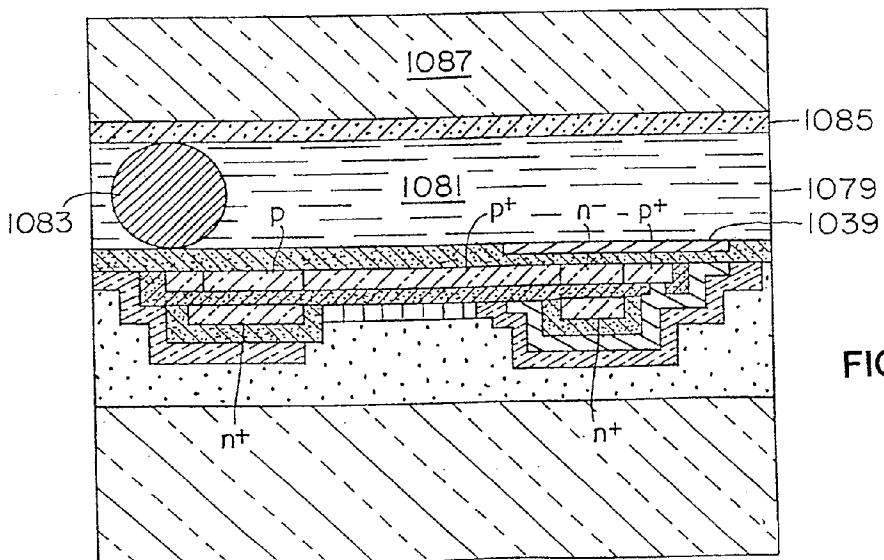
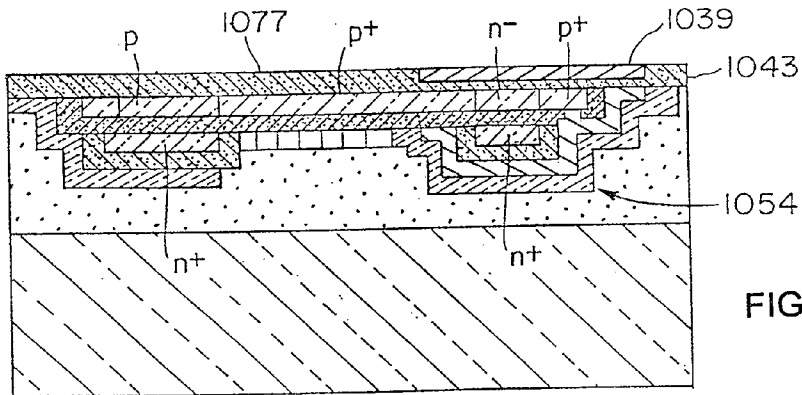
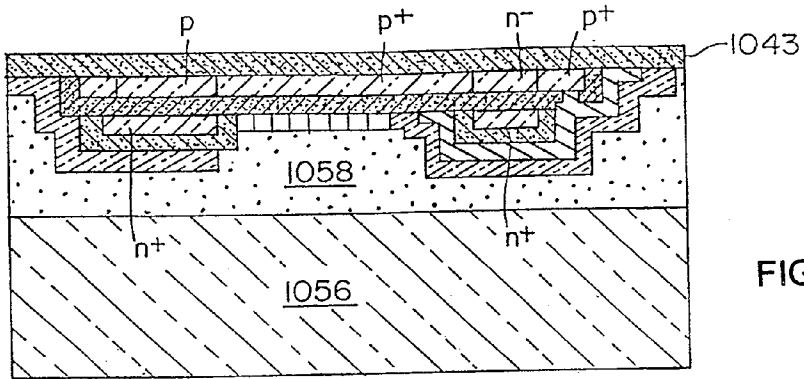


FIGURE 22H



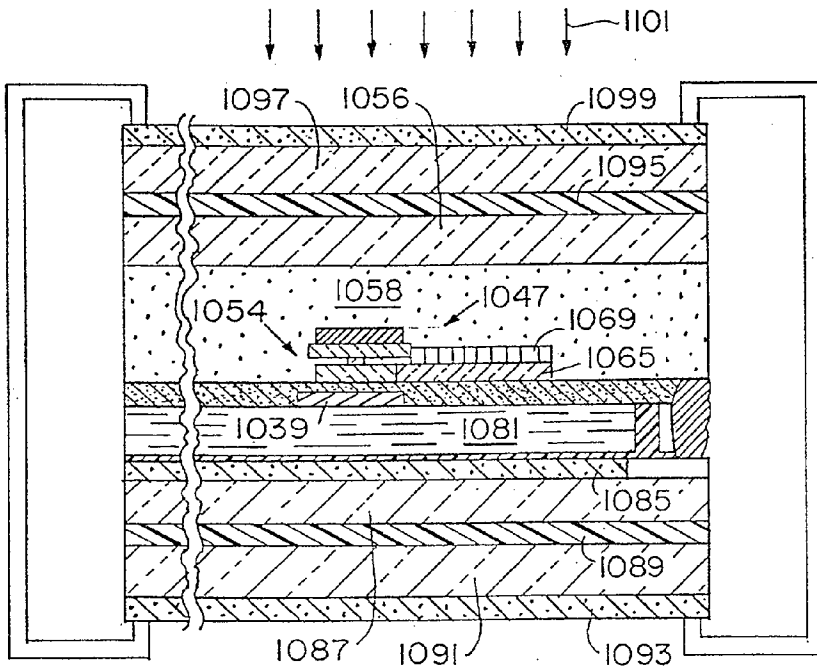


FIGURE 23

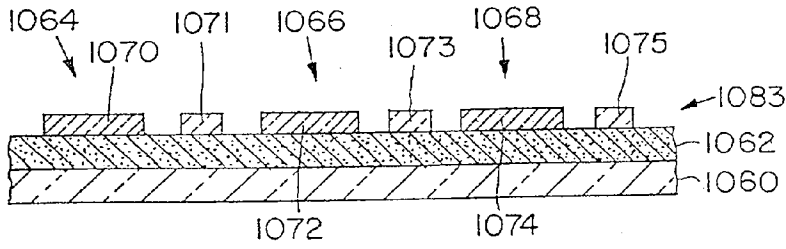


FIGURE 24A

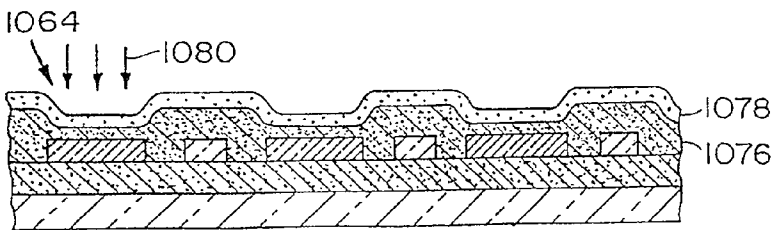


FIGURE 24B

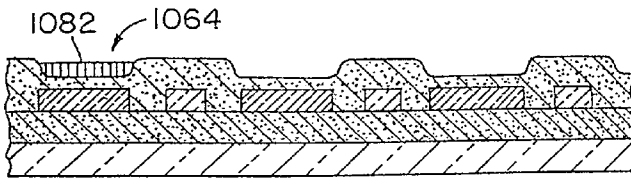


FIGURE 24C

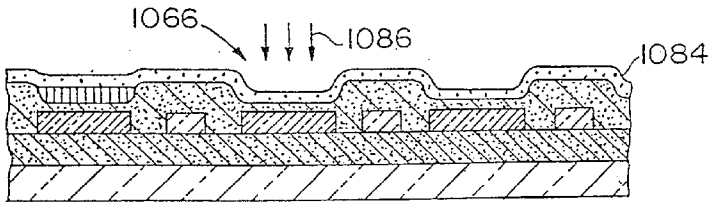


FIGURE 24D

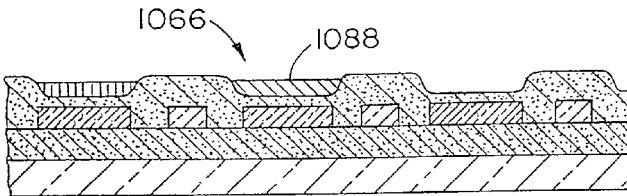


FIGURE 24E

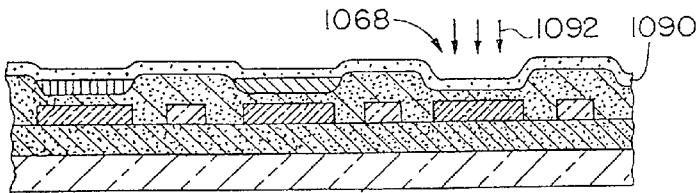


FIGURE 24F

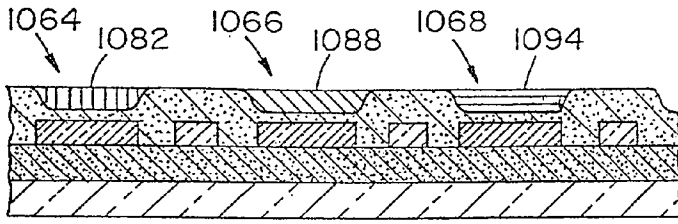


FIGURE 24G

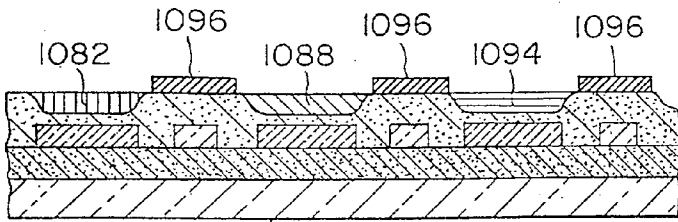


FIGURE 24H

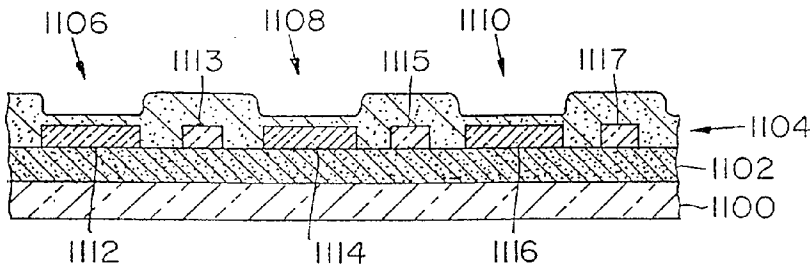


FIGURE 25A

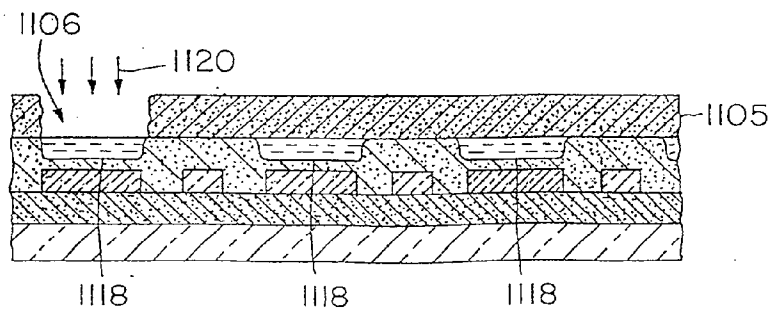


FIGURE 25B

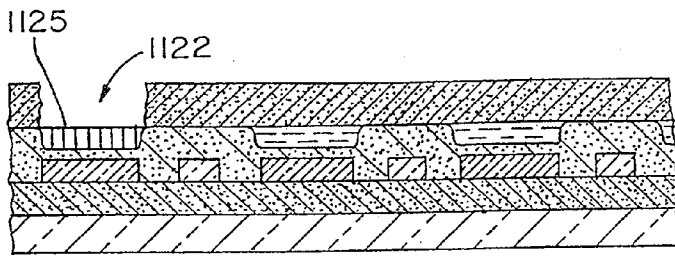


FIGURE 25C

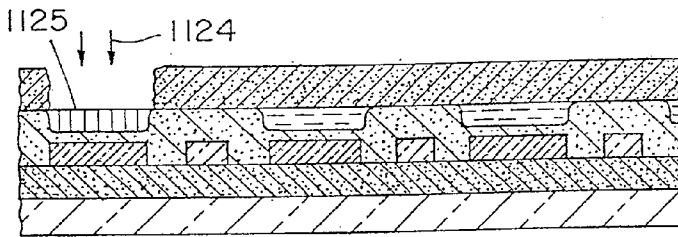


FIGURE 25D

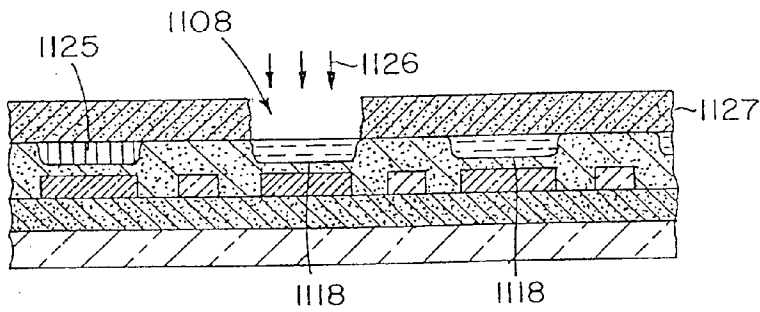


FIGURE 25E

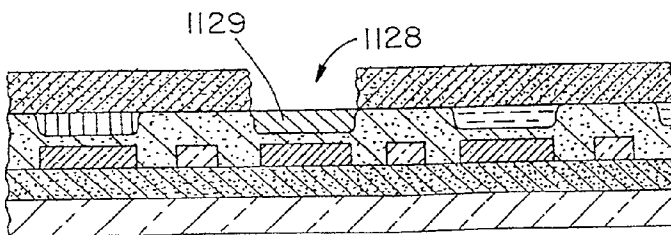


FIGURE 25F

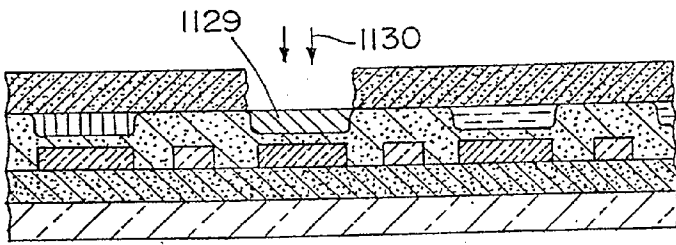


FIGURE 25G

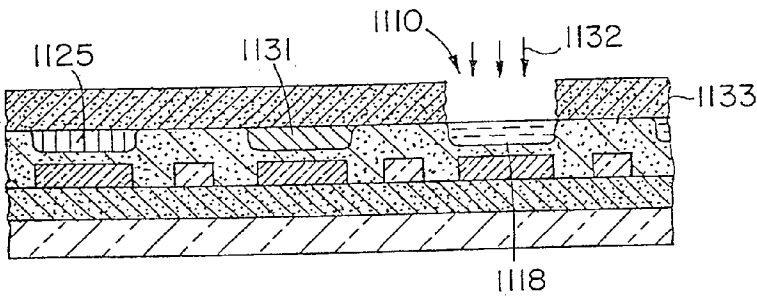


FIGURE 25H

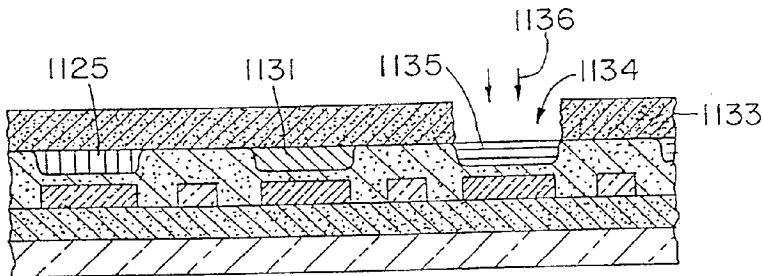


FIGURE 25I

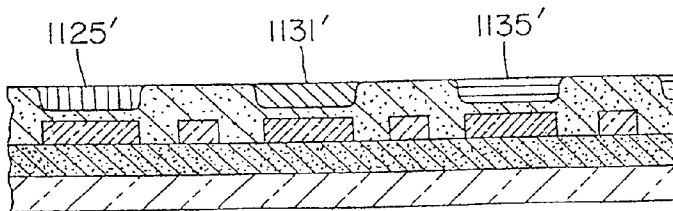


FIGURE 25J

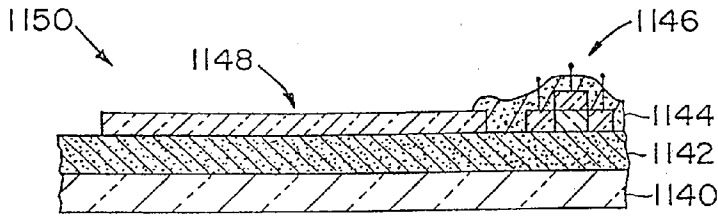


FIGURE 26A

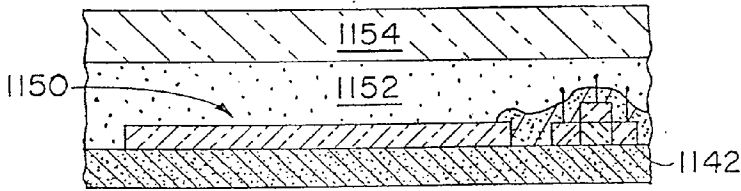


FIGURE 26B

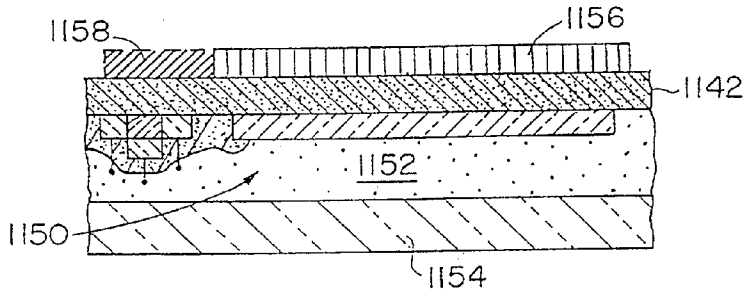


FIGURE 26C

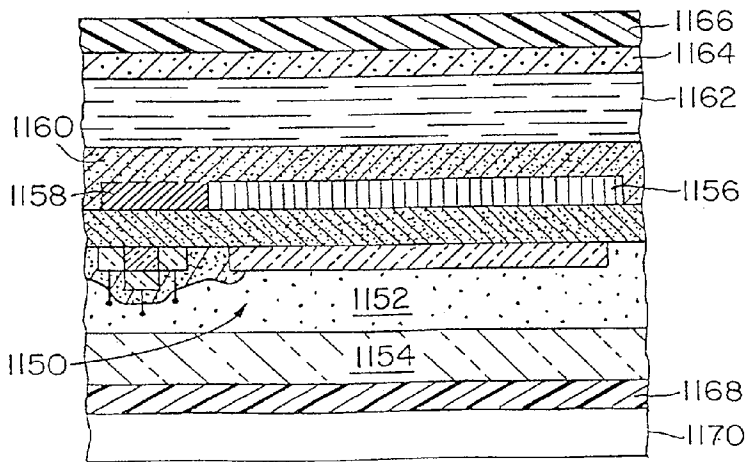


FIGURE 26D

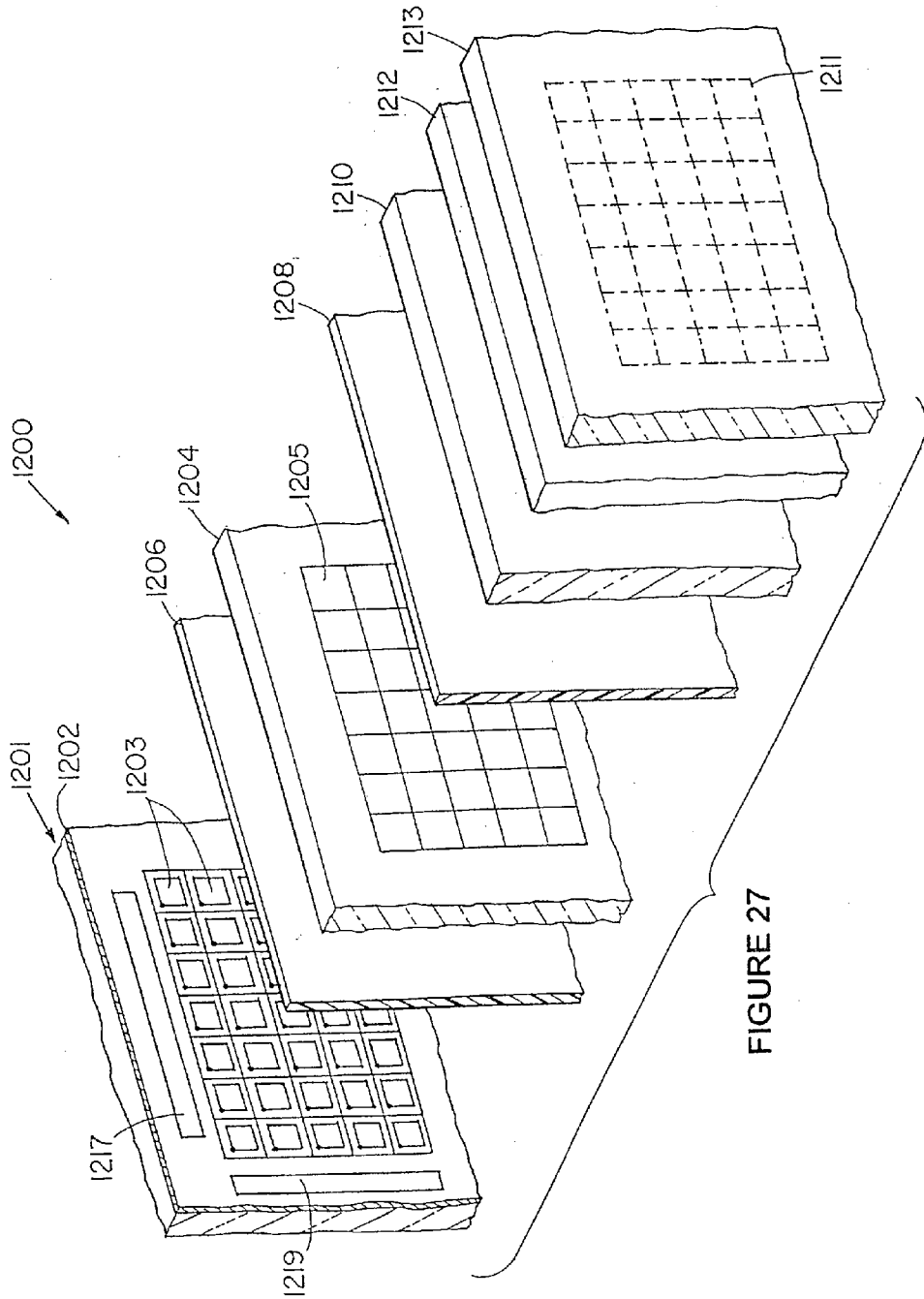


FIGURE 27

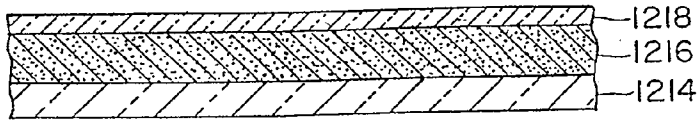


FIGURE 28A

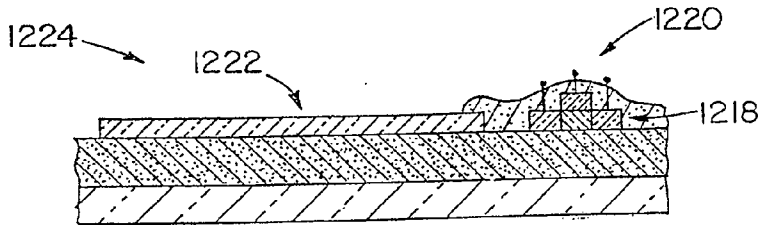


FIGURE 28B

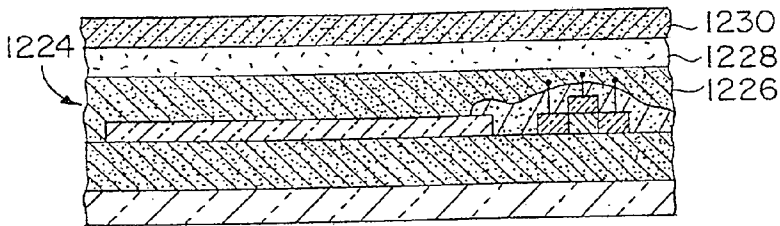


FIGURE 28C

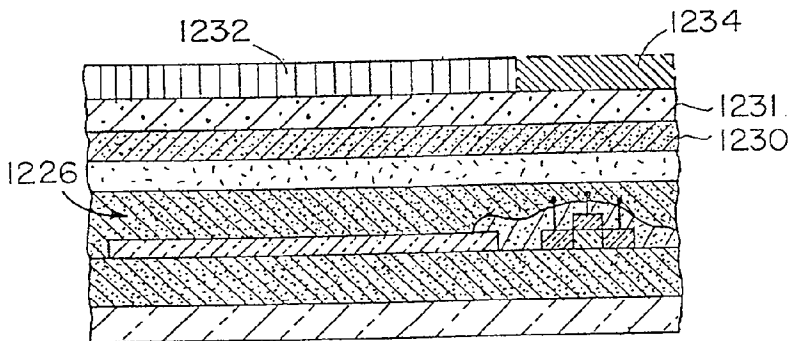


FIGURE 28D

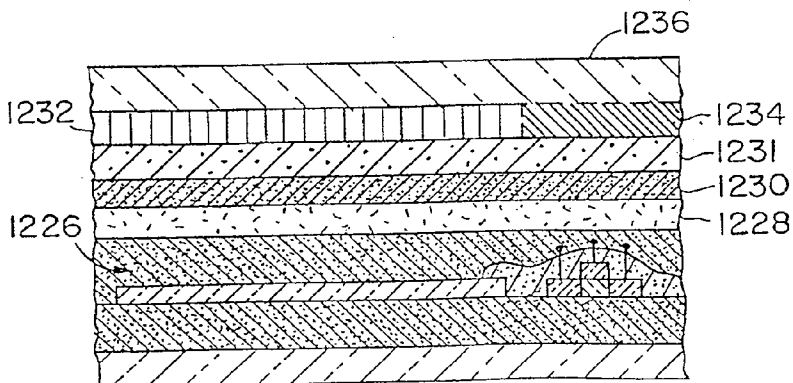


FIGURE 28E

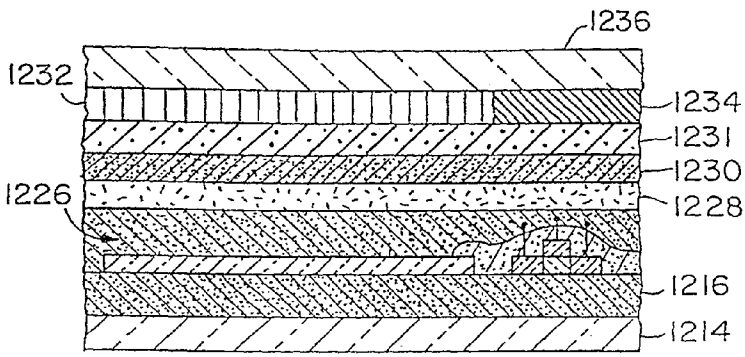


FIGURE 29A

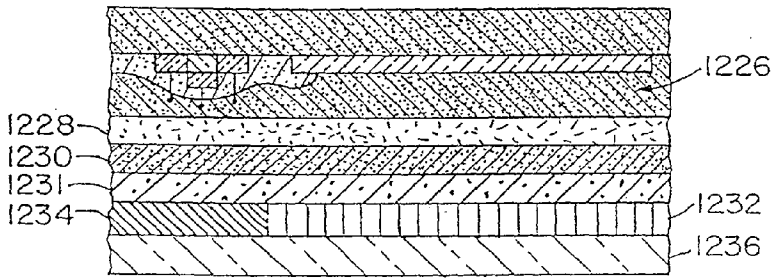


FIGURE 29B

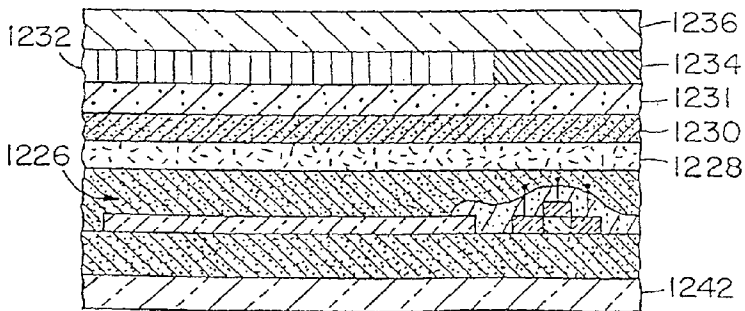


FIGURE 29C

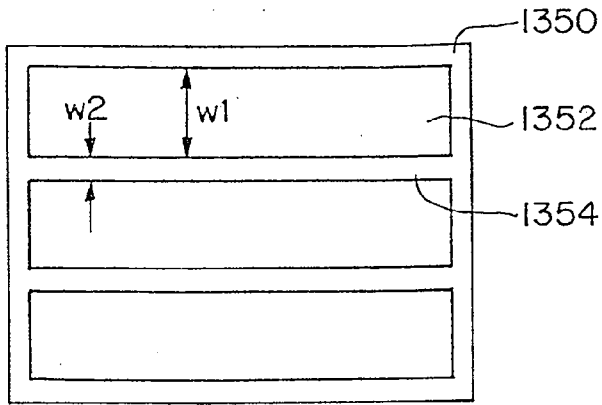


FIGURE 30

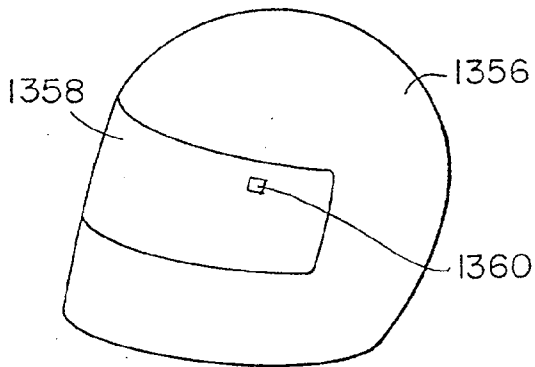


FIGURE 31

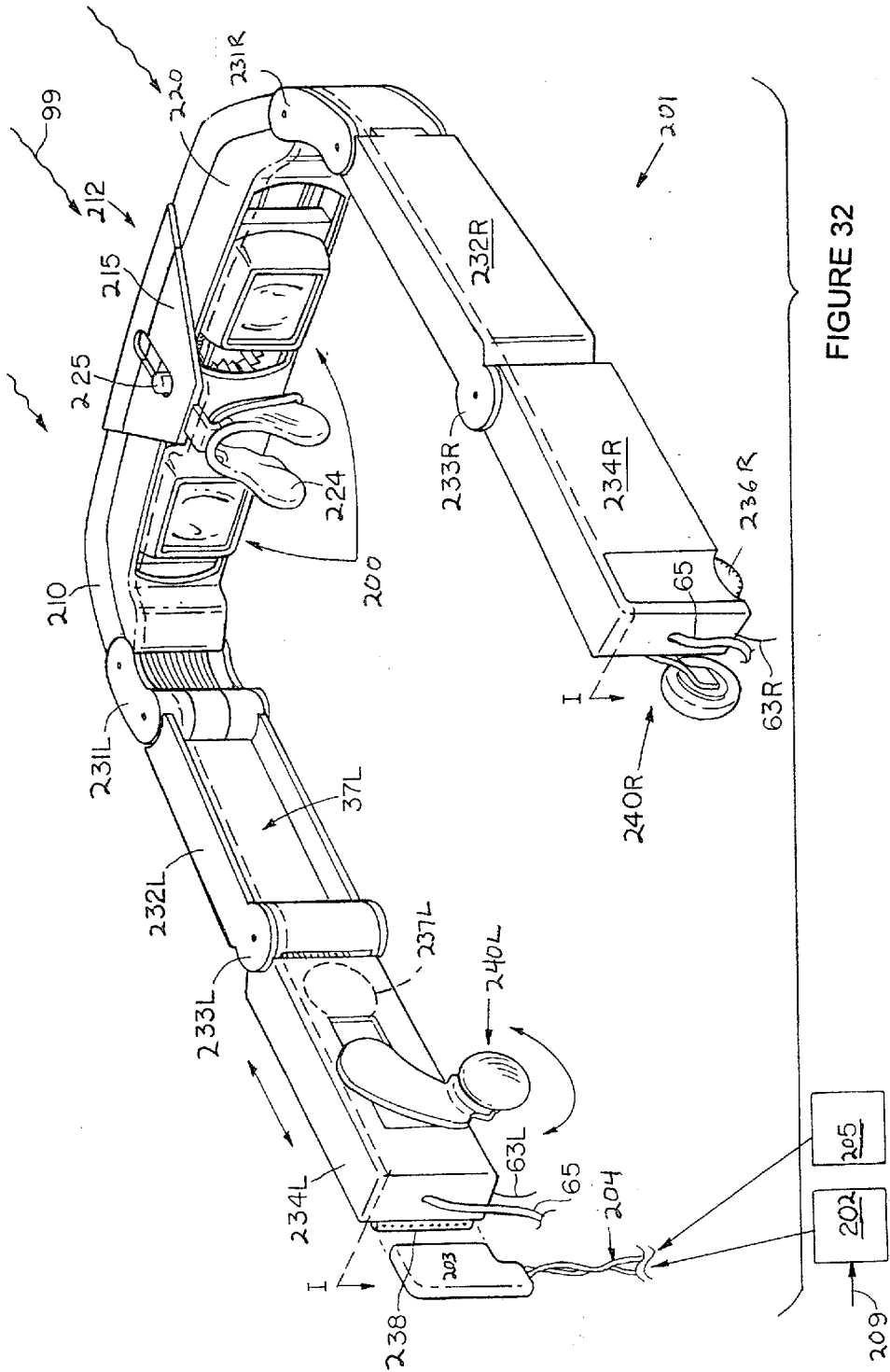


FIGURE 32

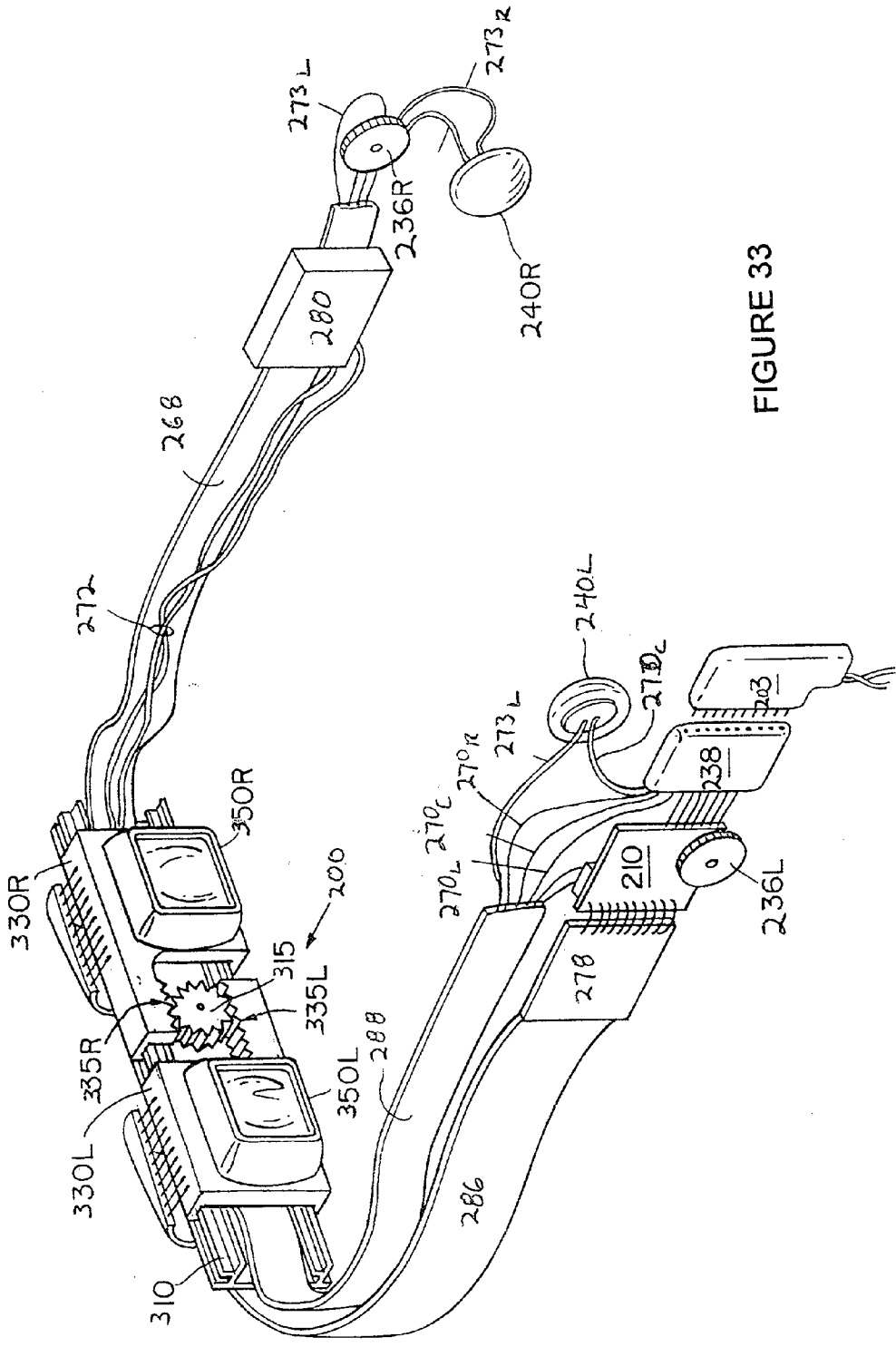


FIGURE 33

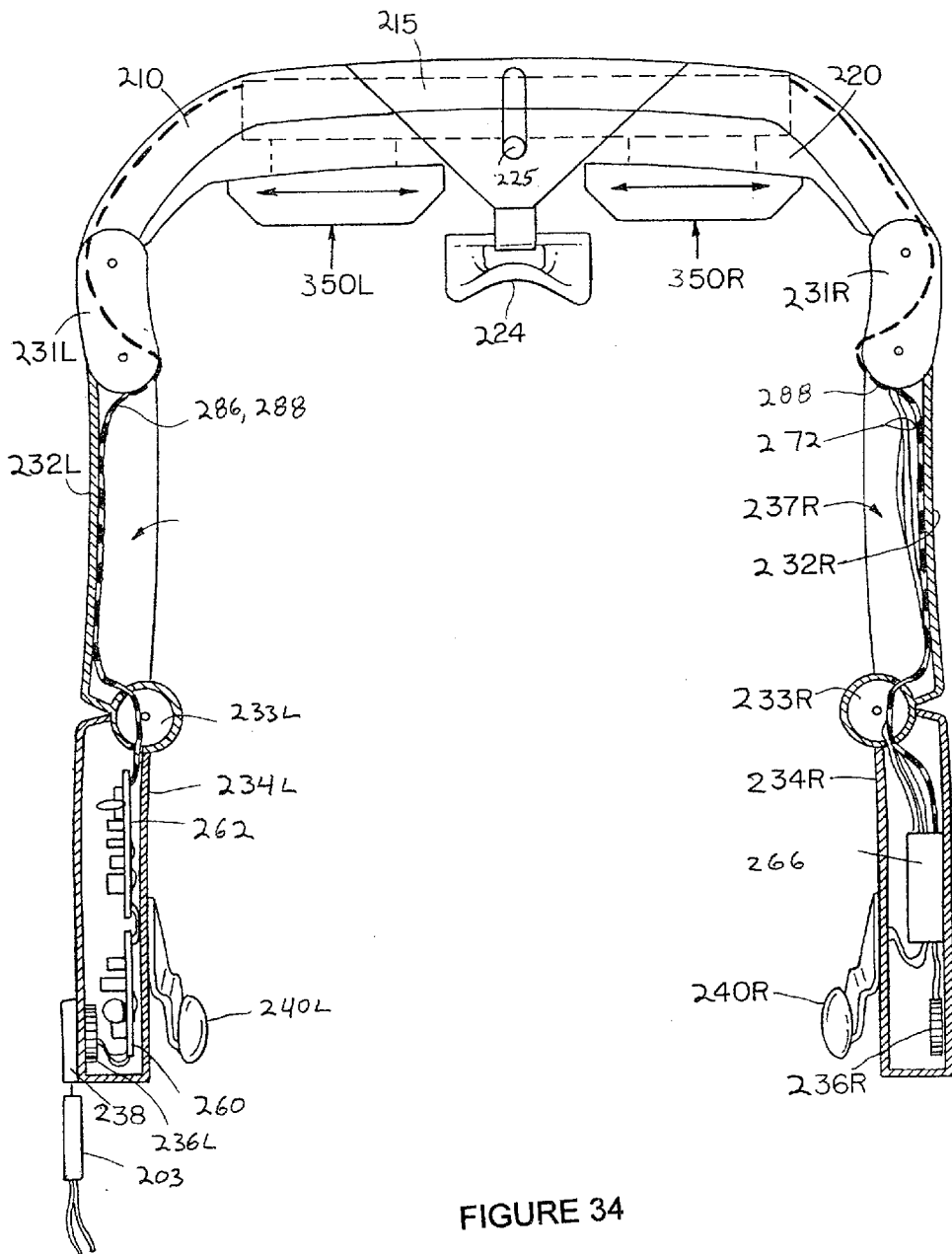


FIGURE 34

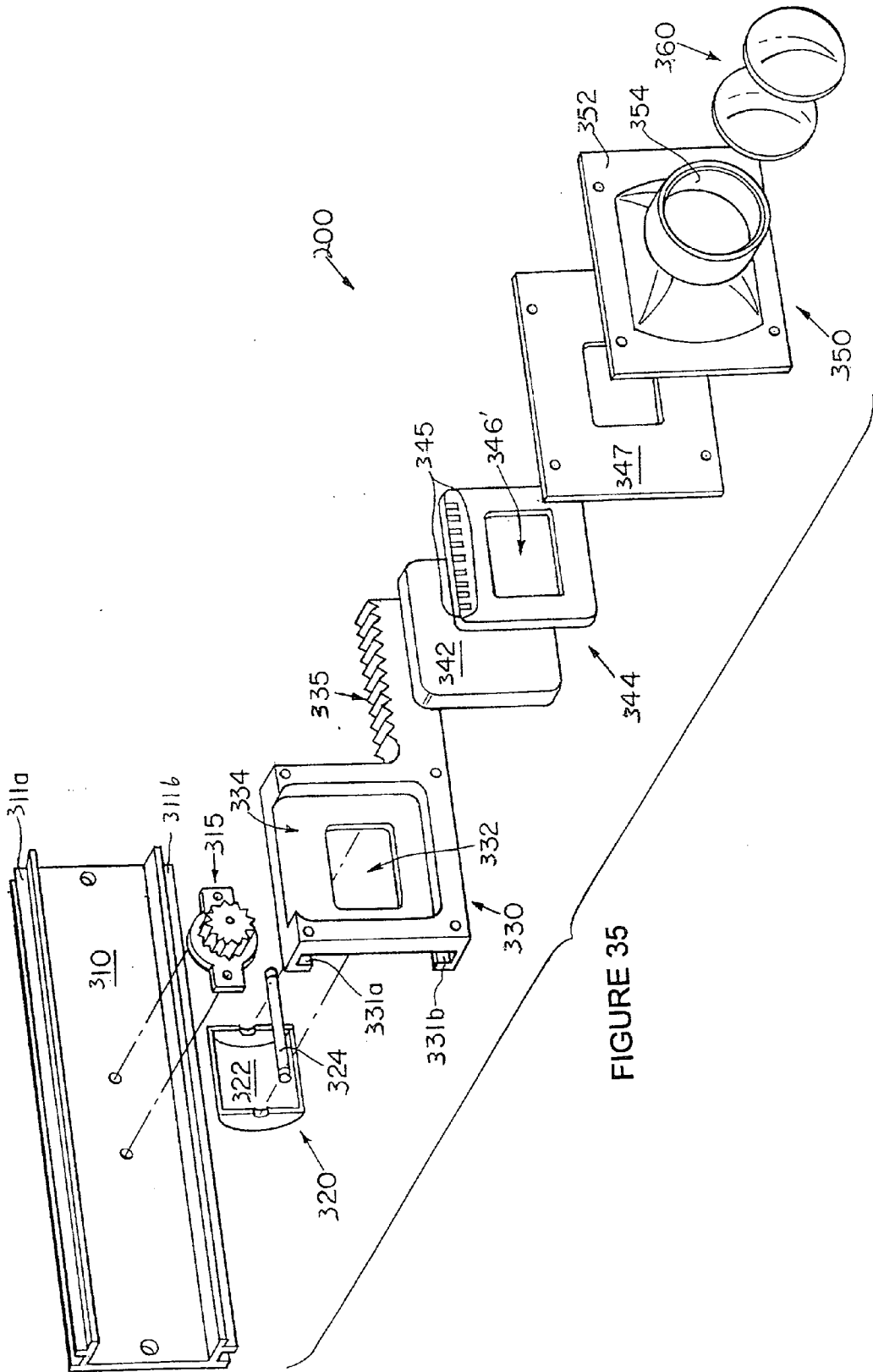


FIGURE 35

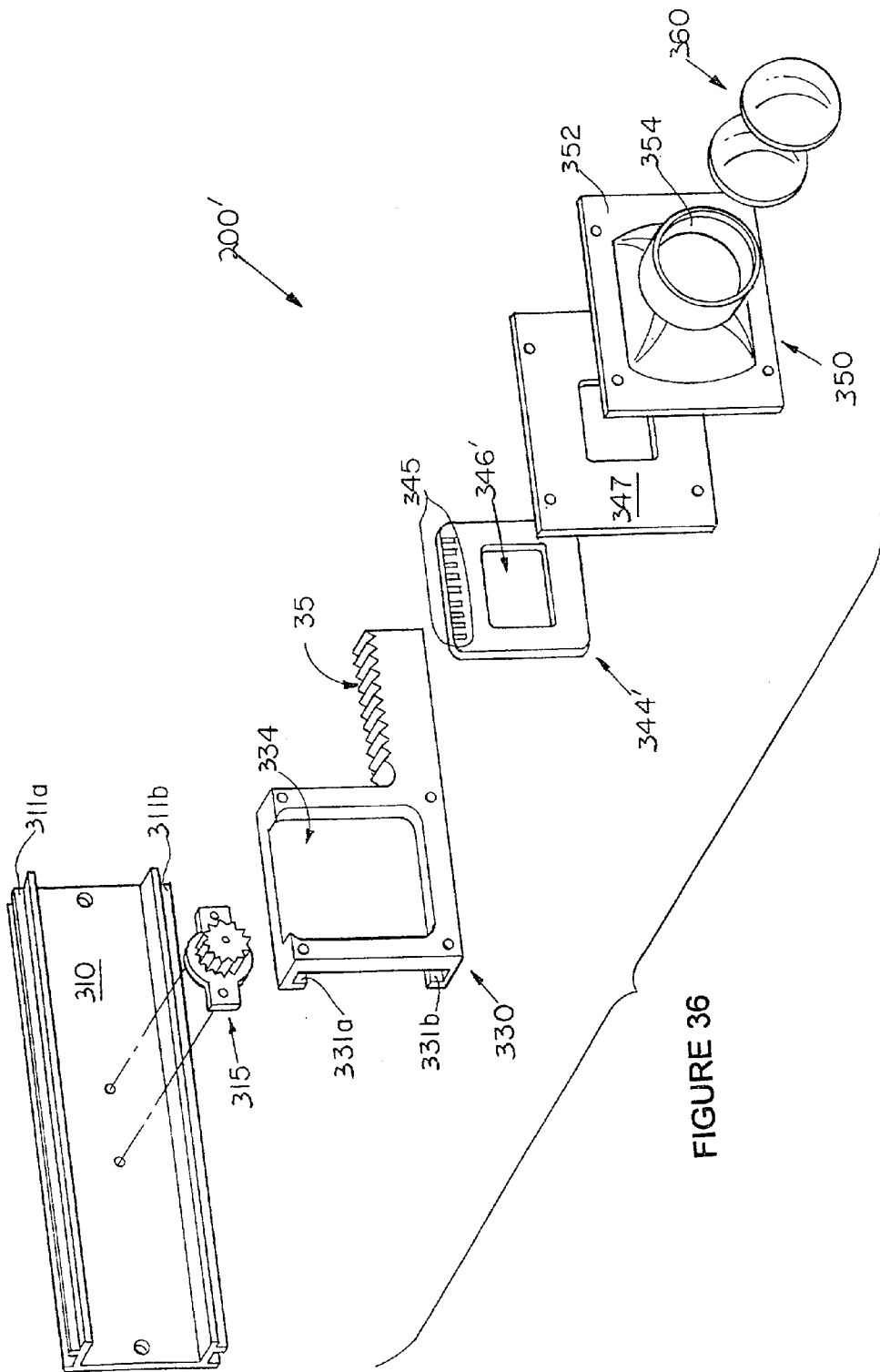


FIGURE 36

FIGURE 37

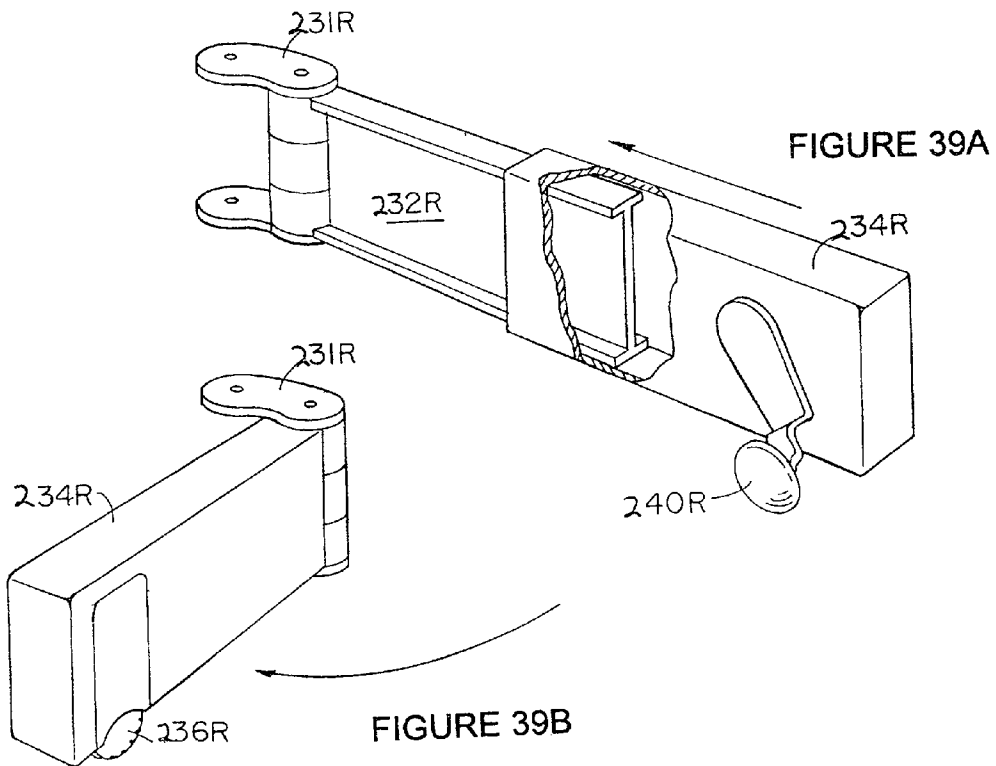
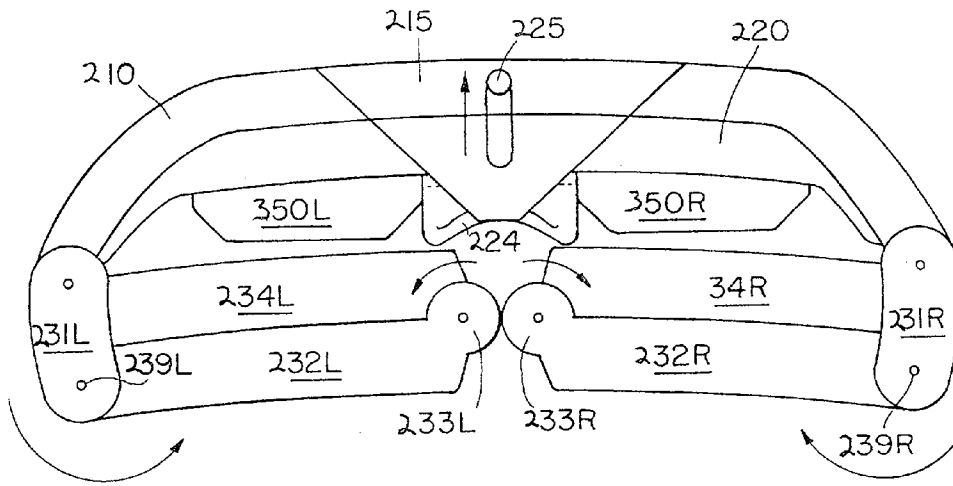


FIGURE 38

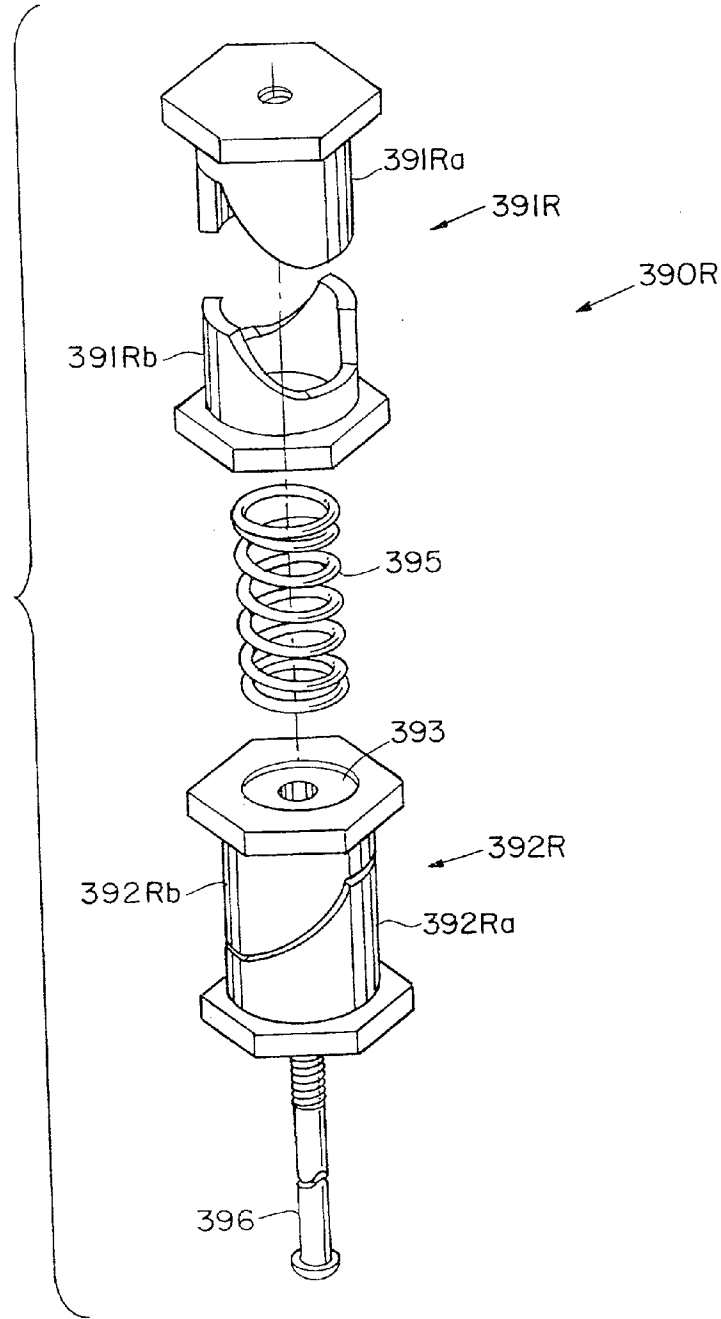
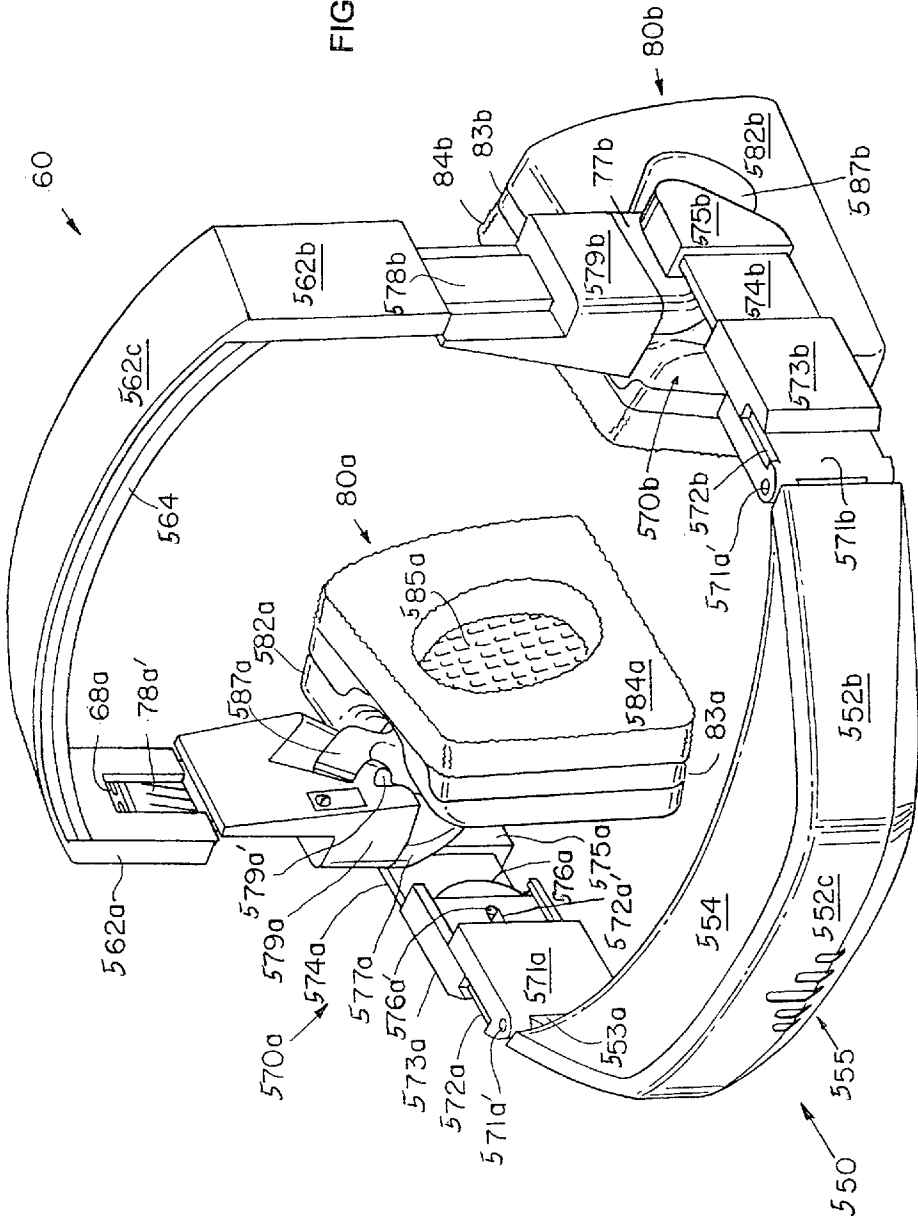


FIGURE 40



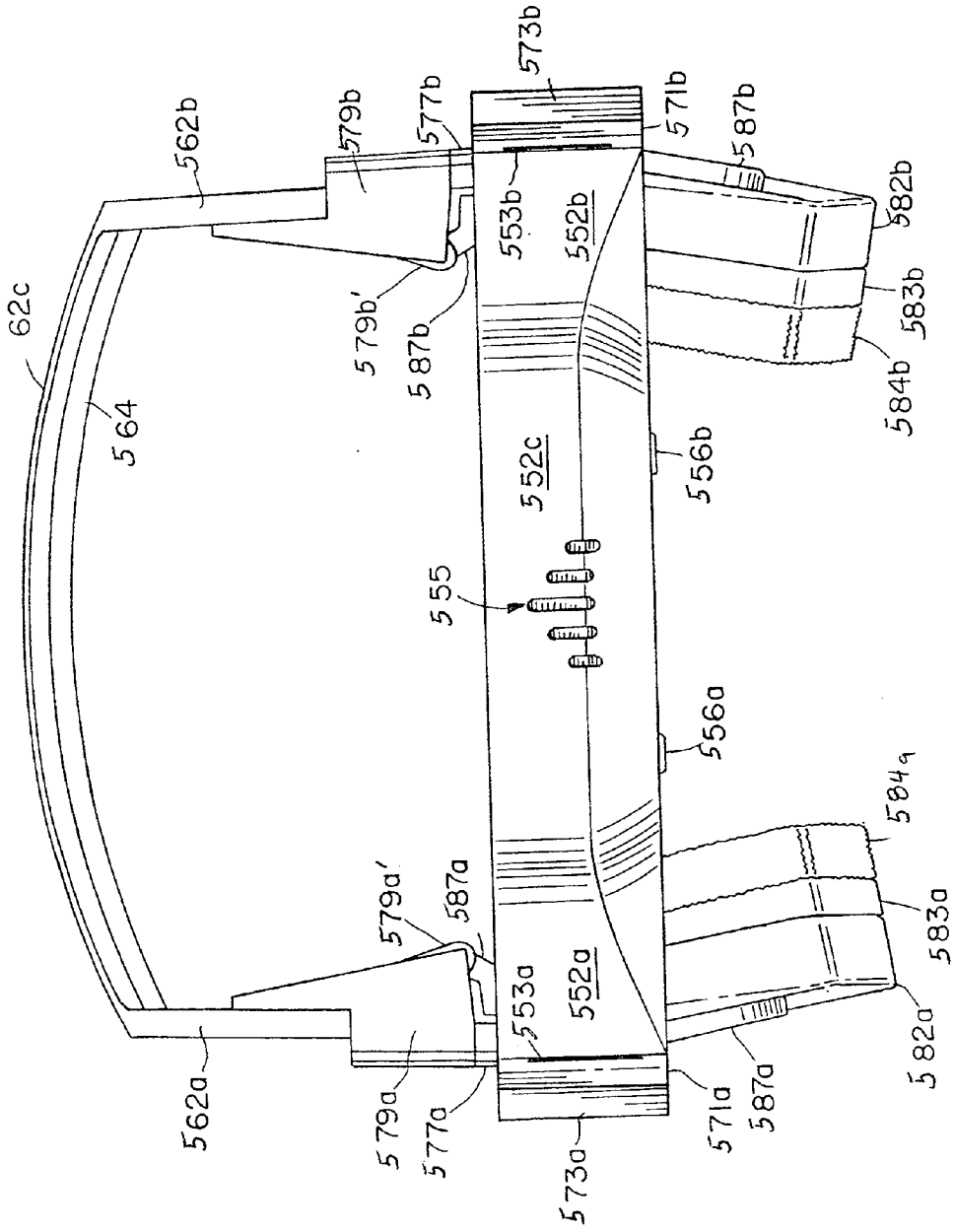


FIGURE 41

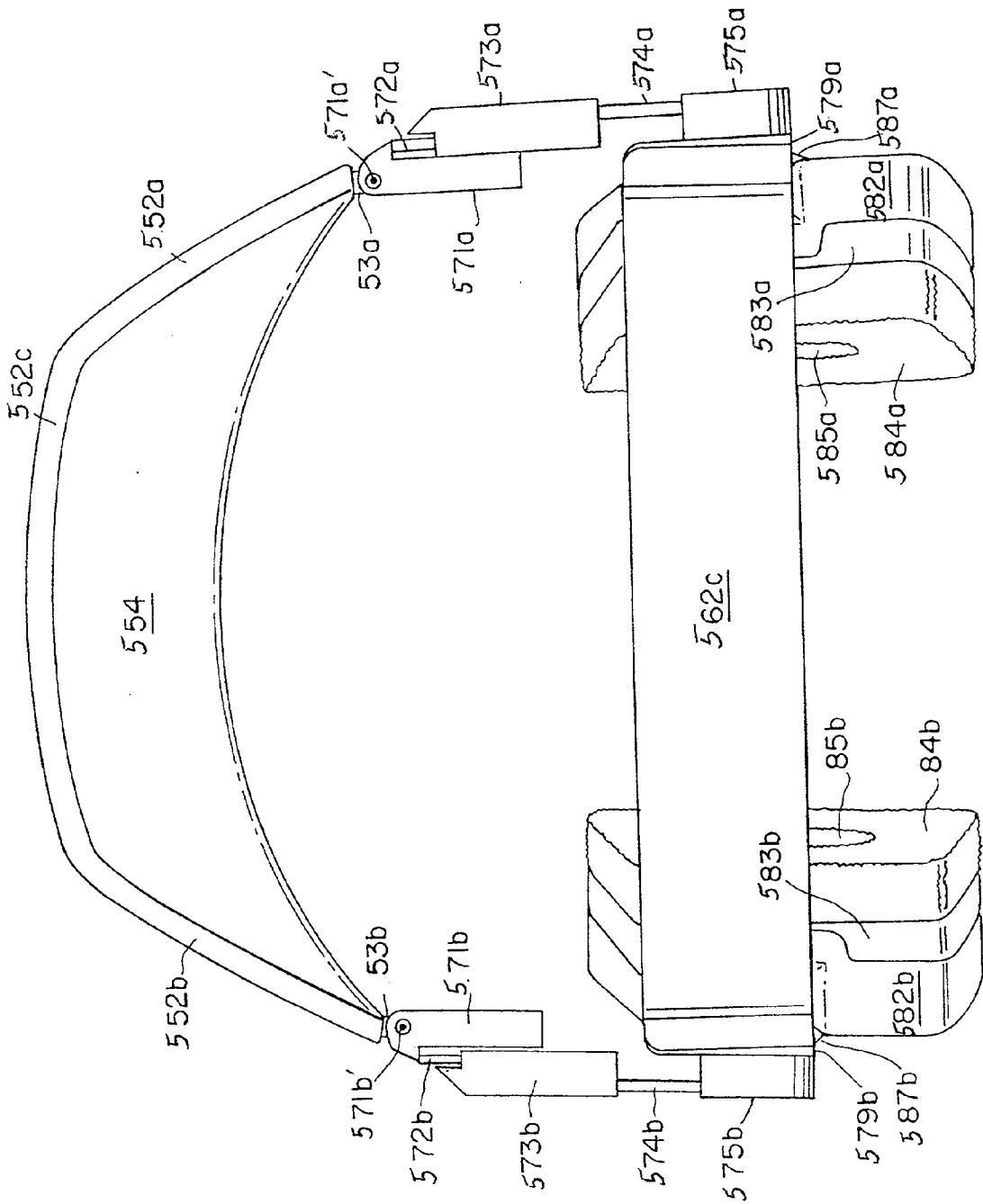


FIGURE 42

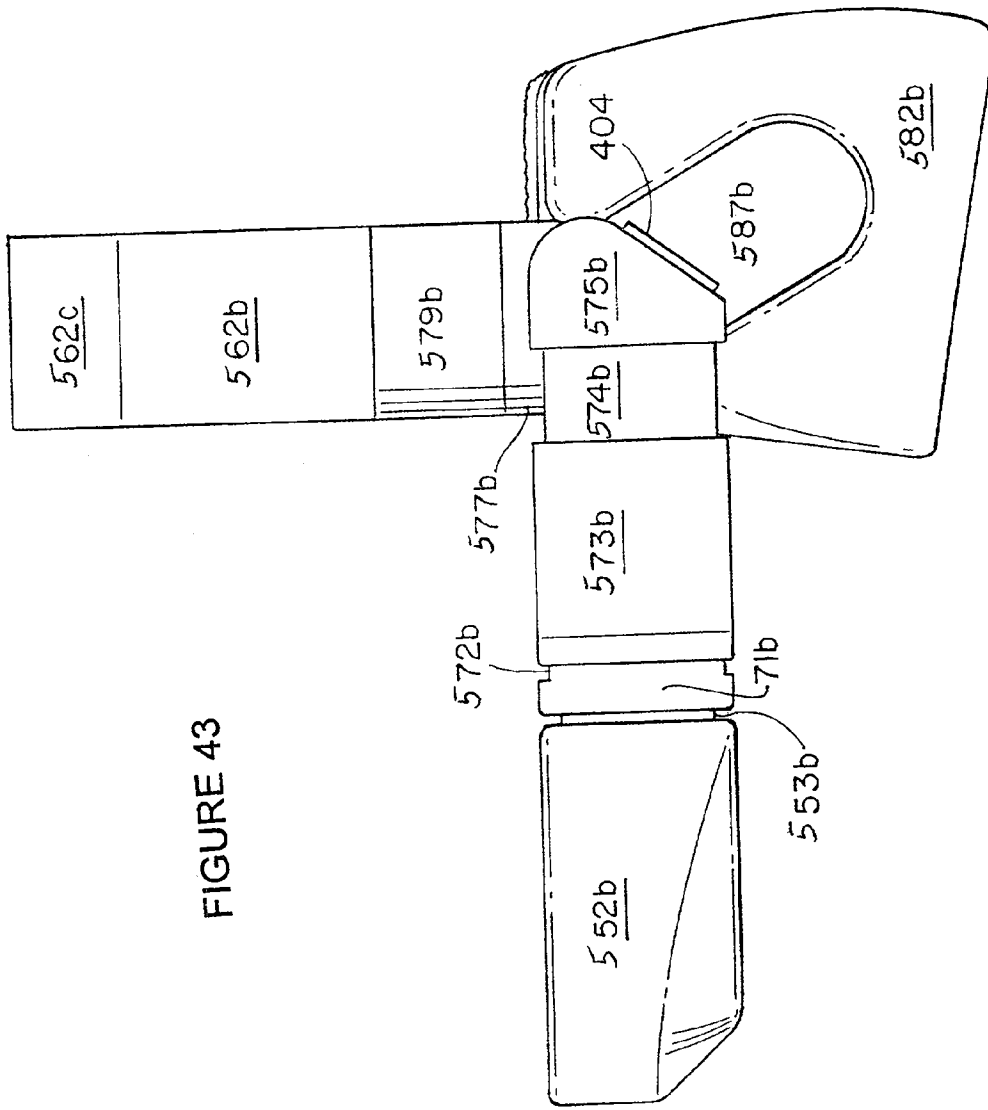


FIGURE 43

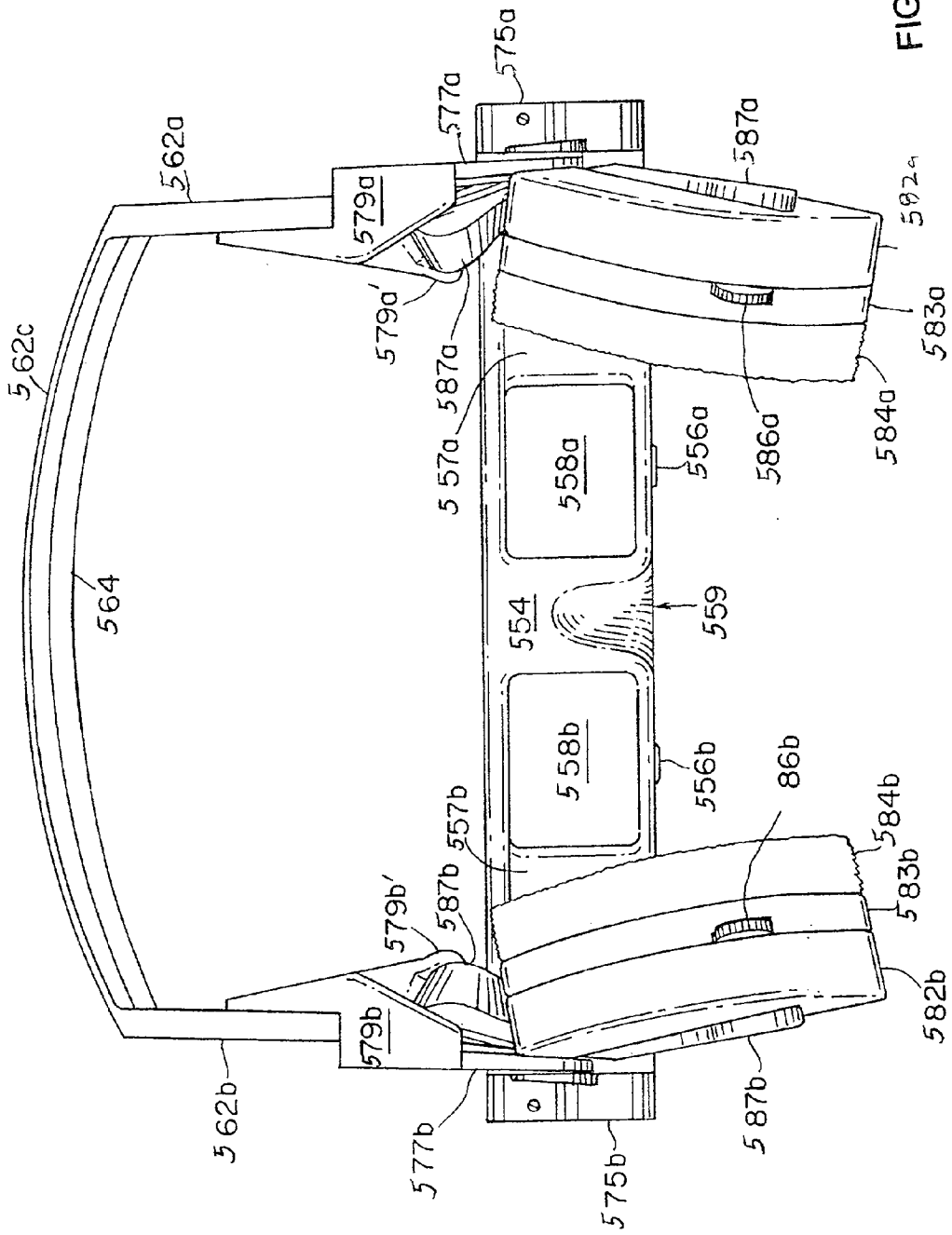


FIGURE 44

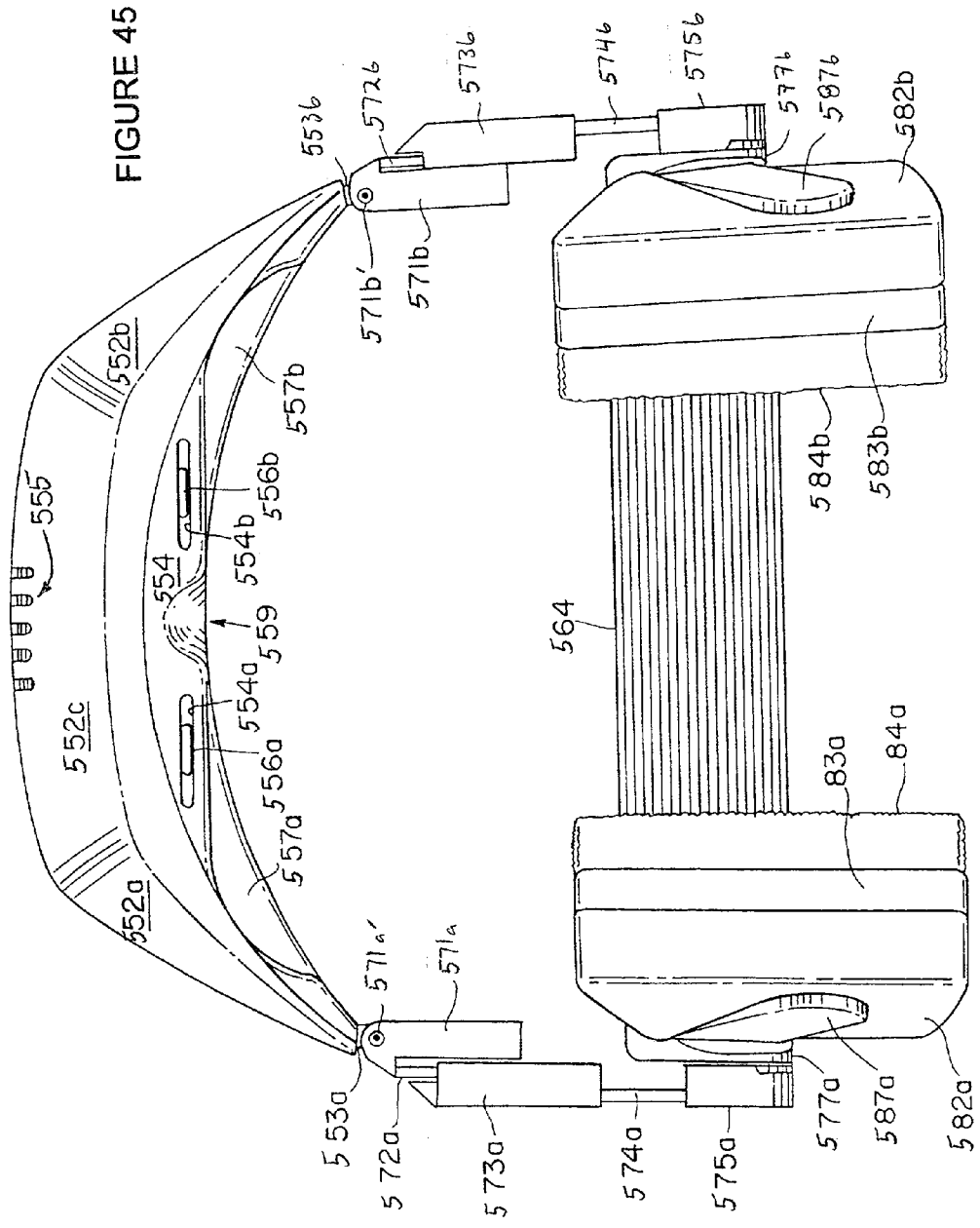
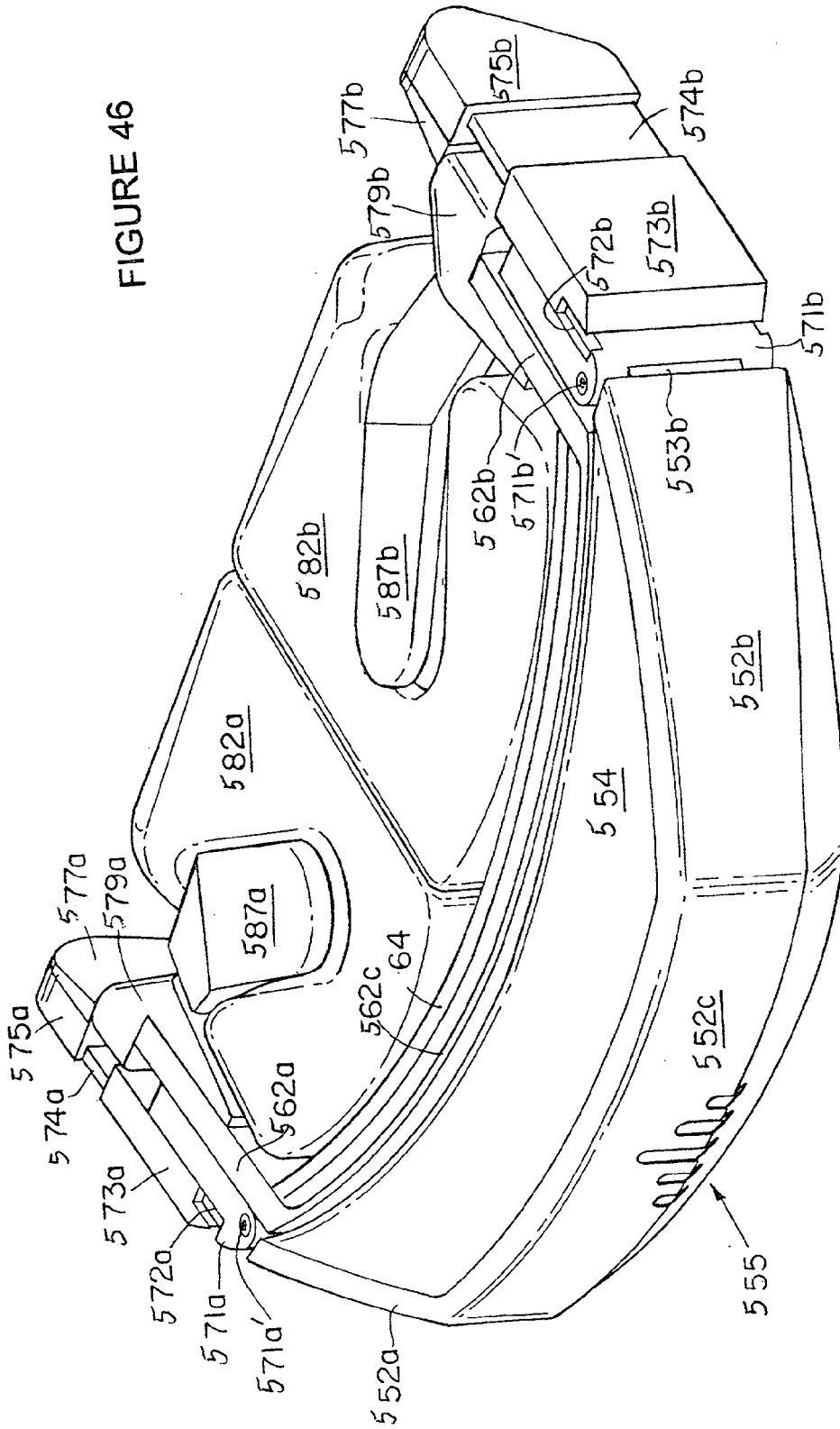


FIGURE 46



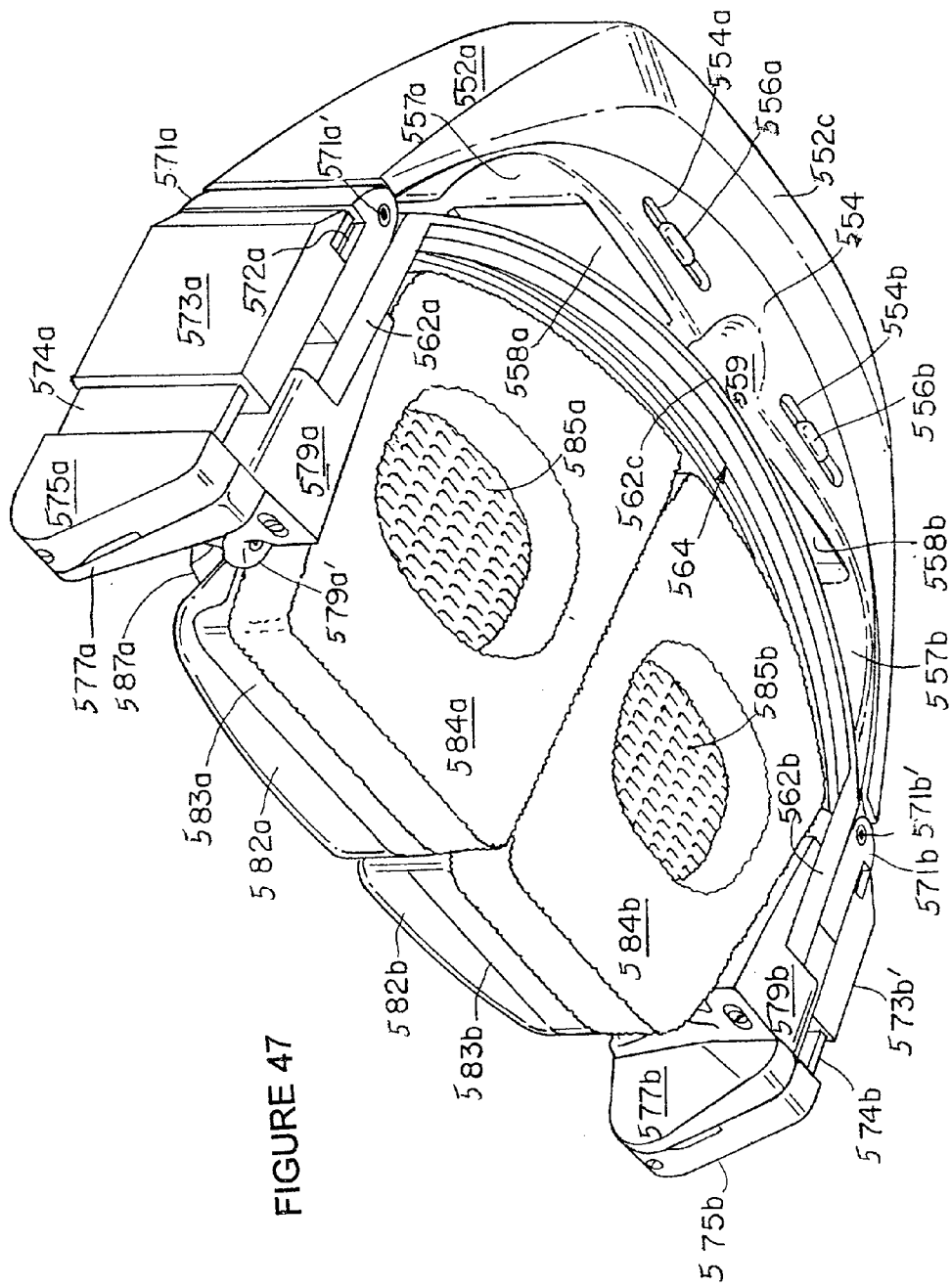


FIGURE 47

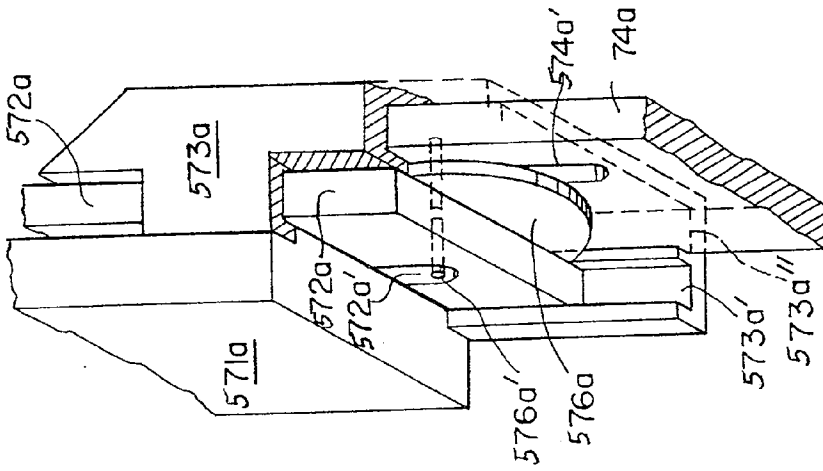


FIGURE 48B

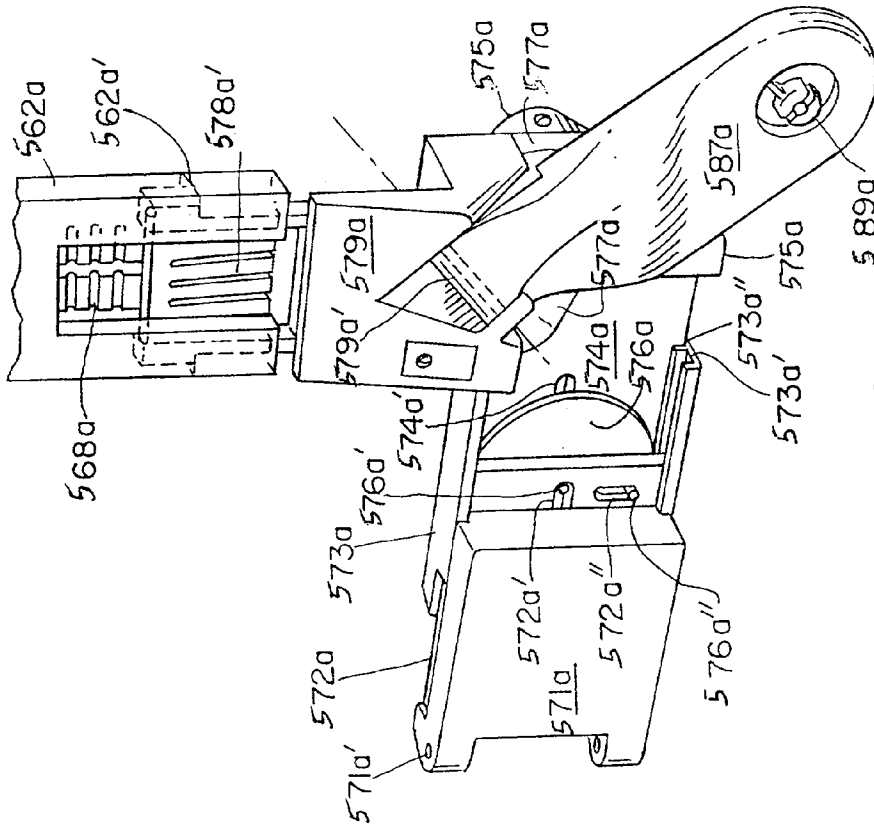


FIGURE 48A

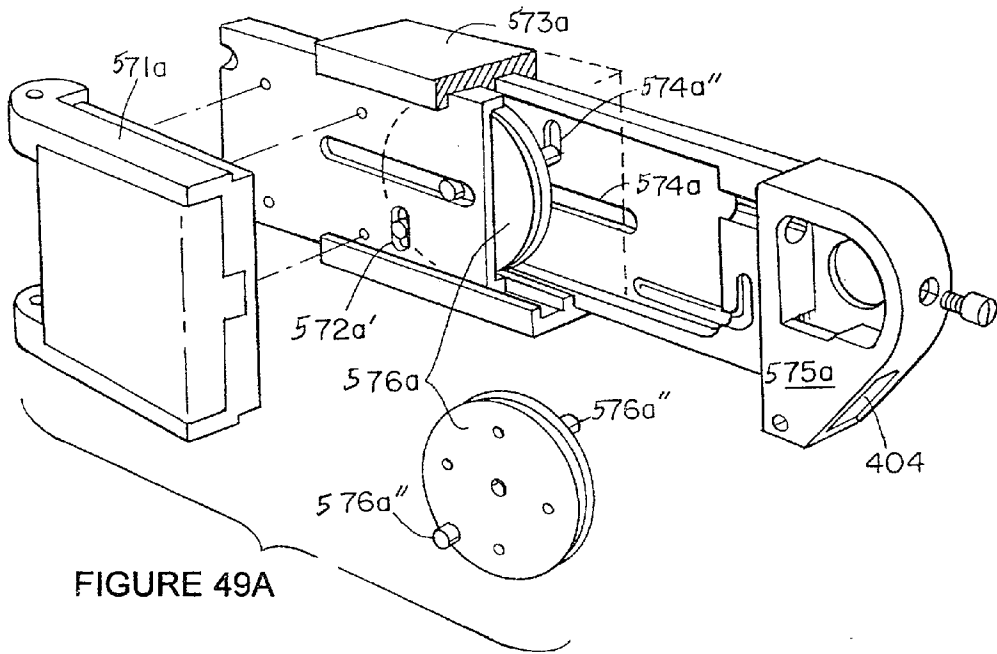


FIGURE 49A

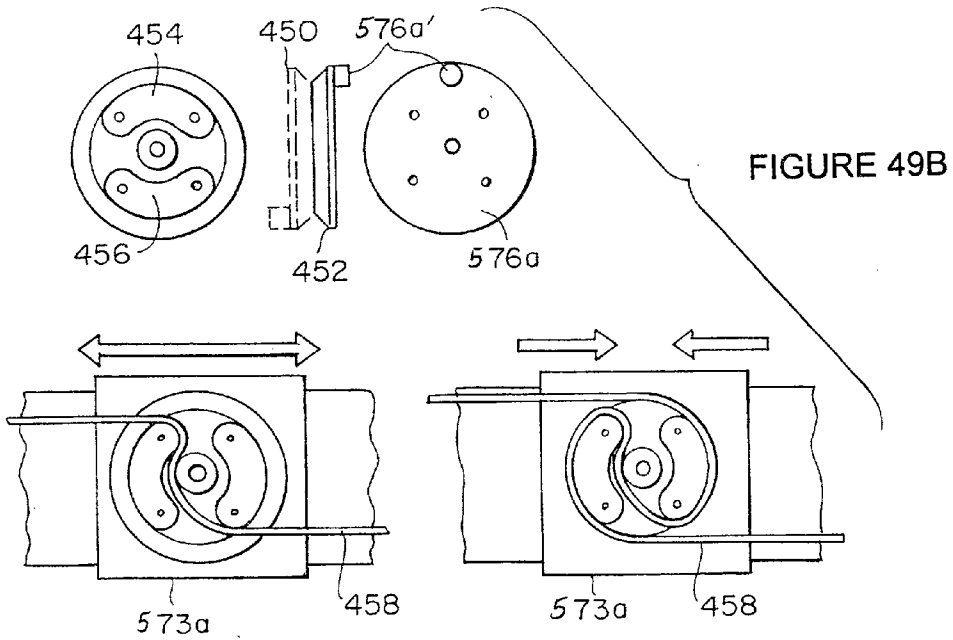
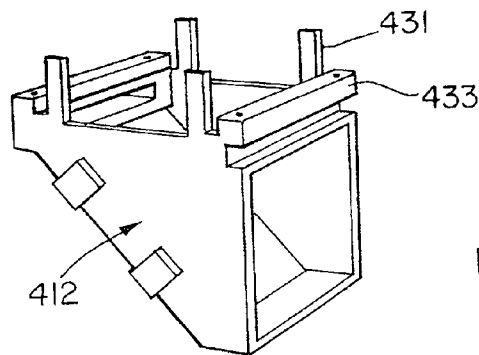
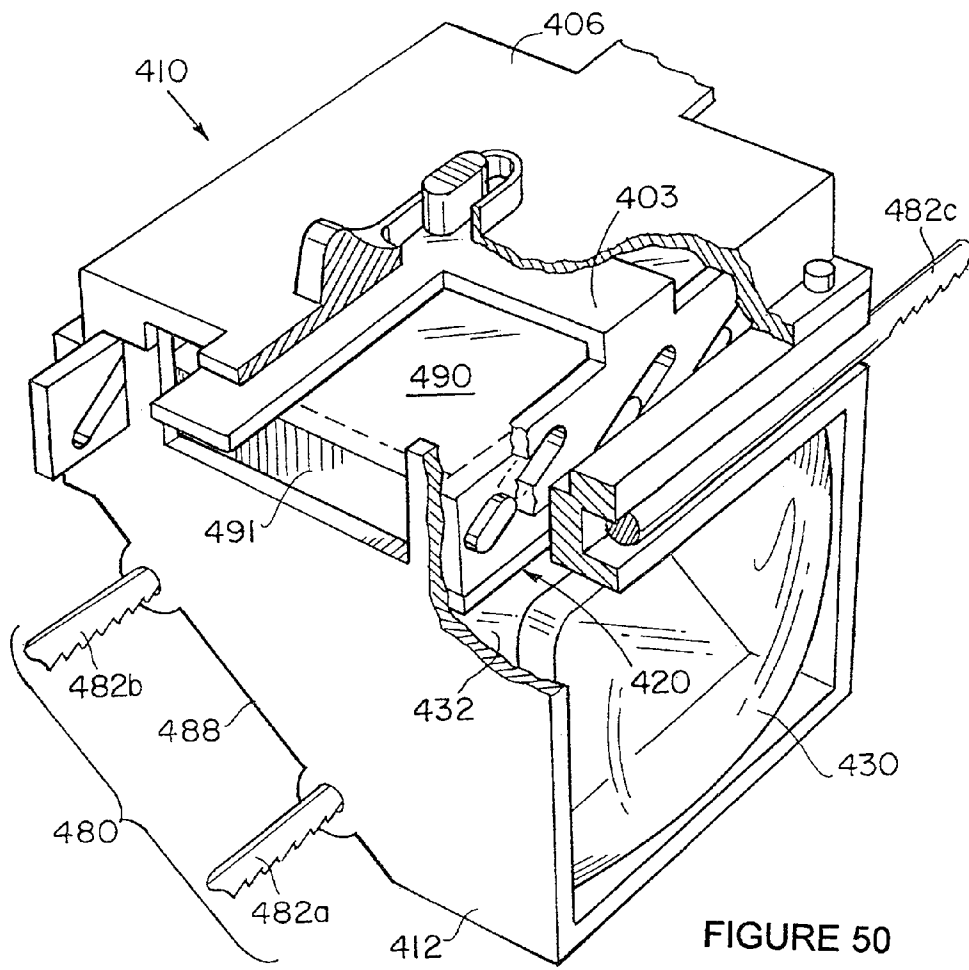


FIGURE 49B



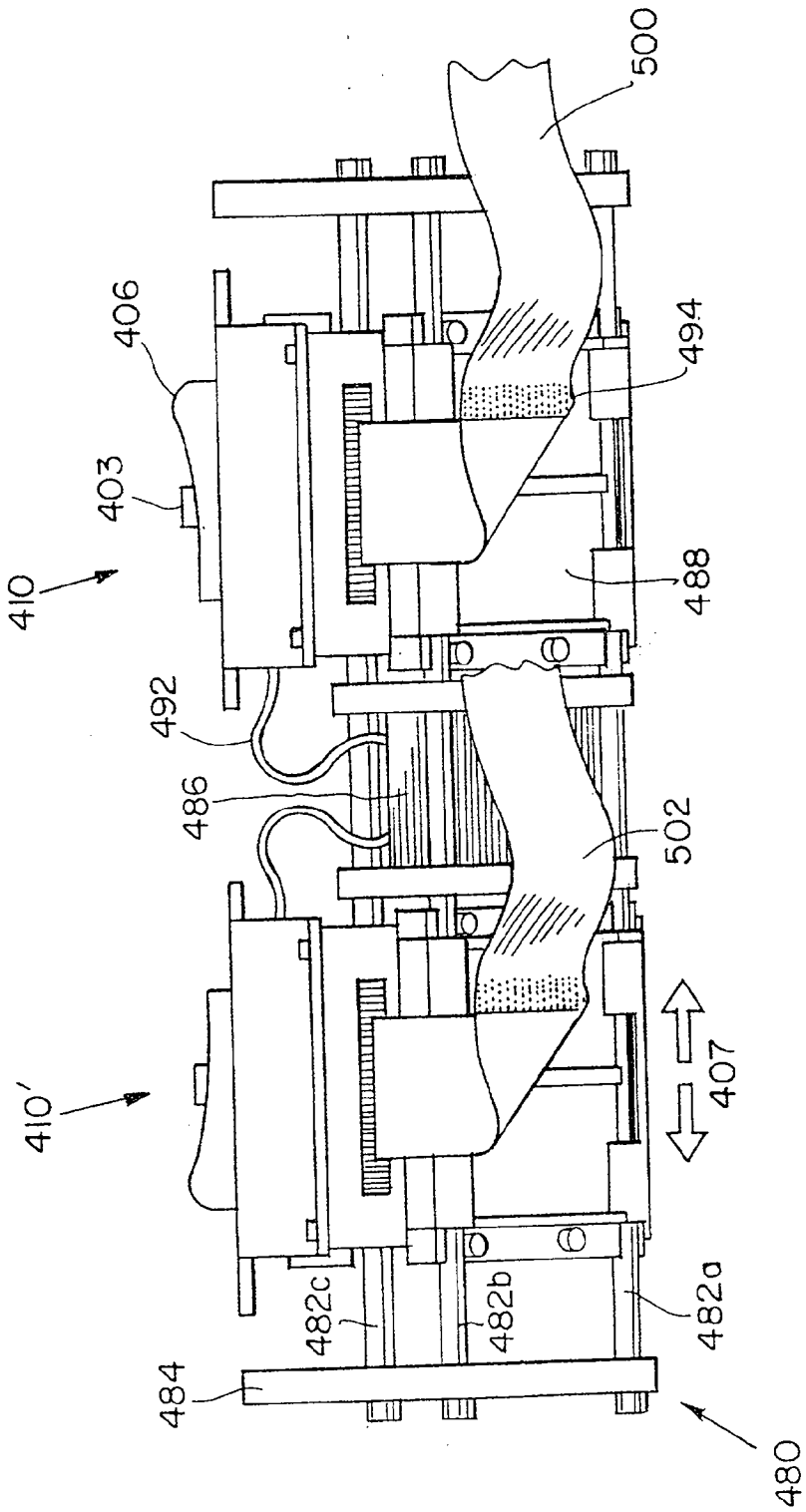


FIGURE 51

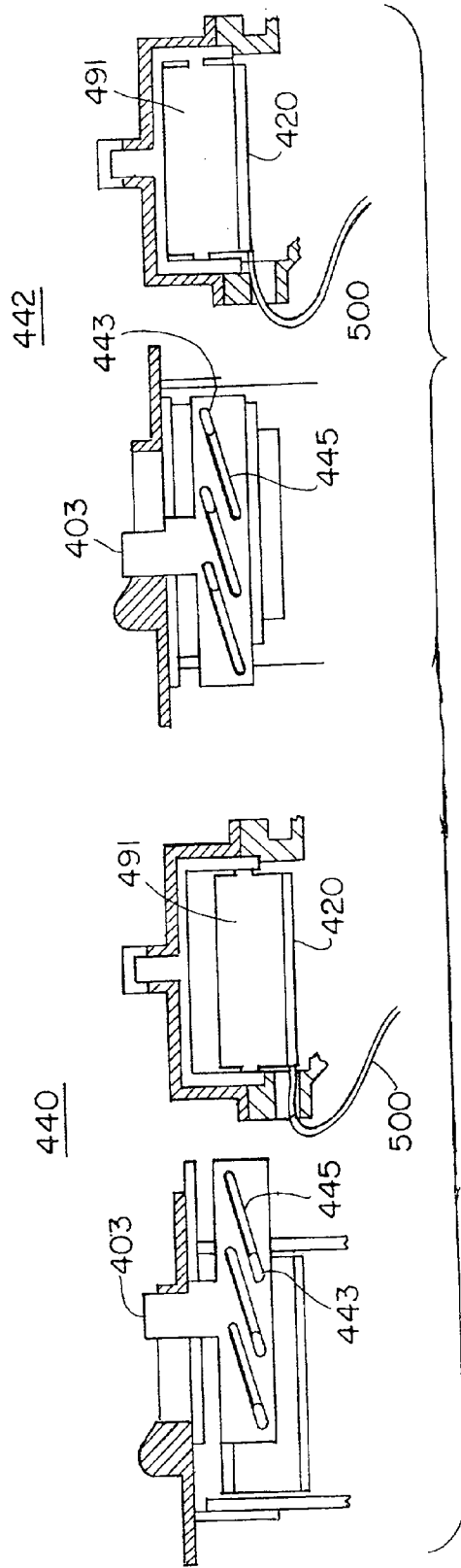


FIGURE 54

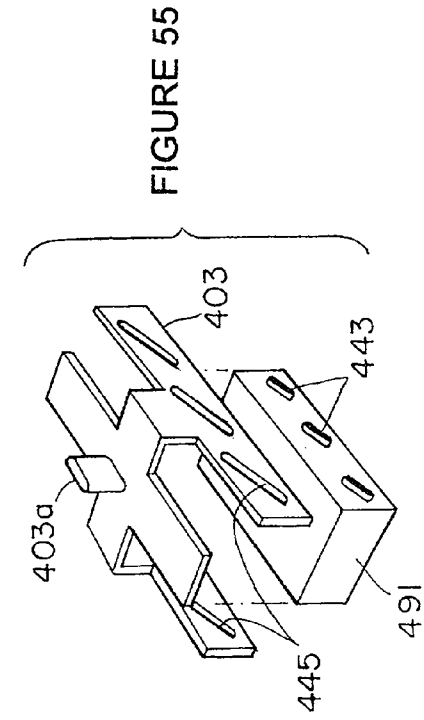


FIGURE 55

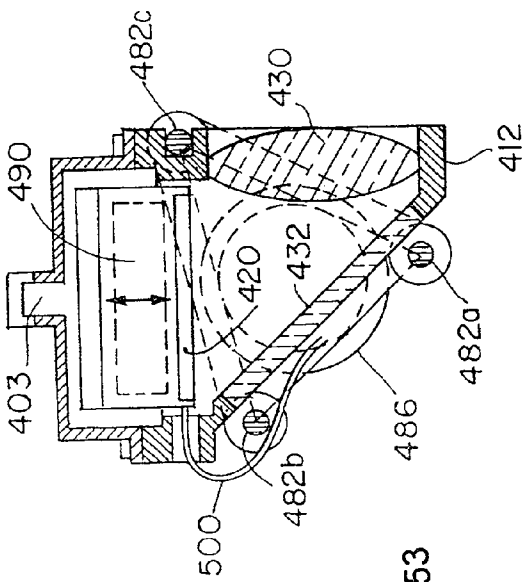


FIGURE 53

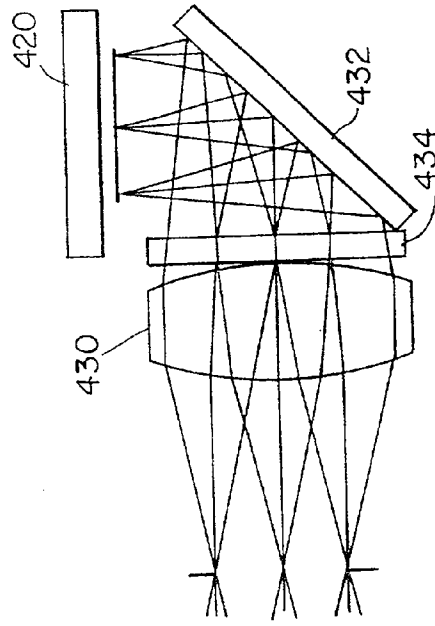


FIGURE 56

HEAD-MOUNTED MATRIX DISPLAY

RELATED APPLICATION

[0001] This is a continuation of application Ser. No. 08/579,448 which was filed Dec. 27, 1995, which was a file wrapper continuation of application Ser. No. 08/220,042, which was filed Mar. 30, 1994, which is a Continuation-in-Part of U.S. application Ser. No. 08/141,133, filed on Oct. 22, 1993, the contents of which are incorporated herein by reference.

BACKGROUND OF THE INVENTION

[0002] Head mounted display systems have been developed for a number of different applications including use by aircraft pilots and for simulation such as virtual imaging. Head mounted displays are generally limited by their resolution and by their size and weight.

[0003] Existing displays have relatively low resolution, and because of the size and weight of available systems, these displays are positioned at the relatively large distance from the eye. Of particular importance, it is desired to keep the center of gravity of the display from extending upward and forward from the center of gravity of the head and neck of the wearer, where it will place a large torque on the wearer's neck and may bump into other instruments during use.

[0004] There is a continuing need to present images to the wearer of a helmet mounted display in high-resolution format similar to that of a computer monitor. The display needs to be as non-intrusive as possible, leading to the need for lightweight and compact system. Existing head mounted displays have used analog cathode ray tube ("CRT") devices mounted above or to the side of the user's head which project an image onto a surface or visor mounted in front of the user's eyes. Often these displays utilize helmets which incorporate earphones into the helmet. Other head mounted display devices have contemplated the use of liquid crystal devices that could be mounted above or to the side of the user's head and employ reflective optics to direct an image within the field of view of the user.

SUMMARY OF THE INVENTION

[0005] In accordance with the present invention a head mounted display includes a housing in which a pair of matrix display elements are secured. These display elements are of a sufficiently light-weight and compact nature that the housing can be mounted onto the head of a user with a pair of hinge mounted arms or support elements that can be rotated relative to the housing from a closed position to an open position. When in the open position the arms extend about the opposite side of the user's head and serve to position audio transducers mounted on the arms into proximity with the ears of the user. The arms can also be double hinged in which each arm is folded once about its mid-point and then rotated about the hinge on each side of the housing to assume the closed position. System electronics and manually adjustable controls can be positioned within the housing or the rotating arms. Positioning of the electronics and controls within the arms permits a more desirable distribution of weight evenly about the sides of the user's head.

[0006] The inter-pupillary distance between the two displays can be adjusted such as by the use of a gear driven cam assembly mounted within the housing.

[0007] The direct view display can be a transmission type display with the light source directly adjacent the light valve active matrix and mounted within the display device. The transmission type display can, in a preferred embodiment, also receive light directly from the user's environment so that the display overlays an image over the users existing field of view.

[0008] In an alternative embodiment the display can be formed with a pivoting headband and an audio system.

[0009] Alternatively, the display can be an emission type device such as an active matrix electroluminescent display or an active matrix of light emitting diodes (LEDs), or a transmissive passive matrix display.

BRIEF DESCRIPTION OF THE DRAWINGS

[0010] The above and other features of the invention, including various novel details of construction and combinations of parts, will now be more particularly described with reference to the accompanying drawings and pointed out in the claims. It will be understood that the particular head mounted display embodying the invention is shown by way of illustration only and not as a limitation of the invention. The principles and features of this invention may be employed in varied and numerous embodiments without departing from the scope of the invention.

[0011] FIG. 1A is an exploded perspective view of a flat panel display in accordance with the invention.

[0012] FIG. 1B is a circuit diagram illustrating the driver system for a preferred embodiment of the invention.

[0013] FIGS. 2A-2L is a preferred process flow sequence illustrating the fabrication of a circuit panel for a flat panel display.

[0014] FIG. 3 is a cross-sectional view of a preferred embodiment of the display panel.

[0015] FIG. 4 illustrates in a perspective view a preferred embodiment of a system used for recrystallization.

[0016] FIG. 5A illustrates the use of a patterned release layer to entrain boundaries in a crystallized material.

[0017] FIG. 5B illustrates the use of a patterned capping layer to entrain boundaries.

[0018] FIG. 6A illustrates the drain current and transconductance characteristics for a MOSFET prior to transfer to glass in accordance with the invention.

[0019] FIG. 6B illustrates the drain current and transconductance characteristics for the MOSFET of FIG. 6A after transfer to glass.

[0020] FIG. 7A illustrates the drain current of the device in FIG. 6A plotted on a logarithmic scale at two different drain voltages.

[0021] FIG. 7B illustrates the drain current of the device in FIG. 6B plotted on a logarithmic scale at two different drain voltages.

[0022] FIG. 8A illustrates the drain current output of the device of FIG. 6A with the gate voltage varying between 0 and 5 volts.

- [0023] FIG. 8B illustrates the drain current output of the device of FIG. 6B with the gate voltage varying between 0 and 5 volts.
- [0024] FIG. 9 is a circuit diagram illustrating the driver system for a projection device of the present invention.
- [0025] FIGS. 10A-10D are a preferred process and transfer sequence for fabricating a light valve matrix and transferring it to a support structure.
- [0026] FIGS. 11A-11C are another preferred process and transfer sequence for fabricating a light valve matrix and transferring it to a support structure.
- [0027] FIGS. 12A-12E are yet another preferred process and transfer sequence for fabricating a matrix and transferring it to glass substrate.
- [0028] FIG. 13 is a perspective view of another embodiment of an active matrix slide assembly of the present invention.
- [0029] FIGS. 14 and 15 are circuit diagrams illustrating two preferred driver systems for the active matrix slide assembly of FIG. 13.
- [0030] FIG. 16 is a top view of a semiconductor wafer which can be processed to provide a plurality of active matrices for use in active matrix slide assemblies.
- [0031] FIG. 17 is an exploded perspective view of an active matrix transmission display employing a color filter system of the present invention.
- [0032] FIGS. 18A-18C is a preferred process flow sequence illustrating the SIMOX process for fabricating a single crystal silicon layer.
- [0033] FIG. 19 illustrates the Van der Waals bonding approach for providing a single crystal silicon layer.
- [0034] FIGS. 20A-20B is a preferred process flow sequence illustrating the bonded wafer process for forming a single crystal silicon layer.
- [0035] FIGS. 21A-21G is a preferred process flow sequence illustrating the fabrication of a transmissive active matrix color display.
- [0036] FIGS. 22A-22K is another preferred process flow sequence illustrating the fabrication of a transmissive active matrix color display.
- [0037] FIG. 23 is a cross-sectional view of the active matrix color display structure fabricated in accordance with FIGS. 22A-22K.
- [0038] FIGS. 24A-24H is a process flow sequence using negative photoresist materials for fabrication of an array of color filter elements.
- [0039] FIGS. 25A-25J is a preferred process flow sequence illustrating in cross-sectional views a photographic development process for fabricating an array of color filter elements.
- [0040] FIGS. 26A-26D is another preferred process flow sequence illustrating the fabrication of a transmissive active matrix color display.
- [0041] FIG. 27 is an explode perspective view of an electroluminescent color display in accordance with the present invention.
- [0042] FIGS. 28A-28E is a preferred process flow sequence illustrating the fabrication of an electroluminescent active matrix color display.
- [0043] FIGS. 29A-29C is a preferred process flow sequence illustrating the transfer of an electroluminescent active matrix color display to an optically transmissive substrate.
- [0044] FIG. 30 is an illustration of a patterned pixel electrode element.
- [0045] FIG. 31 is an illustration of a head-mounted active matrix display system.
- [0046] FIG. 32 is a rear perspective view of a preferred embodiment of the invention.
- [0047] FIG. 33 is a perspective view of a preferred embodiment of a wiring harness.
- [0048] FIG. 34 is a top plan view of the preferred embodiment of FIG. 32 showing the placement of the wiring harness of FIG. 33.
- [0049] FIG. 35 is an exploded view of an optical assembly for use in a transmissive display system.
- [0050] FIG. 36 is an exploded view of a preferred embodiment of an optical assembly for use in an emissive display system.
- [0051] FIG. 37 is a top plan view showing the embodiment of FIG. 32 in a stowed position.
- [0052] FIG. 38 is an exploded perspective view of a preferred embodiment of cam assembly for the pivot point 39 of FIG. 37.
- [0053] FIGS. 39A-39B are partial perspective views of another preferred embodiment for storing the stems 30 of FIG. 32.
- [0054] FIG. 40 is a perspective view of an alternative embodiment of the invention.
- [0055] FIG. 41 is a front view of an alternative embodiment of the invention.
- [0056] FIG. 42 is a top view of an alternative embodiment of the invention.
- [0057] FIG. 43 is a side view of an alternative embodiment of the invention.
- [0058] FIG. 44 is a back view of an alternative embodiment of the invention.
- [0059] FIG. 45 is a bottom view of an alternative embodiment of the invention.
- [0060] FIG. 46 is a top perspective view of the alternative embodiment in a closed position.
- [0061] FIG. 47 is a bottom perspective view of the closed position.
- [0062] FIGS. 48A-48B are detailed views of the sliding assembly.

[0063] FIG. 49A-49B are further detailed views of the spool assembly and cable management system.

[0064] FIG. 50 is a perspective view of an optical module.

[0065] FIG. 51 shows two modules mounted on a rail assembly.

[0066] FIG. 52 is a perspective view of the optics housing.

[0067] FIG. 53 is a cross-sectional side view of the optics.

[0068] FIG. 54 illustrates the full down and full up position of the focus adjusting system.

[0069] FIG. 55 shows the focus slide and backlight housing.

[0070] FIG. 56 is an alternative embodiment of the optical system for a high resolution display.

DETAILED DESCRIPTION OF THE INVENTION

[0071] A preferred embodiment of the invention is illustrated in the perspective view of a panel display in FIG. 1. The basic components of the display include a light source 10 that can be white or some other appropriate color, a first polarizing filter 12, a circuit panel 14, a filter plate 16 and a second polarizing filter 17, which are secured in a layered structure. A liquid crystal material (not shown) is placed in a volume between the circuit panel 14 and the filter plate 16. An array of pixels 22 on the circuit panel 14 are individually actuated by a drive circuit having first 18 and second 20 circuit components that are positioned adjacent the array such that each pixel can produce an electric field in the liquid crystal material lying between the pixel and a counterelectrode secured to the color filter plate 16. The electric field causes a rotation of the polarization of light being transmitted across the liquid crystal material that results in an adjacent color filter element being illuminated. The color filters of filter plate system 16 are arranged into groups of four filter elements such as blue 24, green 25, red 27, and white 29. The pixels or light valves associated with filter elements 24, 25, 27, 29 can be selectively actuated to provide any desired color for that pixel group.

[0072] Other preferred embodiments employ the use of a solid state material to form a light valve for each pixel. A light emitting material such as an electroluminescent film or any material whose optical transmission properties can be altered by the application of an electric field can be used to supply the light valves of the present invention.

[0073] A drive circuit that can be used to control the display on the panel is illustrated in FIG. 1B. Circuit 18 receives an incoming signal and sends a signal to the pixels through buses 13. Circuit 20 will scan through buses 19 to turn on the individual transistors 23 which charges capacitor 26 in each pixel. The capacitor 26 sustains the charge on the pixel electrode and the liquid crystal 21 until the next scan of the array. The various embodiments of the invention may, or may not, utilize capacitors with each pixel depending upon the type of display desired.

[0074] FIGS. 2A-2L illustrate the use of an Isolated Silicon Epitaxy (ISE) process, to form silicon-on-insulator (SOI) films in which circuit panel circuitry is formed. Note that any number of techniques can be employed to provide a thin-film of single crystal Si. An SOI structure, such as that

shown in FIG. 2A, includes a substrate 30 and an oxide 34 (such as, for example, SiO₂) that is grown or deposited on the substrate 30. A thin single crystal layer of silicon is formed over the oxide 34. The oxide (or insulator) is thus buried beneath the Si surface layer. For the case of ISE SOI structures, the top layer is a substantially single-crystal recrystallized Silicon, from which CMOS circuits can be fabricated. The use of a buried insulator provides devices having higher speeds than can be obtained in conventional bulk (Czochralski) material. Circuits containing in excess of 1.5 million CMOS transistors have been successfully fabricated in ISE material.

[0075] As shown in FIG. 2B, the film 38 is patterned to define a transistor region 37 and a pixel electrode region 39 for each pixel. An oxide layer 40 is then formed over the patterned regions including channel 48 between the two regions 37, 39 of each pixel. The intrinsic crystallized material 38 is then implanted 44 (at FIG. 2C) with boron or other p-type dopant to provide a n-channel device (or alternatively, an n-type dopant for an p-channel device).

[0076] A polycrystalline silicon layer 42 is then deposited over the pixel and the layer 42 is then implanted 46, as seen in FIG. 2D, with an n-type dopant to lower the resistivity of the layer 42 to be used as a gate. The polysilicon is patterned to form the gate 50, as seen in FIG. 2E, which is followed by a large implant 52 of boron to provide p+ source and drain regions for the transistor. As shown in FIG. 2F, an oxide 54 is formed over the transistor and openings 60, 56, 58 are formed through the oxide 54 to contact the source 66, the drain 64, and the gate, respectively. A patterned metalization 70 of aluminum, tungsten or other suitable metal is used to connect the exposed pixel electrode 62 to the source 60 (or drain), and to connect the gate and drain to other circuit panel components.

[0077] A second fabrication procedure is one of the substrate release processes that have been developed to form thin (1 to 5 micron) films of processed silicon bonded to glass; these films contain active semiconductor devices such as FETs that are partially or completely fabricated prior to transfer. The crystallization and release procedures including the cleavage of laterally grown epitaxial films for transfer (CLEFT) approach are described more fully in U.S. Pat. No. 4,727,047 incorporated herein by reference. The chemical epitaxial lift-off (CEL) approach is described more fully in U.S. Pat. Nos. 4,846,931 and 4,883,561. Both of the CLEFT and CEL techniques permit the reuse of the substrate, leading to reduced cost compared to other approaches in which the substrates are consumed. By combining thin film release techniques with SOI wafers, we will be able to form the required high quality films and circuits on glass.

[0078] The foregoing indicates that CEL processes can be limited by the lateral distance that is required for the HF (or other etchant) undercut of the release layer. The key to large area panels using CEL is the release layer. The key to large area panels using CEL is the release of patterned devices and/or circuits rather than complete large-area films, because the circuits or devices have unused areas that can be used as vertical channels through the film to allow the etch to reach the release layer. This approach is illustrated in FIGS. 2H-2L. To remove the circuit from the release substrate a first opening 70 (in FIG. 2H) is formed in an exposed region of layer 36 that occurs between pixels. A

second larger portion of layer 34 is than removed to form cavity 72 such that a portion of layer 36 extends over the cavity 72.

[0079] In FIG. 2I, a support post 76 is formed to fill cavity 72 and opening 70, and which extends over a portion of layer 36. Openings or via holes 74 are then provided through layer 36 such that an etchant can be introduced through holes 74, or lateral openings 78, to remove layer 34 (see FIG. 2J). The remaining insulating layer 36 and the circuitry supported thereon is now held in place relative to substrate 30 with support posts 76.

[0080] An epoxy that can be cured with ultraviolet light is used to attach an optically transmissive substrate 80 to the circuitry, and layer 36. The substrate 80 is than patterned such that regions of epoxy 82 is cured (see FIG. 2K). The substrate 30 and posts 76 are removed to provide the structure shown in FIG. 2L, which is than processed to provide the desired display panel.

[0081] Note that the UV-cured adhesive (or tape) can be patterned to protect the circuits where necessary, and HF can be used to reach the remaining the release layer.

[0082] Note that where the tape is used, tape provides support to the circuits after release. Large area GaAs devices containing films have been fabricated in this way, and these have been released to form devices from entire wafers on one tape. The released circuits can be remounted on the glass and the other elements of the liquid crystal display panel. Transparent adhesives are the preferred method of mounting.

[0083] To form the final display panel the circuit panel shown in FIG. 2L is etched leaving the desired pixel elements exposed. Insulation and alignment layers, spacers, a sealing border and bonding pads for connections as added onto the circuit panel. A screen printing process can be used to prepare the border. The plate containing the color filters and the counterelectrode is sealed to the circuit panel with the sealing border after insertion of spacers. The display is filled with the selected liquid crystal material via a small filling hole or holes extending through the border. This filling hole is then sealed with a resin or epoxy. First and second polarizer films or layers are than bonded to both sides and connectors are added. Finally, a white light source 114, or other suitable light source, is coupled to polarize 112.

[0084] A cross-sectional view of the resulting device is shown in FIG. 3 wherein pixel electrodes 102 and 104 are laterally spaced from each other. Each pixel 102, 104 will have a transistor 106 and a color filter 120, 122 associated therewith. Polarizing elements 112, 118 are positioned on opposite sides of the structure which also includes bonding element or adhesive 108 and optically transmissive substrate 110, such as glass or plastic. Layer 108 can be a transparent epoxy or a low temperature glass that can have a thickness of 2-10 microns.

[0085] The CLEFT process permits the separation of a thin single-crystal films, grown by chemical vapor deposition (CVD), from a reusable homoepitaxial substrate. Unlike the CEL process, in the CLEFT process the circuits or devices are first bonded to glass and after mounting the separation is made between the circuits and the substrate.

[0086] The films removed from the substrate by CLEFT are essentially single-crystal, of low defect density, are only

a few microns thick, and consequently the circuit panel has little weight and good transmission characteristics. For the purposes of the present application, the term "essentially single crystal" means a film in which a majority of crystals extend over a cross sectional area in a plane of the film of at least 0.1 cm², and preferably in the range of 0.5-1.0 cm or more.

[0087] The CLEFT process, illustrated in U.S. Pat. No. 4,727,047 involves the following steps: growth of the desired thin film over a release layer (a plane of weakness), formation of metallization and other coatings, formation of a bond between the film and a second substrate such as glass (or superstrate), and separation along the built-in-plane of weakness by cleaving. The substrate is then available for reuse.

[0088] The CLEFT process is used to form sheets of essentially single crystal material using lateral epitaxial growth to form a continuous film on top of a release layer. For silicon the lateral epitaxy is accomplished by the ISE process or other recrystallization procedures. Alternatively, other standard deposition techniques can be used to form the necessary thin-film essentially single crystal material.

[0089] One of the necessary properties of the material that forms the release layer is the lack of adhesion between the layer and the semiconductor film. Since a weak plane has been created by the release layer, the film can be cleaved from the substrate without any degradation. The release layers can comprise multi-layer films of Si₃N₄ and SiO₂. Such an approach permits the SiO₂ to be used to passivate the back of the CMOS logic. (The Si₃N₄ is the layer that is dissolved to produce the plane of weakness.) In the CLEFT approach, the circuits are first bonded to the glass, or other transfer substrate, and then separated resulting in simpler handling as compared to W-cured tape.

[0090] In the ISE process, the oxide film is strongly attached to the substrate and to the top Si film which will contain the circuits. For this reason, it is necessary to reduce the strength of the bond chemically. This technique involves a release layer that is preferentially dissolved with an etchant without complete separation, to form a plane of weakness in the release layer. The films can then be separated mechanically after the glass is bonded to the circuits and electrodes.

[0091] Mechanical separation is accomplished as follows: The upper surface of the film is bonded with a transparent epoxy to a superstrate such as glass. The film and glass are then bonded with wax to glass plates about 5 mm thick that serve as cleaving supports. A metal wedge is inserted between the two glass plates to force the surfaces apart. Since the mask has low adhesion to the substrate, the film is cleaved from the substrate but remains mounted on the glass. The substrate can then be used for another cycle of the CLEFT process, and the device processing is completed on the back surface of the film. Note that since the device remains attached to a superstrate, the back side can be subjected to standard wafer processing, including photolithography.

[0092] The method further involves the preparation of single crystal films, with seeding in the case of an Si substrate and without seeding for the case of foreign substrates. For the case of seeded Si films, the standard recrystallization process is employed. In either case, the bottom oxide or nitride layer can be optimized for release purposes.

[0093] In one embodiment of the recrystallization system, shown schematically in FIG. 4 the substrate temperature is elevated to near the melting point by a lower heater 130. An upper wire or graphite strip heater 132 is then scanned across the top of the sample 134 to cause a moving melt zone 136 to recrystallize or further crystallize the polycrystalline silicon. In the standard process on Si, the lateral epitaxy is seeded from a small opening through the lower oxide, and the resultant single crystal film has the orientation of the substrate. Capping layer 138 is deposited over the polycrystalline material prior to crystallization.

[0094] The use of foreign substrates precludes seeding. In this case, essentially single crystal Si is obtained by grain boundary entrainment techniques. Grain boundary entrainment can be used by patterning either the release oxide or the cap layer to introduce a modulation in the thermal gradients in the regrowth region. This modulation in the temperature field changes the location of the melt front and entrains the boundaries in predictable locations. Patterning of the release oxide 142 is shown in FIG. 5A. In this embodiment the substrate 140 has grooves 150 which are filled with the release oxide 142. Owing to this entrainment of boundaries 148 in the crystallized material 144 that can extend between the cap 146 and the release layer 142, the Si circuits or electrodes can be located in regions of high quality. Metallization and other features can be located over subgrain boundaries.

[0095] As shown, a preferable technique is to pattern the reusable substrate with the necessary entrainment structure. Once patterned in this way, the reusable substrate would not require repatterning. In such a scheme the entraining grooves are provided with a material of sufficient thickness to entirely fill the grooves. The material in the grooves could for example, comprise planarized Si_3N_4 , while the release layer could comprise further deposition of SiO_2 . Alternatively, the grooves could be filled entirely with SiO_2 ; the grooves could then function as channels for the release etch.

[0096] A second approach involves patterning the cap layer 145 after cap deposition, as shown in FIG. 5B. Patterned ridges 147 of the cap 145 overlie boundaries 148 in the recrystallized material that can extend between the cap 145 and release layer 141. A third approach would be to pattern the polycrystalline silicon layer.

[0097] Capping layers can be used with foreign substrates. The capping layer must be adherent throughout the thermal cycle, but must be removable for device processing. A cap works well for smooth Si substrates, but the patterned layers necessary for entrainment can require new films.

[0098] FIGS. 6-8 illustrate the electrical characteristics of a MOSFET made in accordance with the invention before and after transfer onto a glass substrate. FIG. 6A graphically depicts the drain current I_D and the transconductance G_M as a function of gate voltage V_G in the linear region, where the drain-source voltage is 50 mV, for a MOSFET prior to transfer to glass. The MOSFET has a width-to-length ratio of $250 \mu\text{m}/20 \mu\text{m}$ and a gate oxide thickness of 890 Å in a $0.5 \mu\text{m}$ thick recrystallized silicon material. FIG. 6B shows the drain current I_D and transconductance G_M of the same device after transfer to glass.

[0099] FIG. 7A graphically illustrates the drain current of the device of FIG. 6A plotted on a logarithmic scale at two drain-source voltages $V_{DS}=50 \text{ mV}$ and $V_{DS}=5\text{V}$.

[0100] FIG. 7B graphically illustrates the drain current of the device in FIG. 6B plotted on a logarithmic scale at drain-source voltages of $V_{DS}=50 \text{ mV}$ and $V_{DS}=5\text{V}$.

[0101] FIG. 8A graphically illustrates the drain current I_D as a function of drain-source voltage of the device of FIG. 6A at gate voltages of $V_{GS}=0, 1, 2, 3, 4$ and 5 volts.

[0102] FIG. 8B graphically illustrates the drain current I_D as a function of drain-source voltage of the device of FIG. 6B at gate voltages of $V_{GS}=0, 1, 2, 3, 4$ and 5 volts. Referring to FIG. 9, an active matrix 600 comprises a plurality of light valves which are individually actuated by colocated driver circuitry (see FIG. 1B). The colocated driver circuitry is controlled by supporting driver circuitry which includes a video conditioning circuit 602, a system clock 604, an optional amplitude to pulse duration (APD) converter 606, column drivers 608, and a row drivers 610.

[0103] The video conditioning circuit 602 receives a video input signal which may be an RGB signal, an NTSC signal or other video format signal, or any digital or analog signal. The conditioning circuit processes the incoming signal producing separate video output signals (on lines, 611, 612 and 613) for each primary color and a synchronization signal (on line 615) for the column and row drivers 608 and 610. The video output signal on line 611 is a serial data stream wherein the amplitude of each signal of the data stream determines the intensity of light transmitted through each light valve.

[0104] If the APD convertor is not employed, the serial data stream on line 615 is received by the row drivers 610. The row drivers 610 send each of the signal data streams to the light valves through buses 618. The column drivers receive the sync signal on line 615 and, responsive to the sync signal, will be sent through buses 619 to turn on individual transistors allowing the associated signal of the data stream to charge the capacitor in each pixel. The capacitor sustains a charge, which is proportioned to the amplitude of the associated signal, on the light valve until the next scan of the array.

[0105] Alternately, the ADP convertor may be employed such that each signal of the video output data stream is converted to a pulse having a pulse width which is proportional to the signal's amplitude. In any case, the driver circuit operates in the same manner as previously described.

[0106] Projection display devices of the present invention can employ light valve matrices having pixel densities which satisfy any of a wide range of the following existing computer display format requirements:

Application	Display Format (Column × Row)
1) Common Personal Computer	1024 × 768 1280 × 1024
2) Workstation (Advanced Personal Computer)	1580 × 1280 2048 × 2048
3) Other Workstations (Non-Standard)	1152 × 900 1280 × 1024 1600 × 1280

[0107] Thus, a display monitor employing one or more single crystal silicon light valve matrices having any of the above-described pixel densities may be provided in accordance with the present invention.

[0108] One feature of the present invention is that projection devices employing single crystal light valve matrices provide high resolution images. High resolution images are possible because high density light valve arrays may be formed in single crystal silicon films. Referring to Table 1, the light valve diagonal is shown for various array sizes and pixel densities. Note that the diagonal dimensions followed by an asterisk indicate the array is compatible with 35 mm optics. The use of 35 mm optics is a key feature in minimizing the size, weight and cost of the described optics requiring the light valve image designed dimension to be no greater than 42 mm (1.654 inches). Therefore, it is desirable to use a light valve imaging technology that provides the highest density of information content. It is likely that the light valve technology discussed herein is compatible with as-fabricated densities of 2000 dots-per-inch. This allows projection of high resolution images using compact, low cost and widely available optical components. The small size of the light valve allows the use of small format condenser lens assembly dichroic mirrors and prisms and projection lens. Subsequently, the package size of the described projector and monitor can be maintained at small dimensions and component weight is similarly minimized. Appropriate 35 mm format optical components are widely available and can be obtained at low cost relative to large and/or custom optical components. For projector and monitor requirements that cannot be met with a 35 mm compatible light valve, larger conventional or custom optical components may be employed. Due to the minimum size of a particular light valve format afforded by the described light valve technology, similar cost, size and weight advantages are translated to the procurement of custom optical components.

[0109] As has been described, the light valve technology described herein can be used to implement projection arrays of 1024x768 through 2048x2048 pixels using 35 mm format optical components. This will permit the execution of high resolution color and monochrome image projectors and monitors at relatively compact dimensions and low weight.

[0110] One implementation of the monitor is to form a 17.5 inchx11.5 inch image suitable for the display of two side-by-side 8.5 inchx11 inch pages with additional screen room for data window access. The use of the described light valve and projection technology would allow the physical format of the monitor to be less than 22 inches high, less than 20 inches wide, and less than 10 inches deep. The use of a single 150 to 300 watt metal-halogen lamp in this implementation would provide the rear-proportion screen image at a brightness of 25 foot-Lamberts or greater. The choice of screen material could include a simple diffuser for maximum viewing angle or a lenticular configuration for maximum brightness over a reduced solid viewing angle.

[0111] TABLE 1. DIAGONAL ARRAY DIMENSION—INCHES/(MM)

[0112] Fabricated dots/inch (DPI) on light valve matrix

ARRAY SIZE	800	1000	1200	2000
1024 x 768	1.600* (40.64)	1.280* (32.51)	1.137* (28.88)	0.640* (16.26)
1280 x 1024	2.049 (52.04)	1.639* (41.63)	1.366* (34.70)	0.820* (20.82)
1580 x 1280	2.542 (64.56)	2.033 (51.65)	1.695 (43.05)	1.017* (25.82)
2048 x 2048	3.620 (91.96)	2.896 (73.57)	2.414 (61.32)	1.448* (36.78)

[0113] Another feature of the present invention is that a projection display device employing single crystal silicon light valve matrices provides images with high brightness. To accomplish this, each single crystal silicon light valve matrix employed in a projection display device has a high optical aperture which is defined as the percentage of transparent area to total matrix area. Table 2 provides the optical aperture for various light valve arrays. It is noted that in general the minimum acceptable optical aperture for an array is 40%. As indicated by Table 2, as pixel density increases, which increases image resolution, optical aperture decreases. However, reducing the switching device size and/or the interconnect size for a given pixel density will increase the optical aperture.

TABLE 2

OPTICAL APERTURE COMPUTATIONS				
Transistor length (um)	3	3	3	3
Transistor width (um)	6	6	6	6
Line width (um)	2	4	6	8
lines per inch	1000	1000	1000	1000
pixel size (um)	25.4	25.4	25.4	25.4
grid shadow (sq. um)	97.6	187.2	268.8	342.4
trans. shadow (sq. um)	18	18	18	18
pixel area (sq. um)	645	645	645	645
Packing Factor (%)	85	85	85	85
OPTICAL APERTURE (%)	69.8	58.0	47.2	37.5
Transistor length (um)	3	3	3	3
Transistor width (um)	6	6	6	6
Line width (um)	2	4	6	8
lines per inch	800	800	800	800
pixel size (um)	31.8	31.8	31.8	31.8
grid shadow (sq. um)	123	238	345	444
trans. shadow (sq. um)	18	18	18	18
pixel area (sq. um)	1008	1008	1008	1008
Packing Factor (%)	85	85	85	85
OPTICAL APERTURE (%)	73.1	73.1	73.1	73.1
Transistor length (um)	3	3	3	3
Transistor width (um)	6	6	6	6
Line width (um)	2	4	6	8
lines per inch	1200	1200	1200	1200
pixel size (um)	21.2	21.2	21.2	21.2
grid shadow (sq. um)	00.7	153.3	218.0	247.7
trans. shadow (sq. um)	18	18	18	18
pixel area (sq. um)	448	448	448	448
Packing Factor (%)	85	85	85	85
OPTICAL APERTURE (%)	66.3	52.5	40.2	29.5
Transistor length (um)	3	3	3	3
Transistor width (um)	6	6	6	6
Line width (um)	2	4	6	8
lines per inch	2000	2000	2000	2000
pixel size (um)	12.7	12.7	12.7	12.7
grid shadow (sq. um)	46.8	85.6	116.4	139.2
trans. shadow (sq. um)	18	18	18	18
pixel area (sq. um)	161.3	161.3	161.3	161.3

TABLE 2-continued

OPTICAL APERTURE COMPUTATIONS				
Packing Factor (%)	85	85	85	85
OPTICAL APERTURE (%)	50.9	30.4	14.2	2.2

[0114] In another preferred embodiment, a growth and transfer process is employed to provide a thin-film of single crystal silicon positioned on glass as shown in FIGS. 15A-15D. Referring to FIG. 10A, a buffer (insulator) layer 528 of silicon is epitaxially grown on a silicon substrate 526. A strained GeSi layer 530 is epitaxially grown on the buffer layer 528 and an upper layer 532 of single crystal silicon is epitaxially grown on the GeSi layer. The strained layer 530 should be thin, on the order of a few hundred angstroms, to avoid misfit defect formation that would thread into the upper silicon layer 532.

[0115] Referring to FIG. 10B, integrated circuit processing techniques, such as any of the techniques previously described herein, are employed to form light valve matrix circuitry 534 in the single crystal silicon layer 532. Next, the processed wafer is mounted with an epoxy adhesive of the type described below to a glass or plastic support 536 (FIG. 10C). The epoxy fills in the voids formed by the processing and adheres the front face to the support 536. The silicon substrate 526 and buffer layer 528 are etched off with the GeSi layer 530 serving as an etch stop layer (FIG. 10D). The GeSi layer could then be selectively etched away without effecting the silicon film 532.

[0116] FIGS. 11A-11C illustrate another preferred process for transferring and adhering circuits of thin films of silicon to a glass substrate. The starting structure is a silicon wafer 718 upon which an oxide layer 716 and a thin film of poly-Si, a-Si or x-Si 714 is formed using any of the previously described processes such as ISE or CLEFT. A plurality of circuits, such as pixel electrodes, TFT's, Si drivers and Si logic circuits, are then formed in the thin film. FIG. 11A shows three such wafers, A, B, C. In wafer A, logic circuits 740 are formed. In wafer B, pixel electrodes 762 and TFT's 751 are formed. In wafer C, driver circuits 720 are formed. A wafer is attached to a superstrate transfer body 712, such as glass or other transparent insulator, using an adhesive 721. Preferably the adhesive is comprised of an epoxy, such as, a cycloaliphatic anhydride; for example; for example, EP-112 LS made by Masterbond Inc. The adhesive must satisfy the following criteria:

[0117] Excellent spectral transmission in the visible range;

[0118] Good adhesion to glass, oxides, metals, nitrides;

[0119] No reactions with glass, metals, oxides, nitrides;

[0120] Low shrinkage;

[0121] Low warp/stress;

[0122] Able to tolerate acids or bases at 100 C for extended periods without lifting, losing adhesion, or degrading;

[0123] Able to withstand 180 C for 2 hours with no optical change;

[0124] Good resistance to acids and solvents;

[0125] Able to tolerate dicing and heating step (including an acid etch step with no lifting);

[0126] Low viscosity to allow thin adhesive films; and

[0127] Ability to be vacuum degassed to eliminate all bubbles.

[0128] In general, the cycloaliphatic anhydrides meet most of the above criteria. The epoxy preferably has a low cure temperature to minimize shrinkage, a very low ion content (<5 ppm) and spectral stability over extended time periods.

[0129] The wafer is attached, using the adhesive 721, to a glass superstrate 712. The adhesive is vacuum degassed to eliminate all bubbles. The sandwich structure is then cured at a low temperature of about 100 C for 4-8 hours which causes the adhesive to gel and minimizes the shrinkage characteristics. Then the adhesive is fully cured at a higher temperature of about 160° C. for about 8 hours. This cure assures that the bonds are fully matured. Without this cure, the adhesive will not stand up to the subsequent acid etching step.

[0130] The wafer, is then cleaned and the native oxide 716 is etched off the back surface. The wafer is put into a solution (KOH or equivalent) of 25 grams to 75 ml H₂O at 100 C. Depending on the thickness of the wafer, it may take up to 5 hours to etch the Si 718 and oxide 716 layers. The solution etches silicon very rapidly, i.e. 2 to 3 microns/min., and uniformly if the wafers are held horizontally in the solution with the etching surface face up. The etchant has a very low etch rate on oxide, so that as the substrate is etched away and the buried oxide is exposed, the etching rate goes down. The selectivity of the silicon etch rate in KOH versus the oxide etch rate in KOH is very high (200:1). This selectivity, combined with the uniformity of the silicon etching, allows the observer to monitor the process and to stop the etch in the buried oxide layer 716 without punching through to the thin silicon layer 714 above it. Wafers up to 25 mils thick and oxides as thin as 4000 Å have been successfully etched using this process. An alternative etchant is hydrazine, which has a much higher etch rate selectivity or ethylene diamine pyrocaccol (EDP).

[0131] When the silicon is completely gone, the vigorous bubbling, which is characteristic of silicon etching in KOH, abruptly stops, signalling that the etching is complete.

[0132] The thin films 714 transferred to the respective glass superstrates 712 are now rinsed and dried. If not already provided with circuits 740, 751, 762, or 720, the films 714 can be backside circuit processed if desired, since the epoxy adhesive 720 has very good resistance to chemicals. In addition, the epoxy is very low in stress, so that the thin film is very flat and can go through conventional photolithography steps.

[0133] In the aforementioned light valve matrix fabrication processes, disclination defects in the liquid crystal material may be induced by non-planar circuit topography formed in the film resulting in irregular stacking and subsequent image aberration. Planarized circuitry would elimi-

nate the disclination problem. An option is to use the oxide layer after transfer of the film to the optically transmissive substrate to provide a planar surface. The oxide layer is planar or substantially planar (i.e. uniformities of <1 micron across its surface) such that an even topography is provided. Then any necessary shielding or pixel circuitry can be formed to produce a planarized circuit substantially free of disclination.

[0134] In the aforementioned embodiments, it is noted that light valve matrices having a diagonal of 1-2 inches do not require spacers in the liquid crystal volume (see FIG. 1A). Since spacers are non-transmissive elements, eliminating them from the volume results in an improved optical aperture and thus increased brightness for the matrix. Also prevents optical aberration caused by spacers at small pixel geometries.

[0135] Due to the higher intensities of light used in projection systems that are necessary to provide the desired brightness, the sensitivity of the single crystal pixel transistors to the light source can impair performance. The light source can be a halogen lamp that produces between 100 and 1000 watts and preferably operates in the range of 150-300 watts. Other lights such as discrete lasers (RGB), cathodoluminescent light sources, and arc-lamps producing similar levels of power per unit area can also be used. It is therefore desirable to reduce the sensitivity of the active matrix to the light source. This is accomplished by shielding one or both sides of each transistor in the array with a light shield that will substantially attenuate the light directed or scattered toward each transistor. A metal or other optically opaque material can be used as a shield. When the shield is a metal it can also serve as an interconnect or a gate to the transistor being shielded. At normal incidence, a metal shield can completely attenuate light from the source at wavelengths at or above the silicon bandgap with thicknesses in the range of 2000-10,000 angstroms. Shielding can also be employed around the edge of the active matrix to attenuate or block light directed towards the peripheral circuitry.

[0136] In FIGS. 12A-12E a process for fabricating a double shielded active matrix array for a projection system is illustrated. The left figure shows a cross-sectional view of a pixel transistor of each step or embodiment. The right side illustration in FIGS. 12A-12C and 12E show a top view including the transistor 804, pixel area 811, and interconnect lines 808 and 810. In FIG. 12A there is shown the silicon substrate 800, oxide layer 802, source and drain 804 regions, a channel region 805, a second oxide layer 806, and portions of the interconnect lines 808 and 810 that serve as the gate and source connector for the transistor 804. FIG. 12B shows a third oxide layer 812 and holes 814 formed therein to provide a bridge interconnect between portions of line 808. In FIG. 12C is shown the formation of the first metal shield 816 over the oxide 812 and through holes 814 to interconnect lines 808. The first shield 816 has a surface area to substantially block normally incident light from reaching transistor 804 from one side of the circuit panel. The area of shield 816 should be minimized to maintain the optical aperture of the array. FIG. 12D illustrates the use of a body contact 822 fabricated after the transfer of the panel onto glass substrate 818 and formation of the second shield 820. The fabrication of such a body contact is described more fully in U.S. Ser. No. 07/823,858 filed on Jan. 22, 1992, which is incorporated herein by reference. In FIG. 12E there

is illustrated the use of a portion of the second shield 824 as a second back side gate 826. Gate 826 can be used to control the opposite side of the channel from the front side gate region 808. The present transfer process thus provides for additional back side processing to provide optical interconnects, optical shielding interconnects, and double sided gating of each or selected transistors in the array.

[0137] The light valve image projector and monitor configurations can be used for the applications beyond image presentation. These include image generation/projection for electronic printing and photographic image recording. In the former, the light valve and image projection optics can be used to form an image on an electrophotographic media (as in the imaging drum of xerographic or laser printer processors). The key advantage is that the entire two-dimensional image can be exposed at once. For photographic applications, the image can be projected onto photographic film or paper.

[0138] Color can be implemented in the projector or monitor through the use of color filters instead of dichroic mirrors. In one implementation, white light from a single or multiple lamps could be passed through each of red, green and blue filter to its incidence onto the appropriate color-assigned light valve. Alternatively, color filters can be fabricated directly on the light valve assembly. This could be done with a single color filter (e.g., red, green or blue) on a light valve or the specific alignment of color filters on the discrete elements constituting the light valve. The latter would allow a color image to be obtained using a single light valve but forces a factor of 3 or 4 reduction in color pixel density as the elements are assigned a red, green, or blue filter or a red, green blue and white filter respectively. Alternatively, subtractive color filters (yellow, cyan and magenta) would be similarly used.

[0139] A key criterion in the projector/monitor design is the management of heat generated by the lamp light source. A significant portion of this heat is in the form of infrared (IR) radiation emanating from the lamp. Methods of controlling this IR radiation are its absorption by an IR filter or its reflection by an IR "heat mirror" that allows high transmission of visible light to the subsequent optics. Another method is the use of a dichroic mirror that separates the IR radiation from the visible light path and directs the IR to directly exit the projector or monitor housing.

[0140] A light valve panel formed by the described technology is compatible with 35 mm format optics. Therefore, this imaging device can be fabricated such that the assembled device has equivalent physical dimensions as a standard 35 mm photographic transparency whose image is projected via a conventional and generally available 35 mm "slide projector". Thus, an embodiment of the light valve projector is to use a single light valve matrix panel with integral drive electronics, as described herein, that is packaged to be size equivalent with a standard mounted 35 mm transparency and insert this modular electronic imaging device into a 35 mm "slide projector" without modification in order to generate the projected image. The light valve imaging device is connected by a cable to control electronics as are described herein. In this embodiment, a single light valve panel could generate a monochrome image or a color image through the use of applied color filters as described elsewhere herein. The light valve panel used for this

embodiment can have the same fabricated element/pixel density as described for the other embodiments.

[0141] In preferred embodiment shown in FIG. 13, an active matrix slide assembly 900 includes an Active Matrix (AM) slide 902 and a remote electronics housing 904. The slide 902 is dimensioned to be positioned in the chamber 838 of a 35 mm slide projector 830. In contrast to previously described embodiments, the slide 902 is not physically connected to the electronics housing 904. Instead, the slide and the electronics in the housing communicate with each other via antennas elements 905 and 906 respectively. In preferred embodiments, the antennas can be a pair of RF antennas or an infrared transmitter element such as an infrared LED paired with an infrared receiver element which can be a photodiode elements. The antenna 905 can be integrated into a handle (not shown) to provide for manual insertion and removal from chamber 838.

[0142] Driver circuitry for the active matrix slide assembly of FIG. 13 is illustrated in FIGS. 14 and 15. Referring to FIG. 14, the driver circuitry includes the signal processing circuit 888, the system clock 890, the power conditioning circuit 891, column drivers 18, row drivers 20, a photovoltaic power source 908, a battery 910, an RF receiver 912 and a demultiplexer 914. The RF receiver 912 receives a stream of RF signals from the antenna 911. A demultiplexer 914 formats the RF signal stream such that it is can be processed by the previously-described signal processing circuit 888. The battery 910 and the photovoltaic power source 908, either individually or together, provide power to support the operations of the active matrix slide circuitry. The photovoltaic power source 908 can use slide projector light source energy to provide power to the active matrix slide and is therefore mounted onto the slide outer surface facing the light source (shown in FIG. 13).

[0143] Referring to FIG. 15, the driver circuitry includes the signal processing circuit 888, the system clock 890, the power conditioning circuit 891, column drivers 18, row drivers 20, a photovoltaic power source 908, a battery 910 and an infrared detector photodiode 913. The photodiode 913 receives infrared signals from the electronics (not shown) which are processed by the signal processing circuit 888.

[0144] As noted previously, an active matrix slide can be fabricated which has equivalent dimensions as a standard 35 mm slide. This can be accomplished because the previously described fabrication processes can produce a plurality of small active matrix circuit panels from a single wafer as shown in FIG. 16. Using a 6 inch silicon wafer 930, a number of active matrices can be produced from the wafer using any of the aforementioned processing techniques.

[0145] Another preferred embodiment of the invention is illustrated in the perspective view of a liquid crystal transmission display in FIG. 17. The basic components of the display include a light source 1000 that can be white or some other appropriate color, a first polarizing filter 1002, an optically transparent substrate 1004, a color filter array 1006, an active matrix circuit panel 1008, a counterelectrode 1010 and a second polarizing filter 1012, which are secured in a layered structure. A liquid crystal material 1014 is placed in a volume between the active matrix circuit panel 1008 and the counterelectrode 1010.

[0146] The circuit panel 1008 comprises an array of pixel elements 1016 formed in a surface 1018 of a thin film of

essentially single crystal silicon. The pixel elements 1016 are individually actuated by a drive circuit having first 18 and second 20 circuit components that are positioned adjacent the pixel array such that each pixel can produce an electric field in the liquid crystal material lying between the pixel 1016 and the counterelectrode 1010 secured to the polarizer 1012. The electric field causes a rotation of the polarization of light being transmitted across the liquid crystal material that results in an adjacent color filter element being illuminated. The color filter array 1006 is located adjacent to the circuit panel 1008 such that each color filter element is associated with a pixel element. The individual elements of color filter array 1006 can be grouped into an arrangement of three (or four) colors that can have any one of a number of geometric configurations such as a triad arrangement, a stripe arrangement or a quad arrangement. The three colors can be, for example, blue, green and red, or alternatively yellow, cyan and magenta, or any other group of colors that will provide the desired colors to be produced by the display. The four colors can be, for example, blue, green, red and white or yellow, cyan, magenta and white/black or any other group of four colors. The pixel elements 1016 or light valves associated with each filter element can be selectively actuated to provide any desired color for that pixel group.

[0147] A drive circuit that can be used to control the display is illustrated in FIG. 1B and was discussed previously or as described in U.S. Ser. No. 07/815,684, filed on Dec. 31, 1991.

[0148] The active matrix circuit panel is formed in or on a layer of essentially single crystal semiconductor material such as silicon. It is noted that any number of fabrication techniques, including those previously described herein, can be employed to provide thin films or layers of single crystal silicon.

[0149] The present invention includes other fabrication techniques which can be employed to provide thin layers of single crystal silicon. In one embodiment, the SIMOX fabrication process shown in FIGS. 18A-18C can be used. A single crystal silicon substrate 1003 shown in FIG. 18A receives an implant of $5 \times 10^{17}/\text{cm}^2$ to $2 \times 10^{18}/\text{cm}^2$ of oxygen atoms 1007 (FIG. 18B). The implant process can be performed at temperatures exceeding 650 C. Next, the wafer is subjected to a high temperature annealing process 1005 (at about 1300 C) for about six hours. Referring to FIG. 18C, the resulting structure has a buried oxide layer 1011 (thickness of about 4000 angstroms) below a single crystal layer 1009 (thickness of about 2000 angstroms). It is noted that a multiple implant and anneal procedure can be employed to further improve the crystallinity of the silicon layer.

[0150] In another embodiment, a thin film or layer of single crystal silicon can be secured on a quartz substrate by Van der Waals bonding. Referring to FIG. 19, a silicon thin film 1017 is located on a quartz substrate 1015. The film 1017 is secured to the substrate 1015 by an electrostatic force known as a Van der Waals force, which is an attractive force between two different atoms or nonpolar molecules. The Van der Waals force arises because a fluctuating dipole moment in one molecule-type (either silicon or quartz) induces a dipole moment in the other molecule-type, and the two dipole moments interact.

[0151] In another embodiment, a bonded wafer approach can be employed to provide a layer of single crystal silicon.

Referring to FIG. 20A, an oxide layer 1021 is formed on a single crystal silicon wafer 1023 by known techniques. A second single crystal silicon wafer 1019 is positioned on the oxide layer 1021. The wafer 1019 is then processed to obtain a thin layer of single crystal silicon (dashed lines). Any known processing techniques, such as lapping or etching, can be used to obtain the thin layer of single crystal silicon 1025 (FIG. 20B). Active matrix circuitry can be formed in the single crystal silicon layer 1025.

[0152] FIGS. 21A-21G illustrate a preferred fabrication process for forming an active matrix color display. Referring to FIG. 21A, an SOI structure includes a substrate 1020 and an oxide 1022 (such as, for example, SiO₂) that is grown or deposited on the substrate 1020. A thin single crystal layer 1024 of silicon is formed over the oxide 1022. The oxide (or insulator) is thus buried beneath the Si surface layer. For the case of ISE SOI structures, described previously, the top layer is a substantially single-crystal recrystallized silicon, from which CMOS circuits can be fabricated. The use of a buried insulator provides devices having higher speeds than can be obtained in conventional bulk (Czochralski) material. However, it is noted that any number of techniques can be employed to provide a thin-film of single crystal Si.

[0153] As shown in FIG. 21B, the film 1024 is patterned to define a pixel electrode region 1026 and a transistor region 1028 for each pixel element 1027. In one embodiment, the pixel electrode is formed of single crystal silicon. In another embodiment, the silicon is removed and indium tin oxide (ITO) is applied and patterned to form the pixel electrode. A transistor 1028 is then formed in accordance with any number of fabrication techniques, including those previously described herein. A thin layer of SiN₂ (not shown) is then formed over each pixel element. Next, a thin layer 1030 of optically transmissive material, such as SiO₂, is also formed over each pixel element 1027 and patterned to provide a well 1032 adjacent to each pixel electrode 1026 (FIG. 21C).

[0154] Referring to FIG. 21D, a color filter element 1034 is formed in the well 1032 adjacent to the thin film of essentially single crystal semiconductor material. Each color filter element 1034 is correlated with a pixel element 1027. The color filter elements can be formed by processing an emulsion or a photoresist carrier, as explained below, or by processing conventional filter materials. The individual color filter elements can be processed to provide an arrangement of three or four different color pixel elements in any of the previously described geometries. A matrix of opaque (or black) elements 1036 can also be formed adjacent to the thin film. Each opaque element 1036 is correlated with a pixel element 1027 serves to absorb light. A light shield for reflecting incident light and preventing the incident light from impinging upon the transistor 1028 associated with the pixel element can also be used. Such light shields are described in U.S. Ser. No. 07/823,858 filed on Jan. 22, 1992, which is incorporated herein by reference.

[0155] A thin optically transmissive layer 1038, which can be SiO₂, polyimide or sputtered glass, is formed over each pixel element (FIG. 21E). Referring to FIG. 21F, the active matrix structure is then transferred to an optically transmissive substrate 1042. To that end, an epoxy 1040 is used to attach an optically transmissive substrate 1042 to the active matrix and the color filter array. However, the optically

transmissive layer 1038 isolates the color filter array from the epoxy 1040. The substrate 1020 (and optionally the oxide layer 1022) is removed and the epoxy 1040 is cured by heating the structure at about 160° C. for 24 hours.

[0156] Referring to FIG. 21G, a cross-sectional view of the resulting display device is shown. Each pixel electrode 1028 and counterelectrode 1050 are laterally spaced from each other. Each pixel element 1027 will have a transistor 1028, a pixel electrode 1026 and an adjacent color filter element 1036 associated therewith. Polarizing elements 1052, 1044 are positioned on opposite sides of the structure which also includes the bonding element or adhesive 1040 and the optically transmissive substrate 1042, such as glass or plastic. The structure is completed by positioning a back light source 1046 adjacent to the polarizing element 1044.

[0157] FIGS. 22A-22K illustrate another preferred fabrication process for forming an active matrix color display. Referring to FIG. 22A, an SOI structure includes a silicon substrate 1041 and an insulating oxide layer 1043 (such as, for example, one micron of SiO₂) that is grown or deposited on the substrate 1041. A thin (i.e. 300 nm) single crystal layer 1045 of silicon is formed over the oxide 1043. The oxide is thus buried beneath the silicon surface layer, such that higher speed devices can be fabricated as explained previously. However, it is noted that any number of techniques can be employed to provide a thin film of single crystal silicon.

[0158] As shown in FIG. 22B, the film 1045 is patterned into islands to define each pixel element 1047. As explained below, the pixel elements are then processed to form a transistor and an electrode for each pixel. To that end, the pixel elements are masked (not shown) and subjected to deep and shallow implants to form an n-well region 1049 (FIG. 22C). Another masked is formed over the pixel elements, and the elements are subjected to deep and shallow implants to form a p-well region 1051.

[0159] Referring to FIG. 22D, an SiO₂ layer 1053 having a thickness on the order of 70 nm is formed over each silicon island 1047. A layer of polysilicon having a thickness of about 500 nm is formed on the oxide layer 1053, doped to provide an n+ region and patterned to form a transistor gate 1055 (FIG. 22E). Another oxide layer 1057 having a thickness of about 70 nm is formed over the polysilicon.

[0160] The pixel elements 1047 are masked (not shown) and doped with 2*10¹⁵ of phosphorus to provide an n+ source/drain implantation (FIG. 22F). After the mask is removed, the pixel elements are again masked and doped with 4*10¹⁵ of boron to provide a p+ source/drain implantation. As such, a transistor 1054 and a pixel electrode 1065 have been formed for each pixel element 1047.

[0161] A portion 1059 of the oxide layer is then removed to form a contact for the transistor 1054. Referring to FIG. 22G, a metallization deposition is then performed to form a layer 1061 over the transistor 1054. The layer can comprise aluminum and has a thickness of about one micron. The layer 1061 serves as a pixel light shield as well as a contact for the transistor 1054.

[0162] Referring to FIG. 22H, the entire pixel can be coated with a thin (about 150 nm) layer of silicon nitride (not shown). Next, a layer of amorphous silicon having a thickness of about 500 nm is deposited over each pixel element.

The layer is then patterned to provide a matrix of black elements **1067**, each black element associated with a transistor. A color filter element **1069** is formed over the pixel electrode **1065**. The color filter elements can be formed by processing an emulsion or a photoresist carrier, as explained below, or by processing conventional filter materials. The individual color filter elements can be processed to provide an arrangement of three or four different color pixel elements in any of the previously described geometries.

[**0163**] Referring to **FIG. 22I**, the active matrix structure is then transferred to an optically transmissive substrate **1056** such as glass or plastic. To accomplish this, an epoxy adhesive **1058** is used to attach an optically transmissive substrate **1056** to the active matrix structure. A thin optically transmissive layer (not shown), which can be SiO_2 , polyimide or sputtered glass, can be formed over each pixel element (not shown) to isolate the color filter array from the epoxy **1058**. The substrate **1041** (and optionally the oxide layer **1043**) is removed and the epoxy **1058** is cured by heating the structure at about 160°C . for 24 hours.

[**0164**] A second light shield **1039** is formed in or on the oxide layer **1043** as shown in **FIG. 22J**. In one embodiment, a metallization layer is formed on the oxide layer **1043** and patterned to form a light shield adjacent each transistor **1054**. In another embodiment, the oxide layer **1043** is thinned adjacent to each transistor **1054**. A light shield **1039** is formed in the thinned regions such that a substantially planar surface **1077** is provided adjacent to the liquid crystal material **1079** (**FIG. 22K**).

[**0165**] Referring to **FIG. 22K**, a liquid crystal material **1079** is disposed in a cavity **1081** along with spacers **1083**. An ITO layer **1085**, which serves as the counterelectrode, is formed adjacent to the cavity **1081**. An optically transmissive layer **1087**, such as glass or plastic, is positioned over the ITO layer.

[**0166**] A partial cross-sectional view of the resulting active matrix color display device is shown in **FIG. 23**. Each pixel electrode **1065** is laterally spaced from the counterelectrode **1085**. Each pixel element **1047** will have a transistor **1054**, a pixel electrode **1065** and an adjacent color filter element **1069** associated therewith. Polarizing elements **1089**, **1095** are positioned on opposite sides of the structure. The display also includes the bonding element or adhesive **1058**, the optically transmissive substrate **1056**, optically transmissive layers (**1087**, **1091**, **1097**) and ITO layers (**1093**, **1099**). The structure is completed by positioning a light source for providing light **1101** adjacent to the ITO layer **1099**.

[**0167**] In accordance with the present invention, an array of the color filter elements is formed adjacent to the array of pixel elements prior to transfer and subsequently transferred with the thin film and further processed to form an active matrix transmission display. In one preferred embodiment, a filter fabrication process using negative photoresist materials is employed to form an array of color filter elements.

[**0168**] **FIGS. 24A-24H** are sectional views illustrating the steps of forming an array of color filter elements in accordance with the this fabrication process.

[**0169**] Referring to **FIG. 24A**, an SOI structure includes a substrate **1060** and an oxide **1062** (such as, for example, SiO_2) that is grown or deposited on the substrate **1060**. A

thin single crystal layer **1054** of silicon is formed over the oxide **1062**. The film **1063** is patterned into an array of pixel elements **1064**, **1066**, **1068**. Each pixel element includes a pixel electrode region **1070**, **1072**, **1074** and a transistor region **1071**, **1073**, **1075** respectively for each pixel element.

[**0170**] To form a first color filter on each of a first pixel element **1064**, a pigment is dispersed in a negative resist material and applied as a film **1078** across an isolation layer **1076** (such as, for example, SiO_2) as shown in **FIG. 249**. Such colored negative photoresist materials are commercially available. A portion of the film **1078** is exposed to a light **1080**. The remainder of the film is masked (not shown) such that it is not exposed to the light **1080**. The exposed portion of the film is developed in the presence of the light to form a first color filter element. The undeveloped portion of the film is removed, leaving a pattern of first color filter elements **1082** adjacent to each pixel **1064** (**FIG. 24C**).

[**0171**] A second color filter element is formed in a similar manner as the first color filter elements **1082**. Referring to **FIG. 24D**, a pigment is dispersed in a negative resist material and applied as a film **1084** across the isolation layer **1076** and the elements **1082**. A portion of the film **1084** is exposed to a light **1086**, while the remainder of the film is masked (not shown). The exposed portion of the film is developed in the presence of the light to form a second color filter element. The undeveloped portion of the film **1084** is removed, leaving a pattern of second color filter elements **1088** adjacent to each pixel **1066** (**FIG. 24E**).

[**0172**] A third color filter element is formed in a similar manner as the first and second color filter elements **1082**, **1088**. Referring to **FIG. 24F**, a pigment is dispersed in a negative resist material and applied as a film **1090** across the isolation layer **1076** and the elements **1082**, **1088**. A portion of the film **1090** is exposed to a light **1092**, while the remainder of the film is masked (not shown). The exposed portion of the film **1090** is developed in the presence of the light, and the undeveloped portion of the film **1084** is removed, leaving a pattern of third color filter elements **1094** adjacent to each pixel **1068** (**FIG. 24G**). Optionally, a matrix array of opaque (or black) elements **1096** can be formed over or adjacent the transistor region of each pixel element **1064**, **1066**, **1068** as well as over the interpixel spaces. Each opaque element **1096** serves to absorb light and provide a uniform background.

[**0173**] In other preferred embodiments, a color filter array is formed adjacent to the active matrix circuitry by applying a color photographic development process for each color. **FIGS. 25A-25I** illustrate in cross-sectional views a photographic development process which uses color-coupler containing developers. Referring to **FIG. 25A**, an SOI structure includes a substrate **1100** and an oxide **1102** (such as, for example, SiO_2) that is grown or deposited on the substrate. A thin single crystal layer **1104** of silicon is formed over the oxide **1102**. The film **1104** is patterned into an array of pixel elements **1106**, **1108**, **1110**. Each pixel element includes a pixel electrode region **1112**, **1114**, **1116** and a transistor region **1113**, **1115**, **1117** respectively for each pixel element.

[**0174**] Referring to **FIG. 25B**, a black and white silver halide emulsion layer **1118** is formed adjacent to each pixel electrode of the active matrix. The formation of color filter elements utilizing a silver halide emulsion can be reviewed in greater detail in U.S. Pat. No. 4,400,454. An isolation

layer **1105**, such as SiO_2 , is formed over the active matrix and patterned to expose the portion of the emulsion layer adjacent each first pixel **1106**. This portion of the emulsion layer is exposed to light **1120** to provide silver particles. A first developer **1122** containing a color coupler is added to each exposed region **1125** of the emulsion layer (FIG. 25C). As such, a dye of a first color is then formed in each region **1125**. Next, the silver is removed by bleaching or rehalogenating **1124** for each region **1125** as shown in FIG. 25D.

[0175] Referring to FIG. 25E, portions of the unexposed silver halide emulsion layer **1118** adjacent to each pixel **1108** are then exposed to light **1126** through a patterned isolation layer **1127** formed over the active matrix. A second developer **1128** containing a color coupler is added to each exposed region **1129** of the emulsion layer to form a dye of a second color in each region **1129** (FIG. 25F). Next, the silver is removed by bleaching or rehalogenating **1130** for each region **1129** as shown in FIG. 25G.

[0176] The remaining portions of the unexposed silver halide emulsion layer **1118** adjacent to pixels **1110** are then exposed to light **1132** through a patterned isolation layer **1133** (FIG. 25H). A third developer **1134** containing a color coupler is added to each exposed region **1135** of the emulsion layer to form a dye of a third color in each region **1135** (FIG. 25I). Next, the silver is removed by bleaching or rehalogenating **1130** for each region **1135**. The layer **1133** is removed and any silver halide remaining in the emulsion layer is removed by fixing. As shown in FIG. 25J, an array of color filter elements **1125'**, **1131'**, **1135'** are thus formed adjacent to each pixel.

[0177] Alternatively, a color filter array can be formed by applying a color photographic development process which uses developers containing dye developers. To accomplish this, the above-described process is performed using developers containing dye developers instead of developers containing color couplers. After processing such as that described in FIGS. 21-23, the thin film with the formed color filter elements can than be transferred, if necessary, for further processing prior to final display fabrication.

[0178] FIGS. 26A-26D illustrate another preferred fabrication process for forming an active matrix color display. Referring to FIG. 26A, an SOI structure includes a substrate **1140** and an oxide **1142** (such as, for example, SiO_2) that is grown or deposited on the substrate **1140**. A thin single crystal layer **1144** of silicon is formed over the oxide **1140** using any of the aforementioned fabrication techniques. For the case of ISE SOI structures, which were described previously, the top layer is a essentially single-crystal recrystallized silicon, from which CMOS circuits can be fabricated. The silicon thin film **1144** is patterned to define an array of pixel elements **1150**. Each pixel element includes a pixel electrode region **1148** and a transistor **1146**, formed in accordance with any number of fabrication techniques, including those previously described herein.

[0179] Referring to FIG. 26B, the active matrix structure is then transferred to an optically transmissive substrate **1154**. To that end, an epoxy **1152** is used to attach an optically transmissive substrate **1154** to the active matrix. The substrate **1140** (and optionally the oxide layer **1142**) is removed, and the epoxy **1152** is cured by heating the structure at about 160°C . for 24 hours.

[0180] An array of color filter elements **1156** is formed on the oxide layer **1142** adjacent to planar surface of the thin

film **1144** (FIG. 26C). Each color filter element **1156** is correlated with a pixel element **1150**. The color filter elements **1156** are formed by processing, in accordance with the aforementioned processing techniques, an emulsion or photoresist carrier. The individual color filter elements can be processed to provide a display having a triad pixel arrangement of three primary (or non-primary) color filter elements. Alternatively, the color filter elements can be arranged into groups of four pixel elements. As noted previously, a primary color is defined herein to correspond to one of a group of colors which can be used to provide a spectrum of colors. An opaque (or black) element **1158** can also be formed adjacent to the thin film. Each opaque element **1158** is correlated with a pixel element **1150** and serves to prevent incident light from impinging upon the transistor **1146** associated with the pixel element.

[0181] A cross-sectional view of the resulting active matrix display is shown in FIG. 26D. A liquid crystal material **1162** is positioned in close proximity to the pixel elements **1150**. An insulating layer **1160**, which can be SiO_2 , polyimide or sputtered glass, is formed over each pixel element for passivating the pixel elements from the liquid crystal material **1162**. A counterelectrode **1164** is laterally spaced from the pixel electrodes **1148**. Each pixel element **1150** has a transistor **1146**, a pixel electrode **1148** and an adjacent color filter element **1156** associated therewith. Polarizing elements **1164**, **1168** are positioned on opposite sides of the structure. The structure is completed by positioning a back light source **1170** adjacent to the polarizing element **1168**.

[0182] Other preferred embodiments employ an emissive material (an electroluminescent film, light emitting diodes, porous silicon or any other light emitting material) in combination with a color filter array to form an emissive active matrix color display. To that end, an electroluminescent (EL) color display is shown in FIG. 27. The EL display **1200** is a layered structure which includes an active matrix circuit panel **1201**, a bottom insulator **1206**, an EL structure **1204**, a top insulator **1208**, an optically transmissive electrode **1210**, a color filter array **1212** and an optically transparent superstrate **1213**.

[0183] The EL structure is positioned between the two insulating layers **1206**, **1208** for preventing destructive electrical breakdown by capacitively limiting direct current flow through the EL structure and for enhancing reliability. The insulators have a high electrical breakdown so that they can remain useful at high fields which are required to create hot electrons in the EL phosphor layers. The capacitive structure is completed by a pair of electrodes. One of these electrodes is pixel electrodes formed on the active matrix **1201** and the other electrode is the optically transmissive electrode **1210**.

[0184] The EL structure **1204** is formed of a single phosphor layer which produces a white (or other multi-line spectrum) light in the presence of an applied field. The layer is patterned to provide an array of individual phosphor elements **1205**. Each EL element **1205** is associated with a pixel element **1203**. The color filter array **1212** is located in close proximity to the EL structure **1204** such that each color filter element **1211** is associated with an EL element **1205** and a pixel element **1203**. The individual elements **1211** of color filter array can be arranged in a triad arrangement of

three primary (or non-primary) color filter elements such as red, green and blue or yellow, cyan and magenta. Alternatively, the color filter elements can be arranged into groups of four different color filter elements such as red, green, blue and white or yellow, cyan, magenta and black/white.

[0185] The pixel elements **1203** of the active matrix **1201** are individually actuated by a CMOS/DMOS drive circuit, described previously herein or in a related application previously incorporated by reference, having first **1217** and second **1219** circuit components that are positioned adjacent the pixel array such that each pixel element can produce an electric field in an associated element **1205** of the EL structure **1204** between the pixel electrode and the transparent electrode **1210**. The electric field causes the EL element **1205** to emit white light or other multi-line spectrum light. The light passes through the associated color filter element **1211** to produce a colored light which is illuminated from the display through the optically transmissive electrode **1210**.

[0186] The active matrix pixel array employs transistors (TFTs) collocated with each pixel in the display to control the function of the pixel. As applied to EL displays, the active matrix approach offers significant advantages including reduced power dissipation in the circuit panel and increased frequency in which the AC resonant driver can operate. The formation of a useful EL active matrix requires TFTs that can operate at high voltages and high speeds. Single crystal silicon is preferred for achieving high resolution in a small (6 in×6 in or less) active matrix EL display.

[0187] In an EL display, one or more pixels are energized by alternating current (AC) which is provided to each pixel by row and column interconnects connected to the drive circuitry. The efficient conduction of AC by the interconnects is limited by parasitic capacitance. The use of an active matrix, however, provides a large reduction of the interconnect capacitance and can enable the use of high frequency AC to obtain more efficient electroluminescence in the pixel phosphor and increased brightness. In accordance with the present invention, the TFTs that provide this advantage are formed in a single crystal wafer, such as bulk Si wafers, or thin films or layers of single crystal or essentially single crystal silicon in accordance with the previously described fabrication techniques. These high quality TFTs are employed in an EL panel display, providing high speed and low leakage as well as supporting the high voltage levels needed for electroluminescence.

[0188] In preferred embodiments, single crystal silicon formed on an insulator (SOI) is processed to permit the formation of high voltage circuitry necessary to drive the EL display. More specifically, thin film single crystal silicon formed by the ISE process, or any of the other fabrication processes described herein, allows for fabrication of high voltage DMOS circuitry for the TFTs as well as low voltage CMOS circuitry for the drivers and other logic elements.

[0189] A preferred fabrication sequence for the formation of an EL color display is shown in FIGS. 28A-28E. Referring to FIG. 28A, an SOI structure includes a substrate **1214** and an oxide **1216** (such as, for example, SiO₂) that is grown or deposited on the substrate **1214**. A thin single crystal layer **1218** of silicon is formed over the oxide **1214**. For the case of ISE SOI structures, the top layer is a substantially single-crystal recrystallized silicon, from which CMOS and

DMOS circuits can be fabricated. The use of a buried insulator provides devices having better isolation than can be obtained in conventional bulk (Czochralski) material. However, it is noted that any number of techniques can be employed to provide a thin-film of single crystal silicon for an EL color display.

[0190] As shown in FIG. 28B, the film **1218** is patterned to define a pixel electrode region and a transistor region for each pixel element **1224**. In one embodiment, the pixel electrode **1222** is formed of single crystal silicon. In another embodiment, the silicon is removed and ITO is applied and patterned to form the pixel electrode **1222**. A transistor **1218** is then formed in accordance with any number of fabrication techniques, including those previously described herein. Next, the EL structure is formed (FIG. 28C). To that end, a thin layer **1226** of insulating material is deposited and patterned over each pixel element **1224**. A white phosphor layer **1228** is deposited and patterned over the bottom insulator **1226**, and a top insulator **1230** is deposited and patterned over the phosphor material.

[0191] Referring to FIG. 28D, a top electrode **1231** is formed on the EL structure. Next, a color filter element **1232** is formed. Each color filter element **1232** is correlated with a phosphor element **1228** and a pixel element **1224** such that each pixel is capable of producing light of a primary color. As explained previously, the color filter elements are formed by processing an emulsion or a photoresist carrier. The individual color filter elements **1232** can be processed to provide a triad arrangement of primary color pixels such as blue, green and red or yellow, cyan and magenta. In another embodiment, the color filter elements can be processed to provide a triad (or quad) arrangement of non-primary color pixels. In yet another embodiment, the color filter elements can be arranged into groups of four pixel elements. An opaque element **1234** can also be formed adjacent to the EL material. Each opaque element **1234** is correlated with a pixel element **1224** and absorbs light for preventing incident light from impinging upon the transistor **1220** associated with the pixel element. A optically transmissive superstrate **1236** such as glass or plastic is formed over the EL structure to complete the EL color display (FIG. 28E).

[0192] In another embodiment, the EL color display can be transferred to an optically transmissive substrate as illustrated in FIGS. 29A-29C. An EL display fabricated in accordance with any of the previously described methods is shown in FIG. 29A.

[0193] The structure is inverted and the initial substrate **1214** is removed (FIG. 29B). The structure is then transferred to an optically transmissive substrate **1242**, such as glass or a curved surface of a visor, and the superstrate **1236** is optionally removed.

[0194] Another feature of the active matrix displays of the present invention is that an array of pixel electrode elements can be patterned in the single crystal silicon material. In one preferred embodiment, the individual pixel electrode elements are solid shaped elements formed of single crystal silicon or indium tin oxide (ITO). In another embodiment, the pixel electrodes can be selectively thinned to optimize transistor performance. Regions of the electrode can be thinned to about one-tenth the thickness of the 0.1 to 2.0 micron single crystal silicon layer.

[0195] In yet another embodiment, the silicon material is patterned to form an array of pixel electrodes and each

electrode is further patterned into a grid, serpentine, or other suitable geometry to reduce transmission loss through the pixel electrode. Referring to FIG. 50, an individual pixel electrode 1350 initially comprises a solid layer of single crystal silicon. However, the element is processed such that areas 1352 of silicon are removed and strips 1354 of silicon remain. As such, the resulting pixel electrode resembles a grid. The open areas 1352 have a width (W1) of about 3-5 microns and the strips 1354 have a width (W2) of about 1-2 microns. This provides an aperture through each pixel electrode that improves transmission of light by reducing interference effects and also reducing reflection, absorption and scattering caused by the pixel material. One advantage of the grid-shaped pixels is the increased light transmission through the active matrix which results in brighter displayed images. Another advantage is that the grid-shaped pixels minimize thickness variations in the single crystal silicon layer. These thickness variations cause light absorption and/or interference which reduces the light transmission through the active matrix. By minimizing thickness variations, brighter displayed images can be provided. An alternative embodiment includes further thinning of the pixel electrode material so that the switching circuits are within a thicker film than the pixel electrode.

[0196] Yet another feature of the active matrix displays described herein is that they may be mounted on a visor of a helmet to form a head-mounted display. Referring to FIG. 31, a visor 1358 formed of optically transmissive material is secured onto a helmet 1356. An active matrix display 1360 is positioned on the visor 1358. When activated by an electronics system (not shown), the display 1360 generates monochrome or multi-color images which are projected into the helmet 1356 for viewing by a subject. The display 1360 is substantially transparent when inactive.

[0197] The formation of the active matrix display and the above described uses are further described in U.S. patent application Ser. No. 07/944,207, Filed Sep. 11, 1992 now U.S. Pat. No. 5,444,547, which is incorporated in its entirety by reference.

[0198] FIG. 32 is a rear perspective view of a preferred embodiment of a head mounted display 201. The head mounted display 201 is constructed of plastic or some other light-weight housing material and is adapted to be worn by a user to view video images via an optical assembly 200. The head mounted display exploits electronic digital imaging to form video images on a pair of light valve display panels, one of which is viewed through the user's left eye and the other of which is viewed through the user's right eye. Related discussions of head mounted display devices are provided in U.S. patent application Ser. No. 07/971,352, filed Nov. 4, 1992 and International Patent Publication WO 93/18428, filed Mar. 12, 1992, the teachings of which are both incorporated herein by reference.

[0199] The images are provided by a remote video source 202, which can be a camera, a computer, a receiver, a video cassette player, or any device that can transmit a video signal. The video source 202 may generate of video signal from data received over a link 209, such as fiber optic cable. In addition, supply voltage is provided to the head mounted display 201 from a power supply 205, which can provide the required supply voltage through the video source 202. The video source 207 can also provide an audio signal. In a

particular preferred embodiment of the invention, the video source 202 and the power supply 205 are physically connected to the head mounted display 201 using a connector 203.

[0200] It should be understood that the head mounted display 1 can be self-contained such that no physical connection to the remote video source 202 or power supply 205 is required. For example, the head mounted display 201 can contain a receiver to receive transmitted video information and translate that received video information to control signals. Such an embodiment is particularly useful for receiving an over-the-air television broadcast. Similarly, the power supply for the head mounted display 201 can be provided by batteries or another power source (e.g., solar cells) that are integrated into the head mounted display 201.

[0201] The head mounted display 201 has a central housing body 212 that is formed from a front housing section 210 and a back housing section 220. The front section 210 is preferably formed from an opaque material such as plastic to block external light 299 from the user's eye's. The rear section 220 is also formed from an opaque material but is adapted to permit the user to adjust the optical assembly 200. The front section 210 is used to mount the optical assembly 200 (FIG. 34). In addition to the optical assembly 200, the user can also adjust a nose bridge assembly 224. The nose bridge assembly 224 can be positioned between an extended position (as illustrated) and a retracted position using an actuating button 225. The user can select a position from a discrete number of detents. In a preferred embodiment of the invention, the actuating button 225 is fastened to one end of a member that slides within a channel of a support member 215. The opposite end of the member is fastened to the nose bridge assembly 224. When in a selected position, the button is registered to a respective detent. The actuating button 225 is pushed to release the button 225 from the detent so that the nose bridge 224 is retracted.

[0202] Attached to each side of the head mounted display body 212 is a stem 230 through a respective forward hinge 231. Each stem contains a forward stem section 232, which is coupled to the forward hinge 231 at the proximal end. In a particular preferred embodiment, the forward stem section 232 contains a rear hinge 233 at the distal end and an earphone storage compartment 237 into which earphones 40 are stowed when the stems are folded.

[0203] Rearward stem sections 234 are coupled to the forward stem section 232 joints 233 at their proximal ends. The rearward stem sections 234 are adapted to supply earphones for use by the user. The earphones 240 pivot down from a horizontally aligned position for use by the user. When stowed, the earphones 240 are returned to a horizontally aligned position for storage in the earphone storage compartment 237 of the forward stem section 232. The earphones also slide forward and rearward for adjustment by the user. The rear stem sections 234 also contain control knobs 236R, 236L for adjusting the audio and video features during the operation of the head mounted display 201. The control knobs 236R, 236L are thus coupled to electronic circuitry, which is also stored within the stem sections 230. In a particular preferred embodiment of the invention, the right rear stem section 234R contains a volume control 236R and the left rear stem section 234L contains a contrast control 236L. Also in a particular preferred embodiment of

the invention, the left rear stem section **234L** contains a female connector **238** for interfacing with the video source **202** through the male connector **203**. Alternatively, an antenna can be provided to receive audio and video signals.

[**0204**] The head mounted display **201** can be used in numerous and varied applications including, but not limited to, commercial audio/video presentations (television, home video), computer and multimedia presentations, hospital operating room use (e.g. orthoscopic surgery), remote camera monitoring, or any other use where private or detailed viewing of a video image is desired. For certain applications, it is desirable that the body **212** of the head mounted display **201** pivot upward like a visor to permit the user to easily alternate viewing the video image and alive scene. An example of such an application is when the head mounted display **201** is worn by a surgeon during orthoscopic, or other, surgery.

[**0205**] **FIG. 33** is a rear perspective illustration of the wiring harness enclosed by the head mounted display **201**. In a particular preferred embodiment, audio and video information and supply power is provided via a 10-pin male connector **203**. The male connector **203** registers to a 10-pin female connector **238**. Of these ten pins, seven pins are provided for the display panel power and backlight power, and three pins are provided for audio signals. The seven video signals are provided to a first circuit **260**. A contrast control **237** is coupled to the first circuit **260** to permit the user to adjust the contrast of the images displayed on the light valve display panels. In other preferred embodiments, other video controls (e.g., brightness, image alignment, color adjust, etc.) are provided and coupled to the first circuit **260**. The first circuit **260** is coupled to a second circuit **262**, which drives the light valve display panels via an N-conductor ribbon cable **264**, where the number of conductors N is determined by the type of display panel.

[**0206**] The first circuit **260** also separates the backlight power signals from the light valve display panel signals and provides those signals to a backlight driver **266** over a 6-conductor ribbon cable **268**. In addition to the two backlight driver signals, the 6-conductor ribbon cable **268** carries four audio signals. A left channel signal **270_L**, a common signal **270_C**, and a right channel signal **270_R** are provided on the 6-conductor ribbon cable **268** to a stereo volume control **236**. In a particular preferred embodiment, the backlight driver **266** and the stereo volume control **236** are disposed within the opposite stem **230** from the circuit **260**.

[**0207**] The stereo volume control **236** permits the user to alter the gain of the signals in the right and left earphones **240**. The adjusted right signal **270_R** is provided to the right earphone **240R** and the adjusted left channel signal **270_L** is carried by the 6-conductor ribbon cable **268** back to the left earphone **240L**. Both the left and right earphone are also provided with the common signal **270_C**. In other preferred embodiments, other audio controls (e.g., stereo balance, tone, etc.) are provided.

[**0208**] The second circuit **262** need not be a discrete device as illustrated. In another preferred embodiment, the second circuit **262** is fabricated with each display panel, such that each display panel is controlled by a respective control circuit.

[**0209**] The backlight driver **266** provides high voltage signals to the optical assembly **200** over signal lines **272**.

The high voltage signals can be used to drive a backlight for each display panel where a transmissive display panel is used. Similarly, the high voltage supply can be used to drive an emissive display panel. In a particular preferred embodiment of the invention, the display panels are of the active matrix liquid crystal display type, which require backlighting.

[**0210**] In a preferred embodiment the discrete circuiting **274**, **276**, **278**, **280** are disposed near the rear of the head mounted display **201** to provide for more even weight distribution. A preferred control circuit for driving the active matrix display panel **213** is described in U.S. patent application Ser. No. 07/971,399, filed Nov. 4, 1992, the teachings of which are incorporated herein by reference. In another preferred embodiment, the display panels are of the passive matrix liquid crystal display type. A control circuit for driving the passive matrix display panel is described in U.S. patent application Ser. No. 07/971,326, filed Nov. 4, 1992, the teachings of which are incorporated herein by reference.

[**0211**] **FIG. 34** is a top plan view of the head mounted display **201** taken along section line I-I of **FIG. 32**. The positioning of the wiring harness **284** is illustrated in phantom. Note that the ribbon cables **286** and **288** are routed around the joints **231** and **233** to permit folding of the stems **230** into a compact unit for storage. In a preferred embodiment, the rear hinge **233** employs a split cylinder that rotates independent of the joint so the ribbon cable is not visible when the stems are opened or folded.

[**0212**] **FIG. 35** is an exploded view of the optical assembly for the head mounted display **201**. A mounting frame **310** is adapted to be mounted to the inner surface of the front section **310** of the head mounted display **201**. The mounting frame **310** has first and second guide rails **311a**, **311b** to permit adjustment of the inter-pupil displacement of the light valve display panels. The adjustment of the inter-pupil displacement will be discussed in more detail below.

[**0213**] Mounted to the mounting frame is a backlighting assembly **320** for use in transmissive display systems. The backlighting assembly **320** contains a backlight **324**, which is preferably a cold cathode backlight. The backlight **324** is disposed in a white reflector **322**, which reflects light from the backlight **324** onto the display panel. In a transmissive color display, the backlighting can be provided by a multi-color sequential backlight where there is a backlight for each primary display color (e.g., red, green, blue) and the backlights are sequentially lit in timing with the switching of the light valve. In another preferred embodiment backlight is provided by direct ambient light **99**. Through a light transmissive front housing section **210** and mounting frame **310**.

[**0214**] A display holder **330** is positioned on the mounting frame **110** such that the mounting frame rails **311a**, **311b** are disposed within respective display holder channels **331a**, **331b**. The display holder **330** contains a display area **334** and an aperture **332** through which light from the backlight **324** passes. The display holder **330** also has a geared rack **335** for use in adjusting the inter-pupil displacement. A viscous damped gear assembly **315** meshes with the geared rack **335** such that rotational motion of the gear assembly **315** causes linear movement of the display holder **330** along the mounting frame **310**. As illustrated, the user adjusts the inter-pupil displacement by sliding the left and right display holders

330 along the mounting frame **310**. Alternatively, an axle can extend from the gear **315** to a knob or crank lever, preferably disposed on the forward face of the front section **210** of the display body **212**. Indicator marking can also be provided to guide the user.

[0215] Although only the left portion of the optical assembly **200** is illustrated in **FIG. 34**, the right display holder is similar to the left display holder, except that the right display holder is rotated 180° relative to the left display holder. In that alignment, the left display holder gear rack **335L** is positioned below the gear assembly **315** and the right display holder gear rack **335R** is positioned above the gear assembly **315** as illustrated in **FIG. 33**. Consequently, the gear assembly simultaneously displaces both the left and right display holders when rotated. In a preferred embodiment of the invention, the inter-pupil displacement is adjustable by the user in a range from about 55 mm to 72 mm to provide an aligned left-right image to the user.

[0216] Returning to the optics assembly, a display assembly **340** is registered to the display chamber **334**. The display assembly contains a translucent plastic light diffuser **342**, a liquid crystal display panel **344**, and a thin plastic matte black mask **347**. The diffuser **342** diffuses light from the backlight **324** that passes through the display holder aperture **332** to provide a light distribution that is sufficiently uniform across the display area **346**. The liquid crystal display panel **344** has a display area that is 0.7 inch as measured diagonally. The liquid crystal display panel **344** is preferably fabricated in accordance with U.S. patent Ser. No. 07/815,684, filed Dec. 31, 1991, the teachings of which are incorporated herein by reference. The display panel **344** contains connectors to connect to the 20-conductor ribbon cable **286** (**FIG. 33**). The display assembly **340** is secured in the display holder chamber **334** by an optics holder **350**, which is fastened to the display holder **330**. The optics holder **350** contains a housing **352** that may be conformable to the users eye to block ambient light and surround a cover glass **354**.

[0217] Optional lenses **360** are adaptable to the display holder **350** to, for example, correct the user's near vision.

[0218] Although **FIG. 35** illustrates a preferred embodiment employing a transmissive display panel, an optical assembly **200'** can be adapted to receive an emissive display panel **344'**, as illustrated in **FIG. 36**. The emissive display optical assembly **200'** differs from the transmissive display optical assembly **200** in the following respects. The emissive embodiment does not use a backlight **320**. Thus the display holder **330** does not require an aperture **332** or a light diffuser **342**. Instead, the light is provided by emissive material on the display panel **344** that is activated by drive signals. The emissive display panel is preferably fabricated in accordance with U.S. patent application Ser. No. 07/643, 552, the teachings of which are incorporated herein by reference.

[0219] **FIG. 37** is a top plan view of the head mounted display **201** in the folded configuration. In particular, note that the nose bridge assembly **224** has been positioned into the retracted position for storage. In the retracted position, the nose bridge assembly **224** does not interfere with the folding of the stems **230**. The hinge points **239** on the forward joints **231** are spring tensioned to facilitate head rotation.

[0220] **FIG. 38** is an exploded view of a preferred spring cam assembly, **390R** that is used at the hinge port **239R** on the right forward joints **231R**. The cam assembly **390R** comprises a first cam **391R** and a mirror image second cam **392R**. The cams **391R**, **392R** contain an outer section **391Ra**, **392Ra** that registers to a respective receptacle on the body **212** and an inner section **391Rb**, **392Rb** that registers to a respective receptacle on the forward stem **32R**. The inner cams **391Rb**, **392Rb** each include a landing **393** that allows for free play before engagement. A compression spring **395** is disposed between spring landings. The cams **391R**, **392R** compress the spring **395** when rotated together. For the right stem **30R**, free play is exhibited for an angular displacement from the folded position, thereafter a variable return force is extended by the spring **395**, which tends to secure the head mounted display **201** to the user's head. The compression can be adjusted by an adjustment bolt **396** that meshes with a threaded opening on the outer sections **391a**, **392b**.

[0221] **FIGS. 39A-39B** are partial views of another preferred stem storage embodiment. The forward stem section **332** is a skeleton frame on which the rear stem section **334** slides for storage. (**FIG. 39B**). Alternatively, the forward stem section **332'** can encapsulate the rear stem section **334'** when stored.

[0222] Other preferred embodiments employ other devices to secure the head mounted display, to the user's head. Such devices include an inflatable bladder **251** (shown in phantom in **FIG. 32**), with an associated pump assembly, that is disposed over the user's temple, and a headband **252**, and ear loops **253**.

[0223] In a preferred embodiment, the head mounted display **201** is formed from injection molded plastic. Particular components, such as the nose bridge support member **215**, are rigid glass filtered molded plastic or a composite laminate.

[0224] **FIG. 40** is a front perspective view of another preferred embodiment of a head mounted display unit **201'**. The head mounted display unit **201'** comprises a visor **50** and a headband **560** coupled together by a pair of pivot assemblies **570a**, **570b**. The right side pivot assembly **570a** is a mirror image of the left side pivot assembly **570b**. The pivot assemblies **570a**, **570b** are adjustable and flex such that the head mounted display unit **201'** can be secured to a user's head. The display unit **201'** also includes a right speaker assembly **580a** and a left speaker assembly **580b** that can be positioned over the user's ears. Each of these components will be discussed below in further detail.

[0225] The visor **550** includes a face plate **552** having a right side **552a** and left side **552b**. In a preferred embodiment, transmissive display panels use a dedicated backlight as illustrated in **FIG. 35**. In another preferred embodiment, emissive display panels are used in the visor **550**. The visor further includes a back section **554**, which will be discussed in further detail below.

[0226] The visor is connected to the right pivot assembly **570a** by a right visor hinge **553a** and to the left pivot assembly **570b** by a left visor hinge **553b** (**FIG. 41**). The visor hinges **553a**, **553b** allow the respective pivot assembly **570a**, **570b** to flex laterally relative to the line of sight of the user. This flexion, for example, permits the user to separate the distance between the speaker assemblies **580a**, **580b** so as to fit the display unit **201'** over the user's head.

[0227] The pivot assemblies **570a**, **570b** each contain components to displace the visor **550** from the earphones **580a**, **580b** longitudinally relative to the user's line of sight. This permits the user to properly adjust the visor for a snug fit. More particularly, longitudinal motion is accomplished by cooperation between a front hinge **571** and a center pivot **575**. The front hinge **571** is mated to a respective visor hinge **553** by a pin **571'**. The front hinge includes a rail section **572** and the center pivot **575** includes a rail section **574**. A center coupler **573** permits the rails **572** and **574** to slide relative to one another. As illustrated in **FIG. 40**, the display unit **201'** is shown fully extended in the longitudinal direction. Within the center coupler **573** is a wheel **576** to facilitate relative motion between the opposed rails **572** and **574**.

[0228] The headband **560** is preferably formed of rigid plastic and includes a headpiece **562** having a right side **562a** and a left side **562b**. In each side of the headpiece **562**, are a series of spaced detents **568** to couple to a respective pivot assembly **570a**, **570b**. Optionally, the headband **560** can include a pad **564**, preferably made of a pliable rubber foam to provide a comfortable fit over the user's head.

[0229] The pivot assemblies **570a** and **570b** cooperate to permit the headband **562** to rotate about the center pivots **575a** and **575b**. In a preferred embodiment of the invention, the headband **560** pivots 360° traverse to the plane of the user's line of sight. As illustrated, the headband **560** is positioned at 90° .

[0230] A lateral pivot joint **577** is coupled to the respective pivot joint **575** such that when the headband **560** is positioned at the 90° position, a pivot point (not shown) is positioned parallel to the visor hinges **553** such that the speaker assemblies **580a** and **580b** can flex laterally. A supporting member **579** is coupled to the lateral hinge **577** via the pivot. The supporting element **579** includes a rail **578**, which is mated to the series of detents **568** by a catch **579**. The headband **560** can be fixed to positions defined by the detent **568** by moving the headpiece **562** along the rails **578**.

[0231] The speaker assemblies **580** are also coupled to the respective pivot assemblies **570a** and **570b**. A lobe member **587** is coupled to the supporting element **579** of the pivot assembly **570** by a hinge **579'**. Each headphone **580** includes a mounting frame **582** which is connected to the lobe member **587**. A speaker component **583** is fixed to the speaker frame **582**. A foam pad **584** rests against the user's ear such that the user hears sound from the speaker component **583** through an aperture **585** in the foam padding **584**.

[0232] **FIG. 41** is a front view of the head mounted display unit **201'** of **FIG. 40**. The front view more clearly illustrates the capability of swiveling the earpiece **580a** and **580b** about the respective pivot points **579a'** and **579b'**. Also illustrated are slide tabs **556a** and **556b** for aligning the display panels (not shown) within the visor **550**. More particularly, the slide tabs **556** permit adjustment of the inter-pupillary displacement of the display panels. Furthermore, the slide tabs **556** preferably operate independently of each other such that each display panel can be positioned relative to the respective eye to compensate for off-center vision.

[0233] **FIG. 42** is a top view of the head mounted display unit **201'** of **FIG. 40**. In particular, the lateral motion about hinge pairs **553-571** and **577-579** are illustrated.

[0234] **FIG. 43** is a left side view of the head mounted display device **201'** of **FIG. 40**. As illustrated, the headpiece **562** is fully retracted. In addition, the visor **550** is partially retracted. A pin connector **404** is mounted in element **575b** to provide video and audio connections to the device. Alternatively, two pin connectors can be used, one on **575b**, the second on **575a**.

[0235] **FIG. 44** is a rear view of the head mounted display device **201'** of **FIG. 1**. Illustrated are ball joints **575a'** and **575b'** of the respective center pivot **575a** and **575b**. As illustrated, each back section **554** of the visor **550** includes a right viewer **558a** and a left viewer **558b**. Each viewer permits the user to view images formed on respective display panels (not shown) disposed within the visor **550**. Preferably, the viewers **558a** and **558b** are positioned within respective recessed cavities **557a** and **557b** of the back section **554** of the visor **550**. The recessed cavities **57a**, **57b** make the display device **201'** eyeglasses compatible. Also illustrated is a nose bridge **559**, which is preferably molded into the back section **554**. Also shown in the Figure are control knobs **586a** and **586b** protruding through the respective speaker assemblies **580a** and **580b**. In a particular preferred embodiment, the right control knob **86a** controls contrast on the display panels and the left control knob **86b** controls speaker volume.

[0236] **FIG. 45** is a bottom view of the head mounted display unit **201'** of **FIG. 40**. More clearly illustrated are the recessed cavities **557a** and **557b** of the back section **554** of the visor **550**. Furthermore, the configuration of the slide tabs **556a** and **556b** in a respective slide channel **554a** and **554a** of the back section **554** is illustrated. Furthermore, the head pad **564** is illustrated as having longitudinal ribs to help maintain the headpiece **564** in place. The hinge between **552a** and **571a**, and the second hinge between **552b** and **571b** can be "hidden" as shown in **FIG. 45**.

[0237] Between the closed position and the 90° position there can be a discrete number of a detent for positioning the headband **560**. In a particular preferred embodiment, a detent is provided at the 45° position. Alternatively, a friction bearing surface can be used to rotate the visor relative to the headband to hold the visor in a partially raised position.

[0238] **FIG. 46** is a front perspective view of the head mounted display device **201'** of **FIG. 40** in a folded position. **FIG. 47** is a bottom perspective view of the display unit **201'** of **FIG. 46**. The unique and novel pivot assemblies **570a** and **570b** cooperate to allow the display unit **201'** to be folded into a compact package. The headpiece **560** is rotated about the center pivots **575a** and **575b** to the 0° position. The earpiece **580a** and **580b** are then folded behind the headpiece **560**, where the earpiece **580a** and **580b** lie flat. In a particular preferred embodiment, the supporting elements **579a** and **579b** contain a spring-loaded pin **579a'** and **579b'** to aid the folding of the earpiece **580a** and **580b**. The pins **579a'** and **579b'** can be similar to the cam assembly of **FIG. 38**. The visor is then retracted toward the center pivots **575a** and **575b** until the display unit **201'** is securely packed. From this folded position, the head mounted display unit **201'** can be easily packed, carried or otherwise transported. **FIG. 46** also shows manual focus adjust elements **400** located on the top of the visor which are described in greater detail below.

[0239] **FIGS. 48A-48B** are detailed views of the light pivot assembly **570a**. As illustrated, the rails **572a** and **574a**

lie in tracks **573a'** and **573a'** of a respective center coupler **573a**. A wheel **576a** having a pin **576a'** through its central axis and fixed at one end to the center coupler **573** is disposed between the opposing rails **72a**, **74a**. Each opposing rail **572a** and **574a** has a respective slot **572a'** and **574a'** through which the wheel pin **576a'** extends. The wheel **576a** is held between slots and contains cable guides as described below. Also illustrated is a connector **589a** on the lobe member **587a** for connecting the speaker assembly **580a** to the assembly. The connector **589a** is an electrical connector carrying audio signals.

[0240] The wiring of the device is as follows: The signals and power enter through the back of **575b** via a connector. The audio portion then passes through to the earcups with one extending through the headband. The video goes forward through the temple slides via the "spool" or wheel **576a**. The pin **576a** is the center axle that allows it to rotate in the hole in **573**. The pin is secured to the wheel. FIG. 49A shows pin **576a'**. The wheel has two of these, on opposite sides, 180° apart. These are what ride in the slots **572a'** and **574a'** (shown in FIG. 49A). The wheel circumference is not in contact with the rails. As shown in the detailed view of FIG. 49A which shows the wheel held between slots **572a'**.

[0241] FIG. 49B shows the wheel is also a spool. It serves to control the cable length as the rails are moved fore and aft. The spool **576a** is designed to be an assembly using two identical pieces **450**, **452**. The kidney shapes act as cable guides **454**, **456** which control the motion of **10** conductor cable **458** as the rails are moved.

[0242] FIG. 50 shows the optics module sub-assembly. Two of these modules **410** are mounted to a triangulated rail system **480** and comprises an optics assembly.

[0243] Each optics module consists of the following: A display **420**; a backlight **490**; a lens **430**; a mirror **432**; an optic housing **412a**; a focus adjust slide **403**; a IPD adjust/cover **406**; and a rail slide **488**. As shown in FIG. 51 the two modules **410**, **415** are mounted on rail system **480**. FIG. 52 is a perspective view of an optic housing **412**. FIG. 53 is a side cross sectional view of the optical system with lens **430**, mirror **432**, the backlight **490** and display **420**. Focus is accomplished via sliding ramp system, shown in FIGS. 54 and 55, which are incorporated into the focus adjust slide and the backlight housing. Tabs protruding from the backlight housing are engaged in slots incorporated in to focus slide. As the focus slide button is moved horizontally, the backlight housing (along with the attached display) move vertically. Multiple tabs ensure positive alignment throughout the motion range. The vertical tabs extending from the optic housing keep the backlight/display assembly centered horizontally left to right as well as acting as vertical slide surfaces. The IPD button serves as the top of the assembly capturing the top on the focus slide.

[0244] FIG. 56 shows the display placed at the focal length of the lens, thus producing an image of the display at an apparent distance of infinity to the viewer. The lens has a small focal length, preferable about 1 inch. The flat optical element is present to correct for lateral color separation in

the lens. This element consists of a diffractive optic **434** designed to compensate for the lateral color in the lens. The mirror serves to fold the optical path to minimize the depth of the head mounted device while extending its height. the mirror is optional to the system and is present for desired form factor. Two such setups make up on binocular head mounted display system: one for each eye. The distance that the displays appear to the viewer can be adjusted for personal comfort, generally between 15 feet and infinity. The magnification of the system is about 10. Other lens systems can be sued and are available from Kaiser Electro-Optics, Inc. of Carlsbad, Calif.

[0245] Equivalents

[0246] While this invention has been particularly shown and described with references to preferred embodiments thereof, it will be understood by those skilled in the art that various changes in form and details may be made therein without departing from the spirit and scope of the invention as defined by the appended claims. Those skilled in the art will recognize or be able to ascertain using no more than routine experimentation, many equivalents to the specific embodiments of the invention described specifically herein. Such equivalents are intended to be encompassed in the scope of the claims.

We claim:

1. A head mounted display device comprising:

- a first matrix display assembly and a second matrix display assembly, each matrix display assembly including a backlight, a matrix display element having a display area with a diagonal length no greater than 1.654 inches and at least 800 lines per inch, the display element generating an image along a first optical path, only one mirror to reflect the image from the respective matrix display element from the first optical path to a second optical path and a viewing lens positioned along the second optical path in a line of sight of a viewer, the first optical path being vertically aligned with the second optical path such that the mirror transposes the image between the first and second optical paths;
- a housing for holding the first matrix display assembly and the second matrix display assembly relative to the head of a display user, the housing having a first aperture through which the user can view the transposed image from the matrix display element of the first matrix display assembly and a second aperture through which the user can view the transposed image from the matrix display element of the second matrix display assembly;
- a mounting frame on which the first matrix display assembly and the second matrix display assembly are mounted such that each matrix display assembly can slide along the mounting frame;
- a headband on which the mounting frame is mounted with a hinge such that the mounting frame can be rotated relative to the headband; and
- a focus adjust mechanism that controls a distance between each matrix display element and the respective lens by varying the length of the optical paths and maintaining

the first optical path of the first matrix display assembly parallel to the first optical path of the second matrix display.

2. The head mounted display device of claim 1 further comprising a second hinge mounted support to mount a pair of audio transducers to the headband.

3. The head mounted display device of claim 1 wherein the matrix display elements are both active matrix liquid crystal displays.

4. The head mounted display device of claim 1 wherein the matrix display elements both comprise active matrix electroluminescent displays.

5. The head mounted display device of claim 1 further comprising a pair of audio transducers.

6. The head mounted display device of claim 1 further comprising a moveable nose bridge mounted to the housing.

7. The head mounted display device of claim 1 wherein the matrix display elements are both passive matrix displays.

8. The head mounted display device of claim 1 further comprising a video control circuit mounted within the display device, the video control circuit transposing a received signal representing a video image.

9. The head mounted display device of claim 8 further comprising a manually adjustable controller mounted on the display device to adjust a control signal delivered by the video control circuit to the matrix display elements.

10. The head mounted display device of claim 1 further comprising a display controller for adjusting a distance between the first and second apertures.

11. The head mounted display device of claim 1 wherein the matrix display is an active matrix liquid crystal display.

12. A head mounted display device comprising;

a matrix display assembly including a backlight, a matrix display element having a display area with a diagonal length no greater than 1.654 inches and at least 800 lines per inch, the display element forming images of a first orientation, only one mirror and a lens, the mirror reflecting the formed images through the lens such that the lens magnifies a reflected image from the display element;

a housing for holding the matrix display assembly relative to the head of a display user, the housing having an aperture through which the user can view images in a second orientation;

a mounting frame on which the matrix display assembly is mounted such that the matrix display assembly can slide along a first axis across the user's field of view relative to the mounting frame; and

a hinge that connects the housing to a headband such that the matrix display assembly can be rotated about a second axis, the second axis being parallel to the first axis.

13. The head mounted display device of claim 12 wherein the matrix display element comprises an active matrix liquid crystal display.

14. The head mounted display device of claim 12 wherein the matrix display element comprises an active matrix electroluminescent display.

15. The head mounted display device of claim 12 further comprising a pair of audio transducers.

16. The head mounted display device of claim 12 further comprising a moveable nose bridge mounted on the housing.

17. The head mounted display device of claim 12 wherein the matrix display element is a passive matrix display.

18. The head mounted display device of claim 12 further comprising a video control circuit mounted within the display device, the video control circuit converting a video image to the first orientation.

19. A head mounted display device comprising:

a matrix display assembly including a backlight, a horizontally oriented matrix display element having a display area with a diagonal length no greater than 1.654 inches and at least 800 lines per inch, only one mirror to reflect light from the display element from a first optical path to a second optical path and a lens positioned along the second optical path, the first optical path being vertically oriented relative to an eye of a user and the second optical path being oriented along the optical axis of the eye of the user such that the lens magnifies a reflected image from the display element;

a housing for holding the matrix display assembly relative to the head of the user, the housing having an aperture through which the user can view the matrix display element;

a mounting frame on which the matrix display assembly is mounted such that the matrix display assembly can slide along the mounting frame;

a headband on which the mounting frame is mounted with a hinge such that the mounting frame can be rotated relative to the headband; and

a focus adjust mechanism that controls a distance between the matrix display element and the lens by movement of the matrix display element in the vertical direction.

20. The head mounted display device of claim 19 wherein the focus adjust mechanism moves the matrix display element in the vertical direction.

21. The head mounted display device of claim 19 wherein the mounting frame includes three longitudinal members to which the matrix display assembly is coupled.

22. The head mount display device of claim 19 wherein the matrix display assembly further includes a diffractive optic element.

23. The head mounted display device of claim 19 wherein the lens has a focal length of about one inch.

24. The head mounted display device of claim 19 wherein matrix display element has an apparent distance from the user of at least about fifteen feet.

25. The head mounted display device of claim 24 wherein the apparent distance is adjustable by the user.

26. A head mounted display device comprising;

a matrix display assembly including a backlight, a matrix display element having a diagonal length no greater than 1.654 inches and having at least 800 lines per inch, the display element forming images of a first orientation, only one mirror and a lens, the mirror reflecting the formed images through the lens such that the lens magnifies a reflected image from the display element;

a housing for holding the matrix display assembly relative to the head of a display user, the housing having an aperture through which the user can view images in a second orientation; and

a mounting frame on which the matrix display assembly is mounted such that the matrix display assembly can slide along a first axis across the user's field of view relative to the mounting frame.

27. The head mounted display device of claim 26 wherein the matrix display element comprises an active matrix liquid crystal display having an active area with a diagonal of 0.820 inches or less.

28. The head mounted display device of claim 26 wherein the matrix display element comprises an active matrix electroluminescent display.

29. The head mounted display device of claim 26 further comprising a pair of audio transducers.

30. The head mounted display device of claim 26 further comprising a moveable nose bridge mounted on the housing.

31. The head mounted display device of claim 26 wherein the matrix display element is a passive matrix display.

32. The head mounted display device of claim 26 further comprising a video control circuit mounted within the display device, the video control circuit converting a video image to the first orientation.

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